

**ROCHESTER INSTITUTE OF TECHNOLOGY
MICROELECTRONIC ENGINEERING**

RIT Factory CMOS Electrical Test

Dr. Lynn Fuller and David Pawlik

Webpage: <http://www.rit.edu/~lffeee>

Microelectronic Engineering

Rochester Institute of Technology

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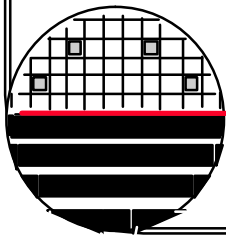
Rochester, NY 14623-5604

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MicroE Webpage: <http://www.microe.rit.edu>

Revision Date: CMOSTEST_Manual.ppt 12-15-08

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INTRODUCTION

■ Motivation

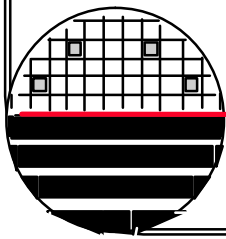
- Most students taking Factory class are not yet familiar with the test equipment used in the test lab.

■ Goal

- Create a PowerPoint Manual, and electrical tests, so that most people will be able to easily perform the electrical tests, and extract the necessary data.

■ Assumptions

- Operator has a base knowledge of:
 - 1) The electrical tests being done
 - 2) How to extract necessary information from the generated curves.



TEST EQUIPMENT



Semi-automatic Prober

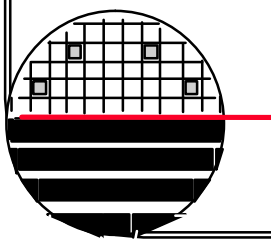
Automatic Prober



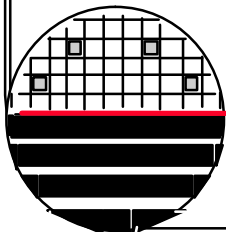
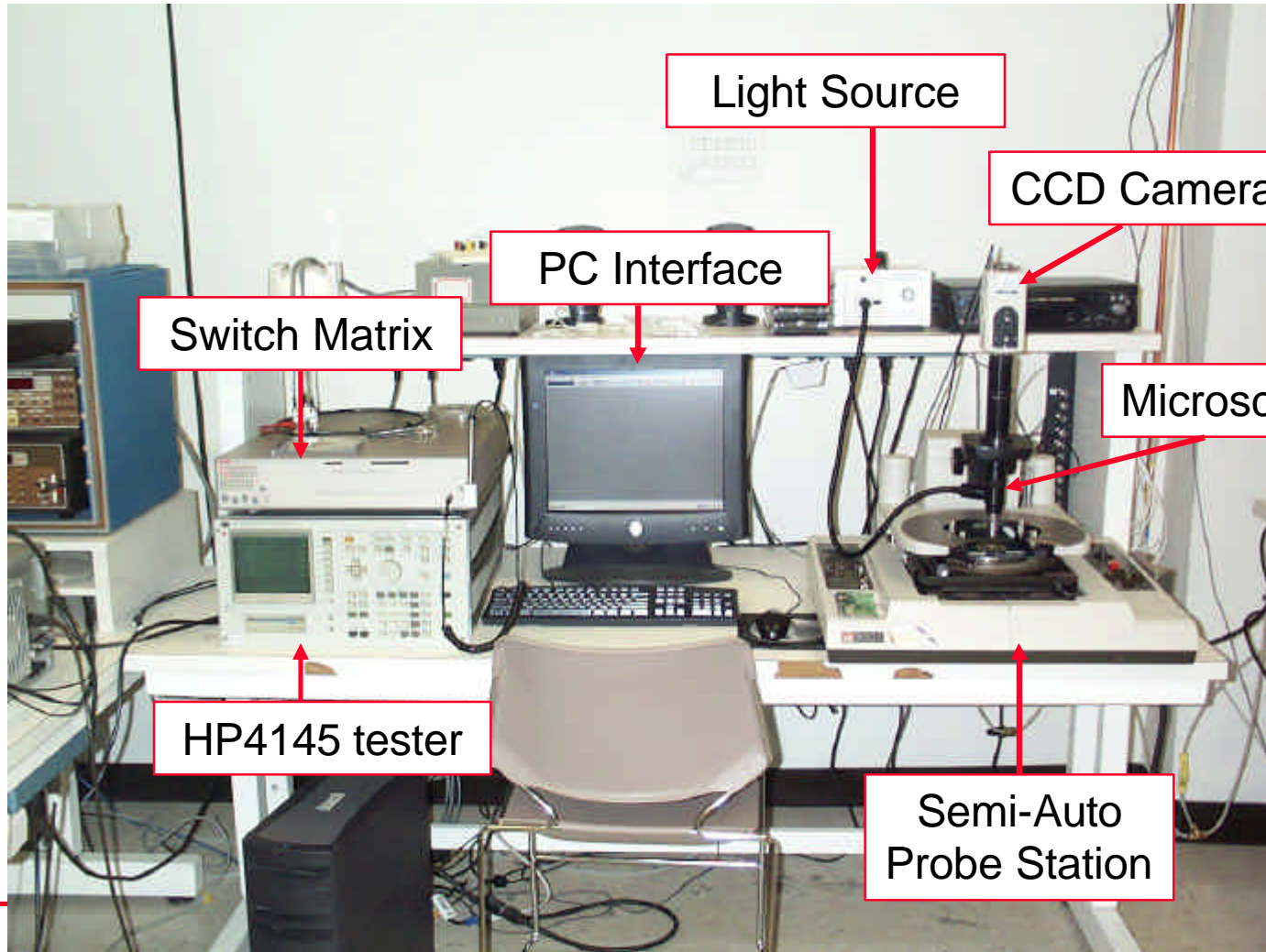
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TEST EQUIPMENT

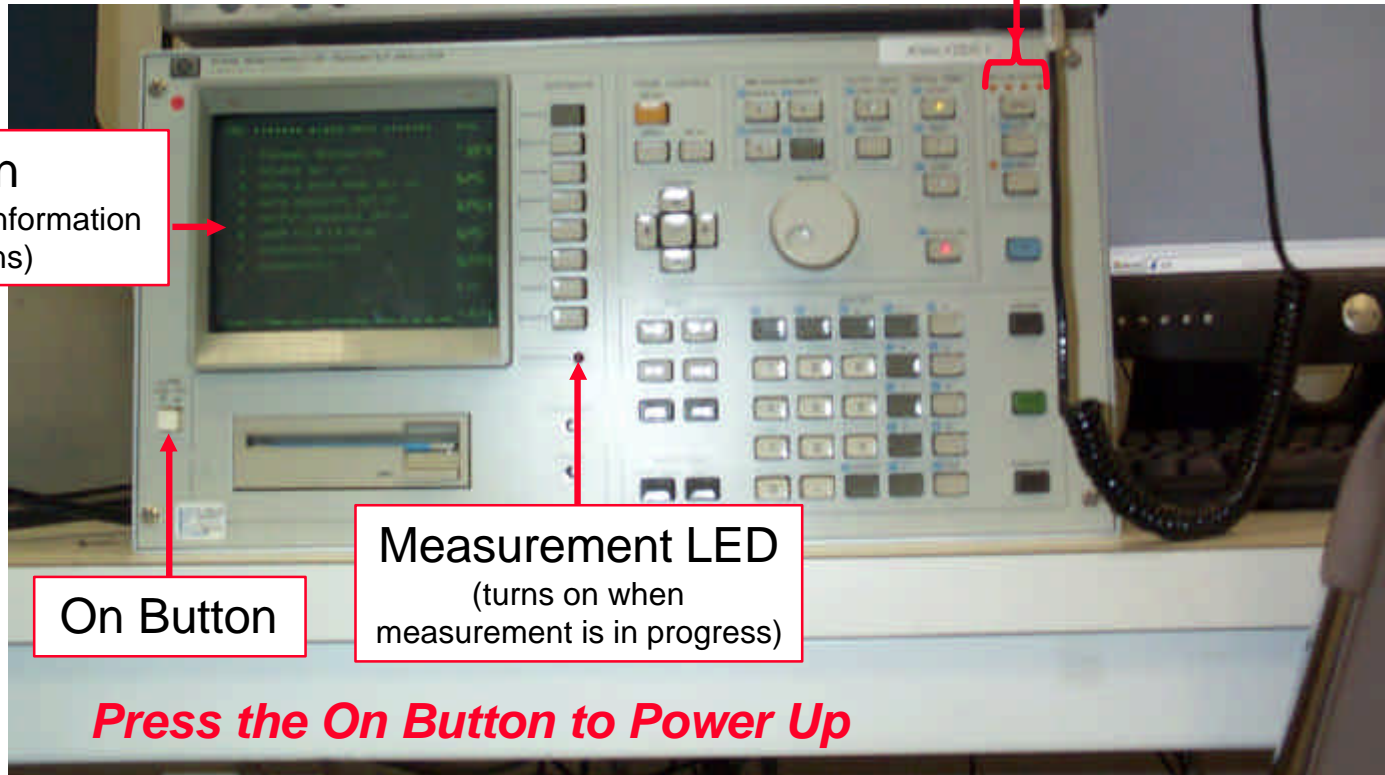
Manual Prober



TEST STATION



HP4145 – PRESS THE ON BUTTON TO POWER UP



Screen

(Displays useful information and options)

On Button

Measurement LED

(turns on when measurement is in progress)

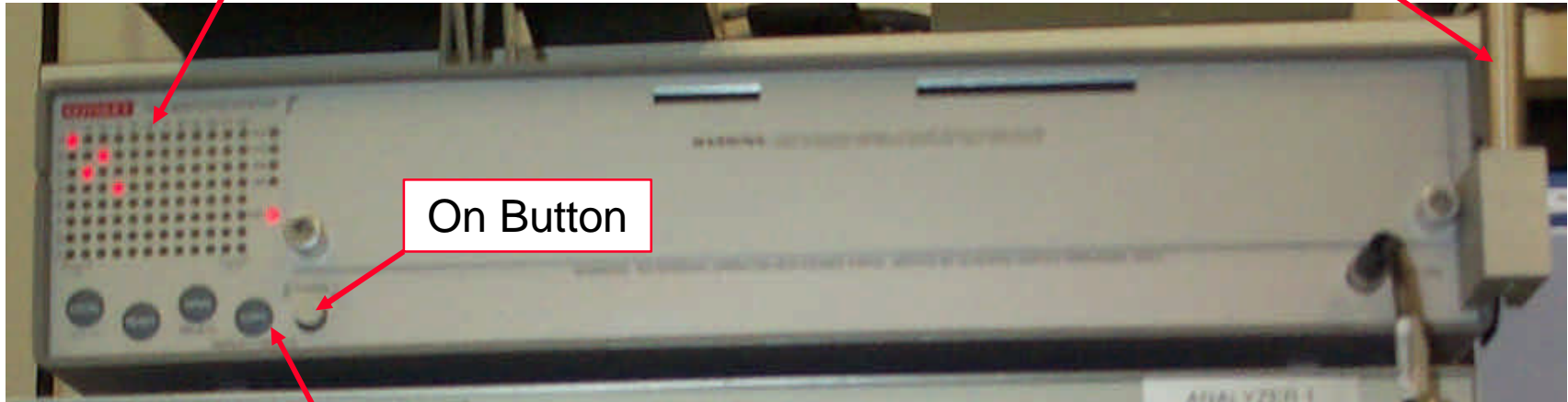
Data Transfer & Standby LED's

Press the On Button to Power Up

SWITCH MATRIX - PRESS THE ON BUTTON TO POWER UP

Switch Matrix
Indicator

Light Pen



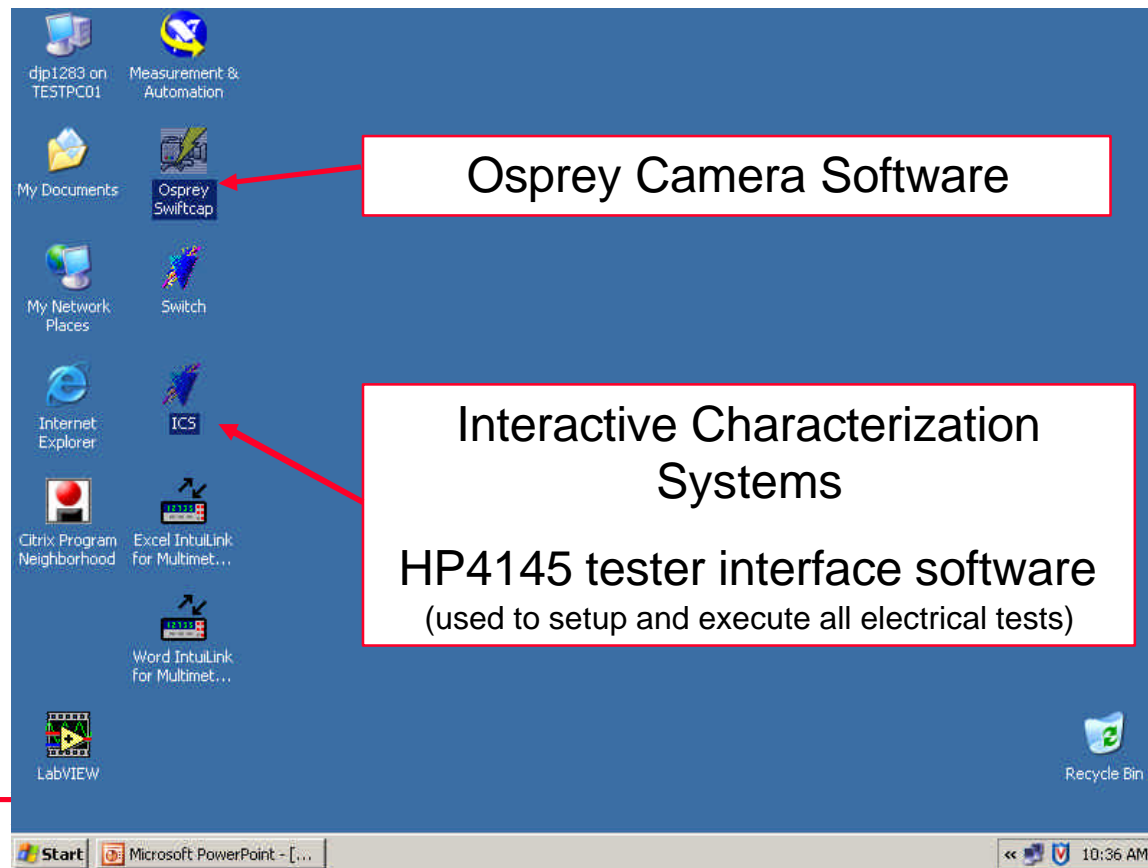
On Button

Copy Button

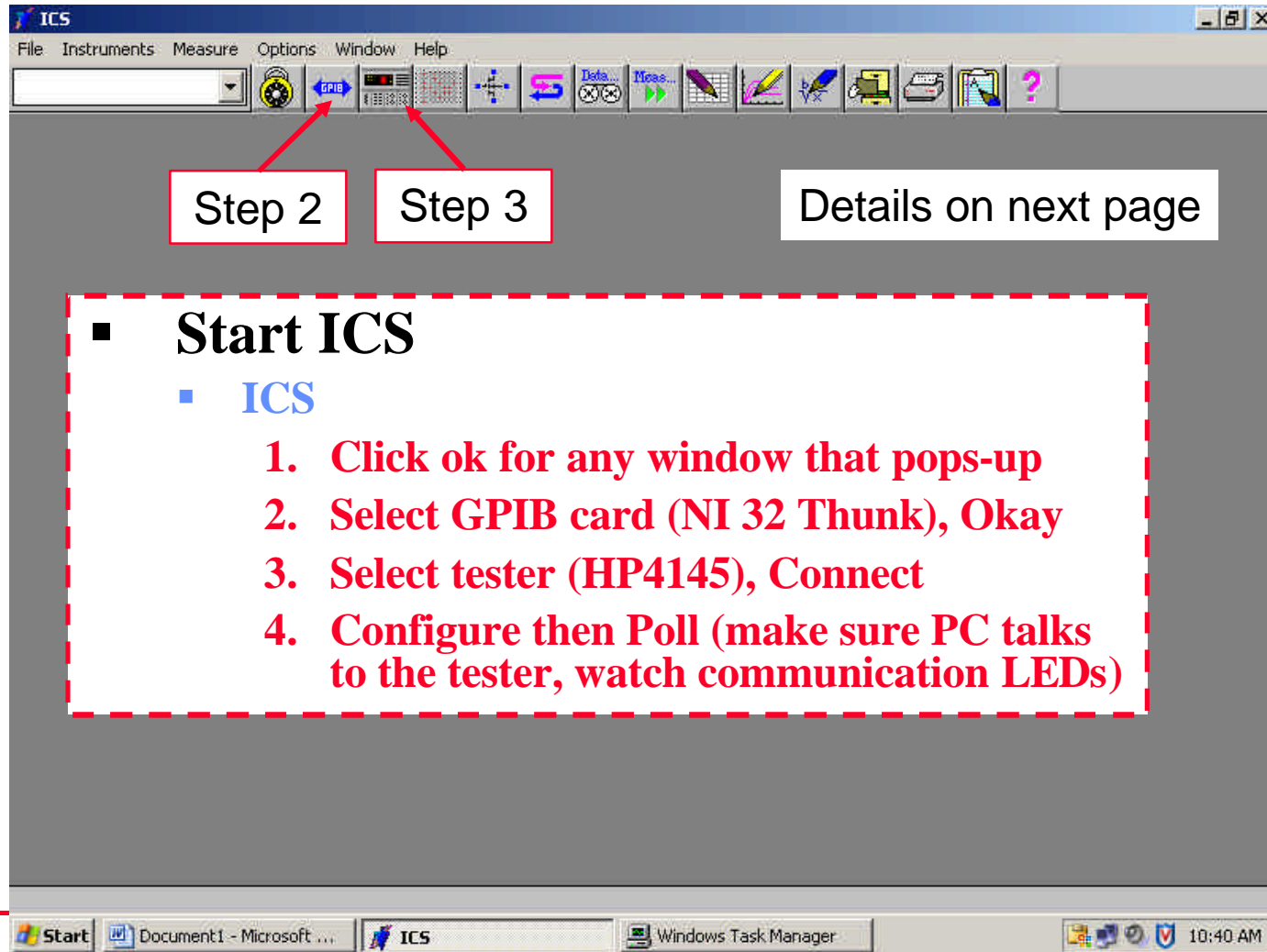
Press the On Button to Power Up

PC DESKTOP

- Log onto PC, locate the two icons shown below, Double click on ICS icon



ICS SETUP



The screenshot shows the ICS software window with a menu bar (File, Instruments, Measure, Options, Window, Help) and a toolbar. Two red arrows point from text boxes to the 'GPIB' and 'Measure' icons in the toolbar. A third text box points to the right side of the window.

Step 2

Step 3

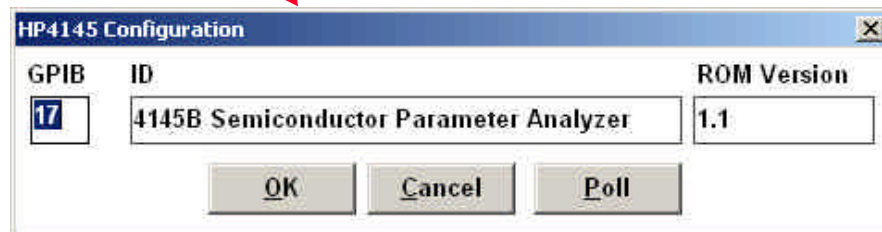
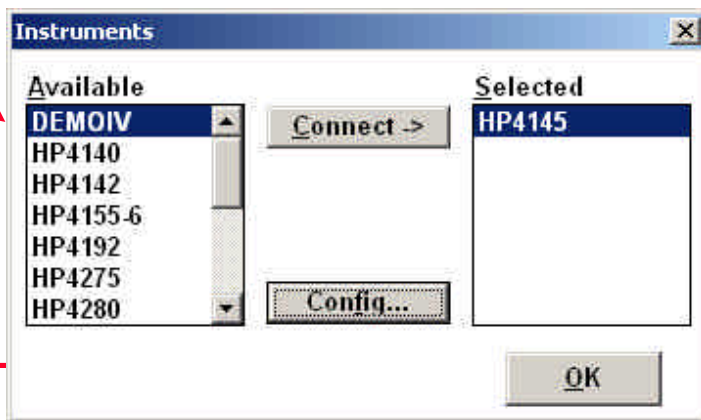
Details on next page

- **Start ICS**
 - ICS
 1. Click ok for any window that pops-up
 2. Select GPIB card (NI 32 Thunk), Okay
 3. Select tester (HP4145), Connect
 4. Configure then Poll (make sure PC talks to the tester, watch communication LEDs)

ICS SETUP DETAILS

ICS Setup

1. Select GPIB card (NI 32 Thunk)
2. Select tester (HP41545)
3. click Config... button on the Instruments window then Poll



ICS LOAD ELECTRICAL TESTS

The screenshot shows the ICS software window with a menu bar (File, Instruments, Measure, Options, Window, Help) and a toolbar. A red dashed box is overlaid on the main workspace, containing a list of instructions. The taskbar at the bottom shows the Start button, the ICS application icon, and the system tray with the time 9:52 AM.

- **Load electrical tests**
 1. **Download ICS_Test_Setups.dat file from Dr. Fuller's webpage:**
<http://www.rit.edu/~lffeee/labnotes.htm>
 2. **Right Click, Save As, Save to desktop**
Location highest level, then [docume~1], then [your username], then [desktop]
 3. **In ICS Click File → Import**
 4. **Navigate to the desktop**
C:/documn~1/username/desktop
 5. **Open "FAC_SUB.dat"**

LIST OF ELECTRICAL TESTS

Test Name	Description	Parameters to be extracted	Units
VDP-POLY	Poly Van Der Pauw	Poly Sheet Resistance	ohms/square
VDP-MET	Metal Van Der Pauw	Metal Sheet Resistance	ohms/square
VDP-N	N+ Van Der Pauw	N+ Sheet Resistance	ohms/square
VDP-P	P+ Van Der Pauw	P+ Sheet Resistance	ohms/square
VDP-PWELL	P-well Van Der Pauw	P-Well Sheet Resistance	ohms/square
CBKR-N	CBKR Metal to N+ silicon	Specific Contact Conductance for metal to N+ silicon	mmho/ μm^2
CBKR-P	CBKR Metal to P+ silicon	Specific Contact Conductance for metal to P+ silicon	mmho/ μm^2
CBKR-POLY	CBKR Metal to Poly	Specific Contact Conductance for metal to Poly	mmho/ μm^2
NFAM	NMOS Family of Curves	Lambda	1/Volts
NVT	NMOS ID - Vgs	Max gm Vtn	mho/ μm of channel width Volts
NSUB	NMOS Sub Threshold ID-Vgs	Sub Threshold Slope Imax/Imin	mV/decade # of decades
PFAM	PMOS Family of Curves	Lambda	1/Volts
PVT	PMOS ID - Vgs	Max gm Vtn	mho/ μm of channel width Volts
PSUB	PMOS Sub Threshold ID-Vgs	Sub Threshold Slope Imax/Imin	mV/decade # of decades
NFIELD	NMOS Family of Curves	N Well Field Vt	Volts
PFIELD	PMOS Family of Curves	P Well Field Vt	Volts
INV	Inverter Vout versus Vin	Imax Vinv, Voh, Vol, Vih, Vil	Amps Volts

ICS – SELECTING AND RUNNING A TEST

The screenshot shows the ICS software interface. The main window is titled "Measure" and has a menu bar with "File", "Instruments", "Measure", "Options", "Window", and "Help". The toolbar contains various icons, with the "Measure" button (8th from the left) highlighted by a red box and labeled "Measure button". The "Measure" window is open, showing a dropdown menu for "NMOS_IDVD" and a "Test selector" dropdown menu. The "Test selector" dropdown menu is open, showing a list of test types: PFAM, NVT, PVT, NSUB, PSUB, NFAM, VDP-POLY, VDP-METAL, etc., CBKR-N, CBKR-P, CBKR-POLY, INV, FIELD_NMOS_VT, and FIELD_PMOS_VT. The "Single" button in the "Measure" window is highlighted by a red box and labeled "Run Single".

Test selector

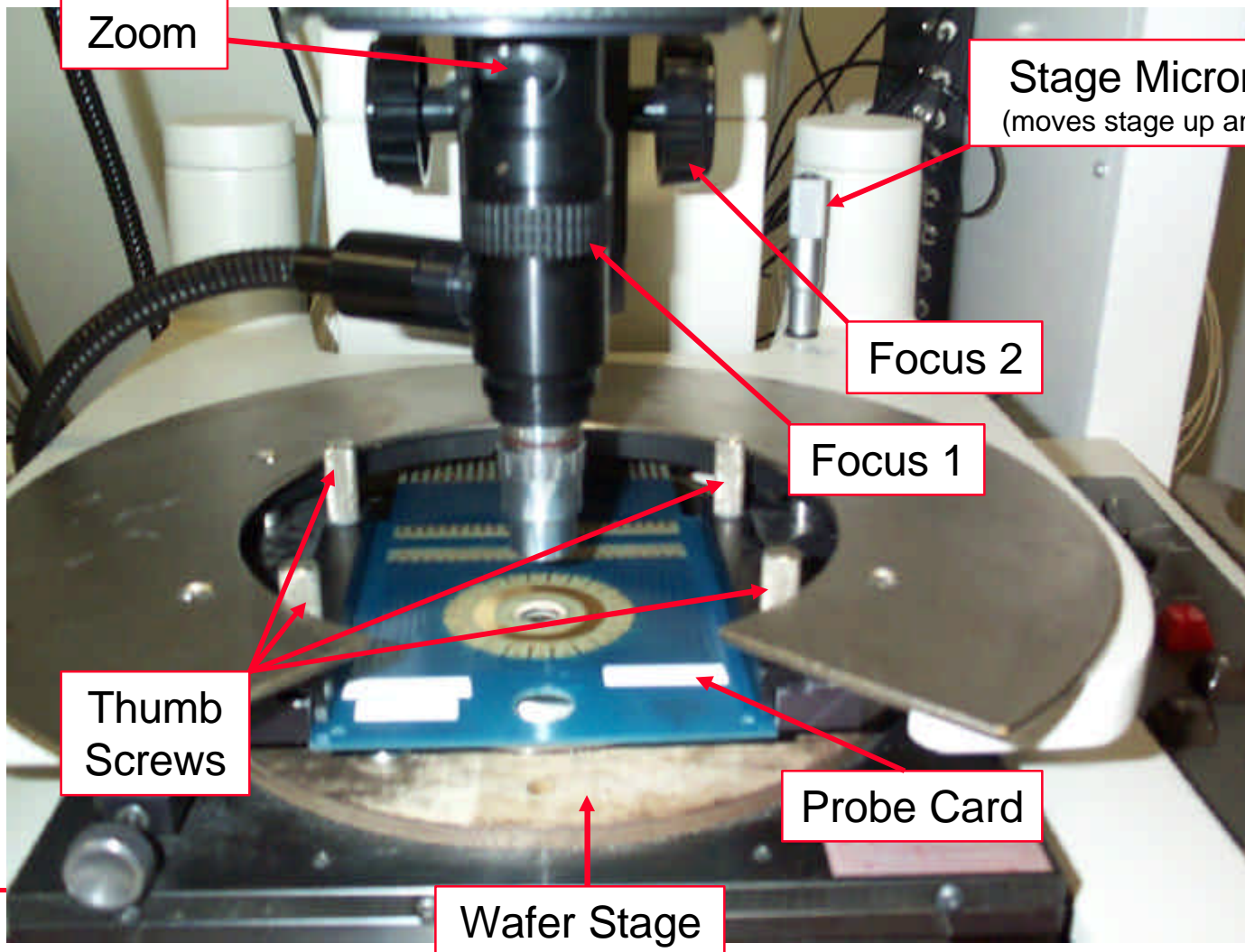
“Measure” button

Run Single

■ **Display the “Measure” window**

1. Click the Measure button (8th from the left)
2. Use drop-down box to select a test
 - PFAM
 - NVT
 - PVT
 - NSUB
 - PSUB
 - NFAM
 - VDP-POLY, VDP-METAL, etc.
 - CBKR-N, CBKR-P, CBKR-POLY
 - INV
 - FIELD_NMOS_VT
 - FIELD_PMOS_VT
3. Click the “Single” button to run the selected electrical test

PROBE STATION – SHOULD ALWAYS BE POWERED ON



INSERTING PROBE CARD

- **Choose Probe Card**
 - There are 2 types: 1) 10 pin card, & 2) 12 pin card
 - Sub-CMOS: 10 pin probe card
 - DAC lots: 12 pin probe card
 - Adv-CMOS: 10 pin probe card
- **Probe Card Slot**
 - Remove Probe Card (If one is in the probe station already)
 1. Twist Micrometer “up” (couple turns)
 2. Loosen 4 thumb screws
 3. Remove card
 - Insert Desired Probe Card
 1. Push card into the slot
 2. Tighten 4 thumb screws



Probe Card

PROBE STATION – SHOULD ALWAYS BE POWERED ON

Y-Axis & X-Axis
indexing distances

Home &
Load/Center
Buttons

Probes
Up/Down

Vacuum
On/Off

Thumb
Screws

Wafer Stage

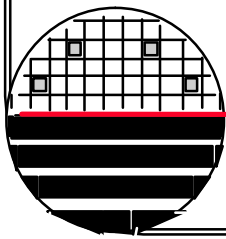
Index/Jog
toggle
Switch

Stage Movement

Probe Card

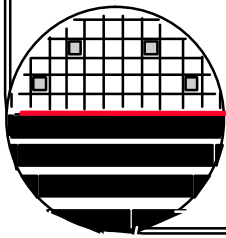
Index: move
the stage a
large distance
indicated by
the user .

Jogg: moves
the stage a
small distance.



LOAD WAFER

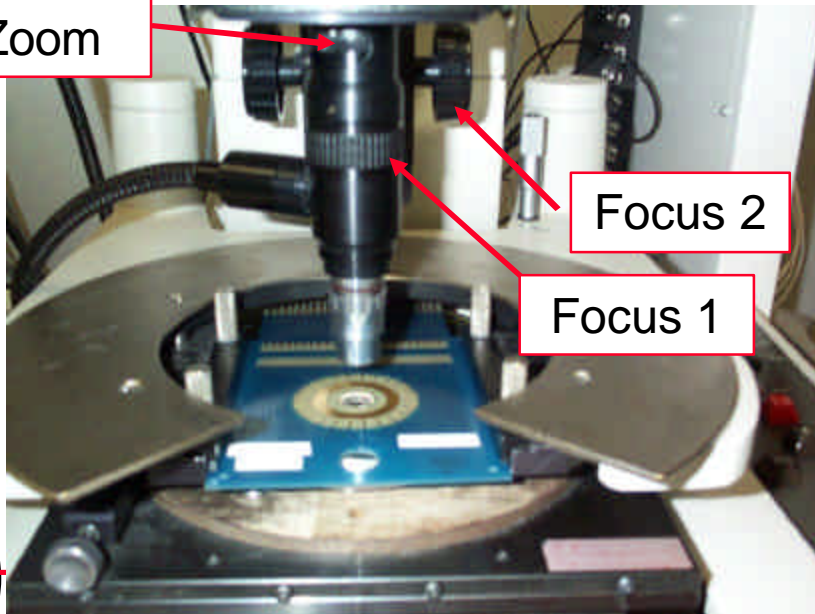
- **Move Stage to the Load Position**
 - Press the “Load/Center” button (moves stage out)
- **Load the Wafer**
 - Make sure the vacuum switch is turned off
 - Load the wafer onto the center of the chuck
 - **Wafer flat towards front of the tool**
 - Turn on the vacuum
 - Press the “Home” button
 - Wafer is loaded and ready for viewing using Osprey



OSPREY – VIDEO IMAGING SETUP

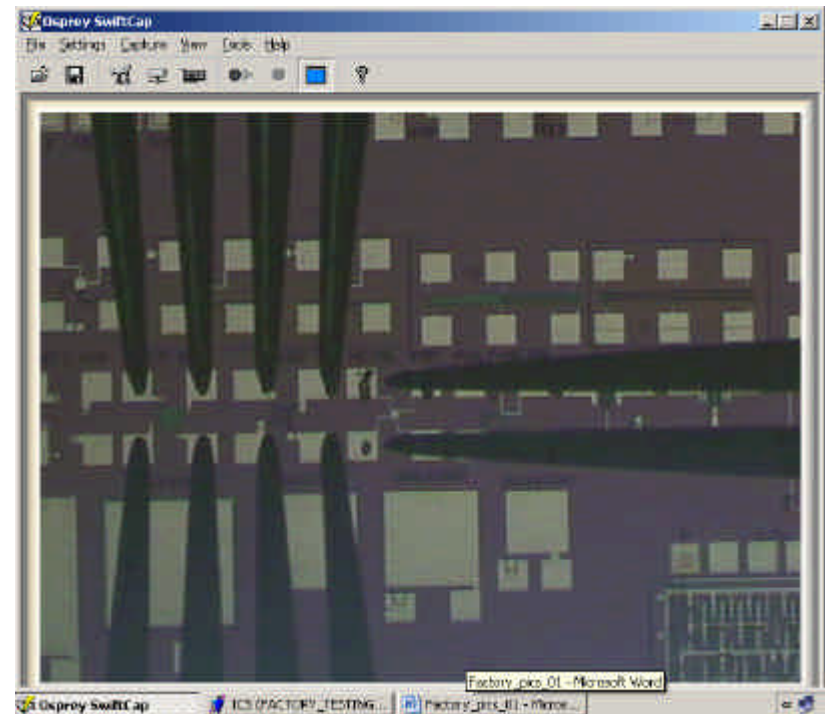
- **Turn the Light on**
 - Turn the dial on the light source clockwise until optimal brightness is achieved
- **Start Osprey Software on your Desktop**
 - Click “close” on the window that pops-up.
 - Second window is a video image of the microscope imaging.
 - Window cannot be resized but magnification (zoom) can be changed
- **Adjust zoom and focus**

Zoom



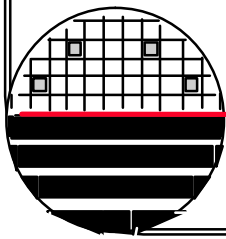
Focus 2

Focus 1

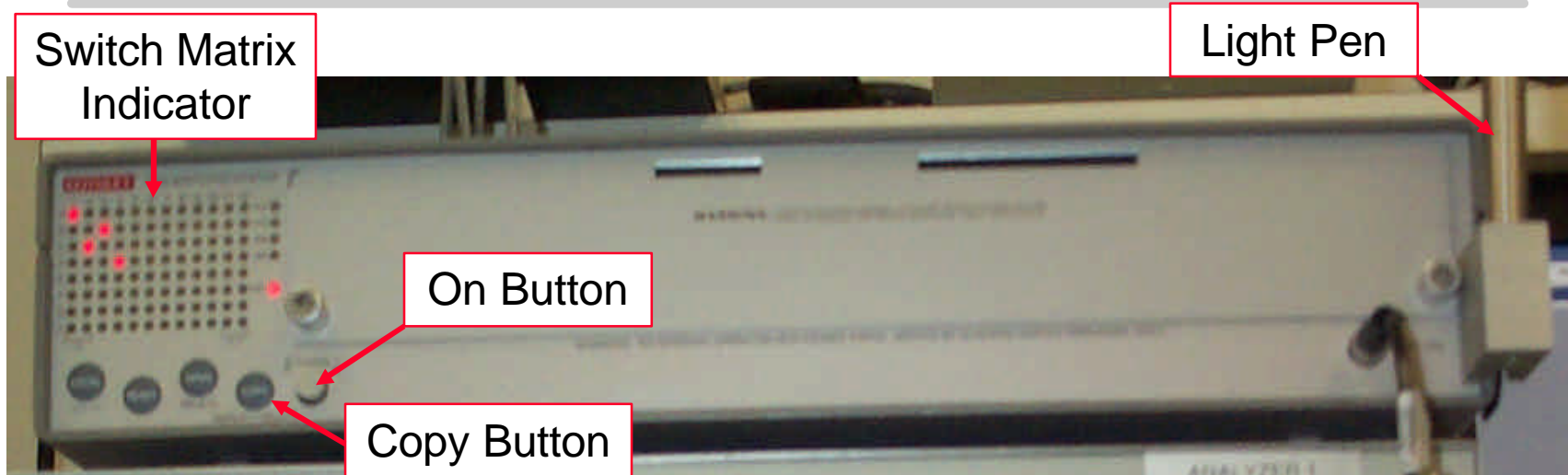


SETUP STAGE HIGHT

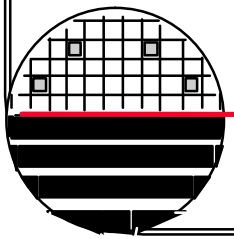
- **Maneuver probes over empty street**
 1. Set Index/Jog switch to Jog
 2. Use arrow buttons appropriately
 3. Stop when over street (empty space between die)
- **Make probes contact Aluminum in the street**
 1. Toggle Probes down (set separate/contact switch to contact)
 2. Use micrometer to move probe card down
 3. When probes slide (very small amount) stop moving micrometer
 4. Toggle probes up (separate)
 5. Move station small amount, and look for probe marks
 - **Black marks where the probes scratched the aluminum**
 - **Marks should be small elongated dots (Ex.)**
 6. Repeat As needed (move micrometer up if needed)



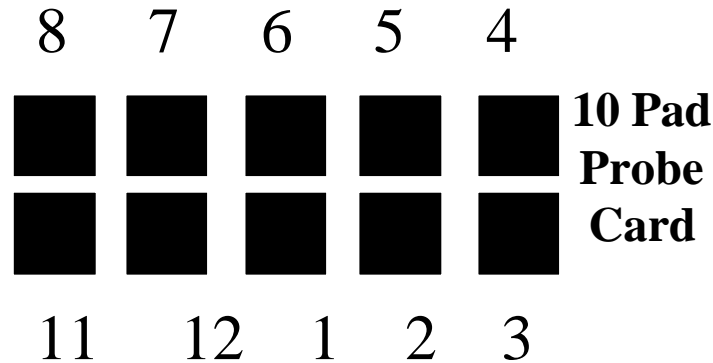
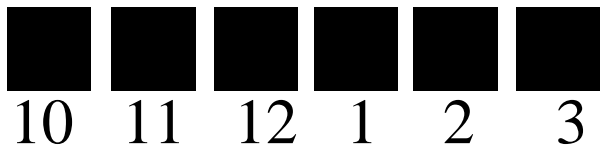
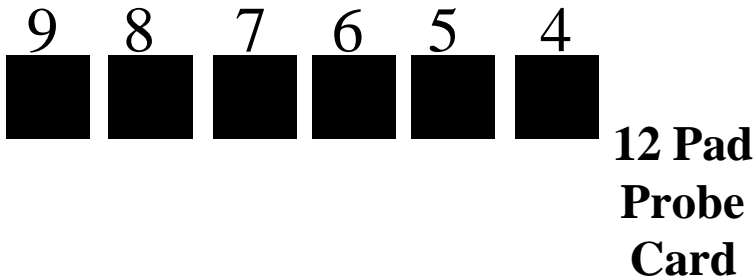
SWITCH MATRIX



- **Turn on Switch Matrix (should be on from page 5)**
- **Use Light wand to activate different switches**
 - Point wand at a circle on the indicator.
 - Push button on the light wand.
 - LED should toggle on and off.
 - Columns indicate pin number on the probe card.
 - Rows indicate SMU number (A = SMU 1, B = SMU 2, etc.).
- **Push the Copy Button.**
 - Activates the appropriate switches (LED is on) so that indicated probe pins and SMUs are connected.
 - Leave this button turned on.



STANDARD PROBE CARDS



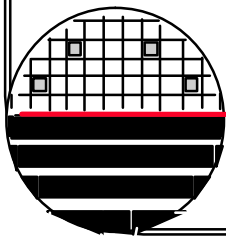
Wafer Chuck



1 2 3 4

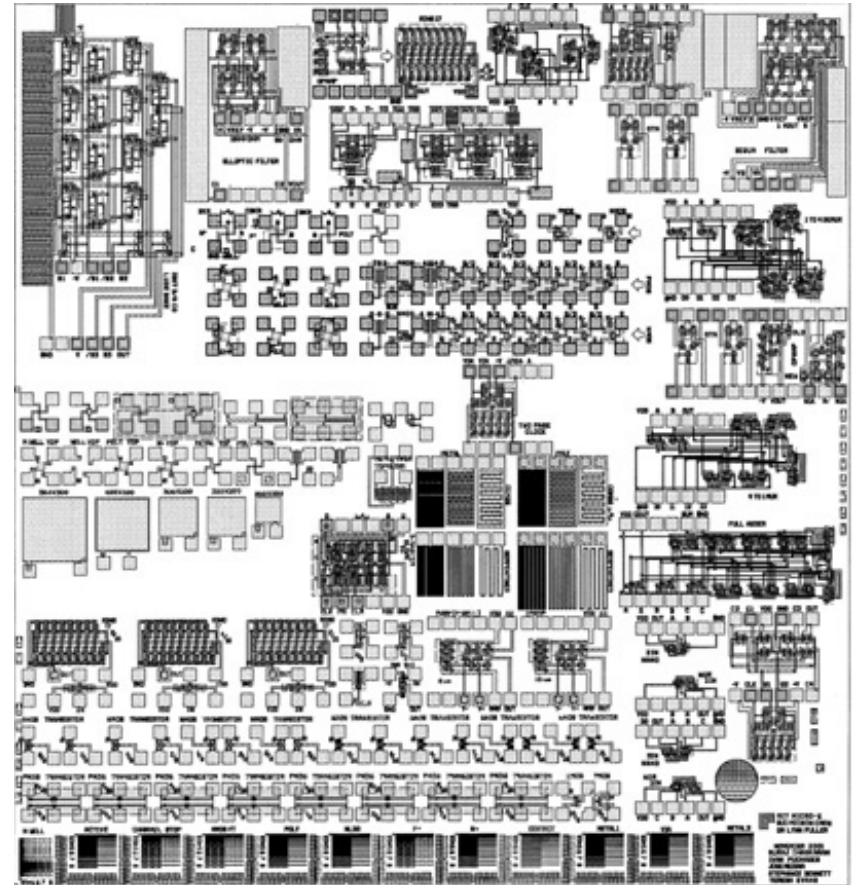
HP 4145 Test Fixture

Numbers indicate switch matrix column



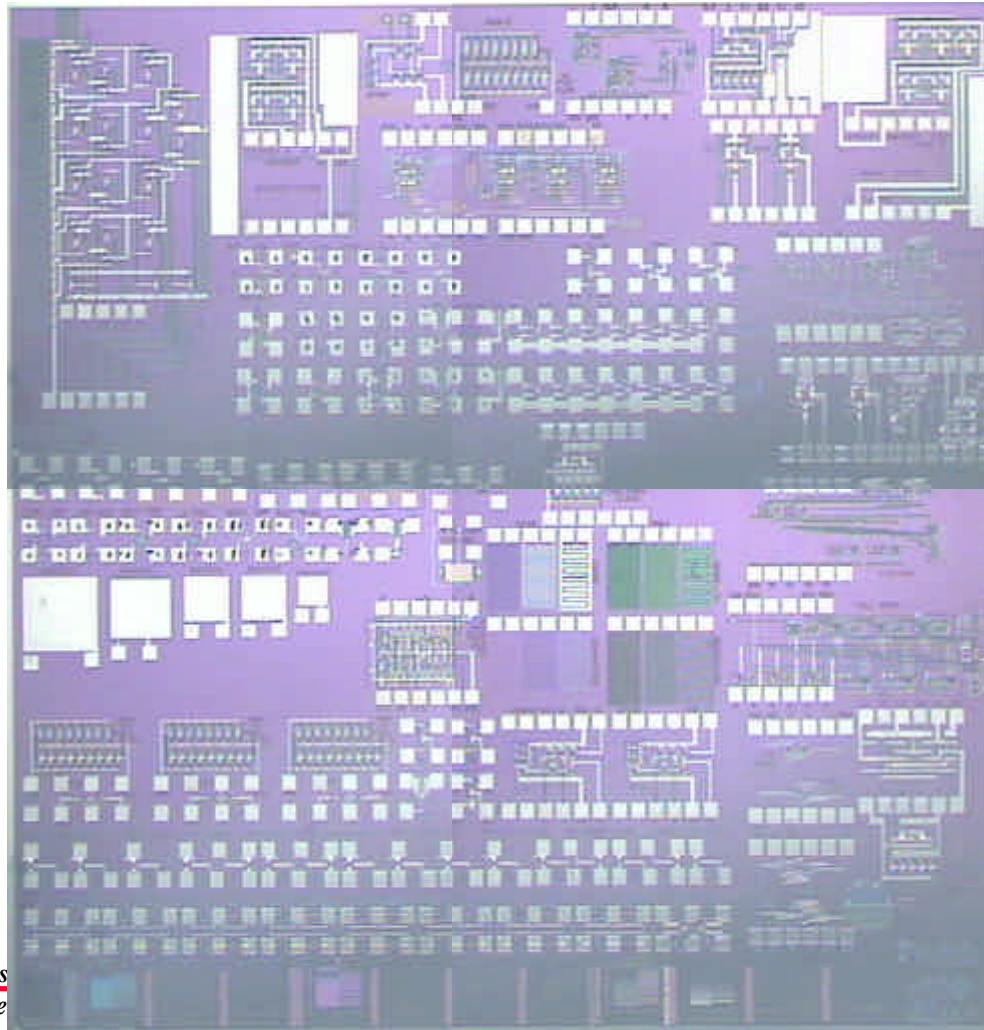
SUB-CMOS MIXED CMOS TEST CHIP

Layout of CMOS test chip for microelectronic engineering manufacturing courses. This chip has transistors down to $0.5\ \mu\text{m}$ gate length, a variety of test structures, digital and analog circuit building blocks including A-to-D and D-to-A converters, operational amplifiers, transconductance amplifiers, and filters of various types.

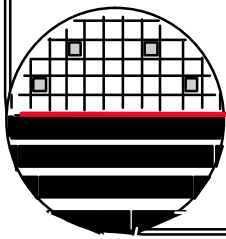


Dr. Lynn Fuller, Lisa Bonanno 2003

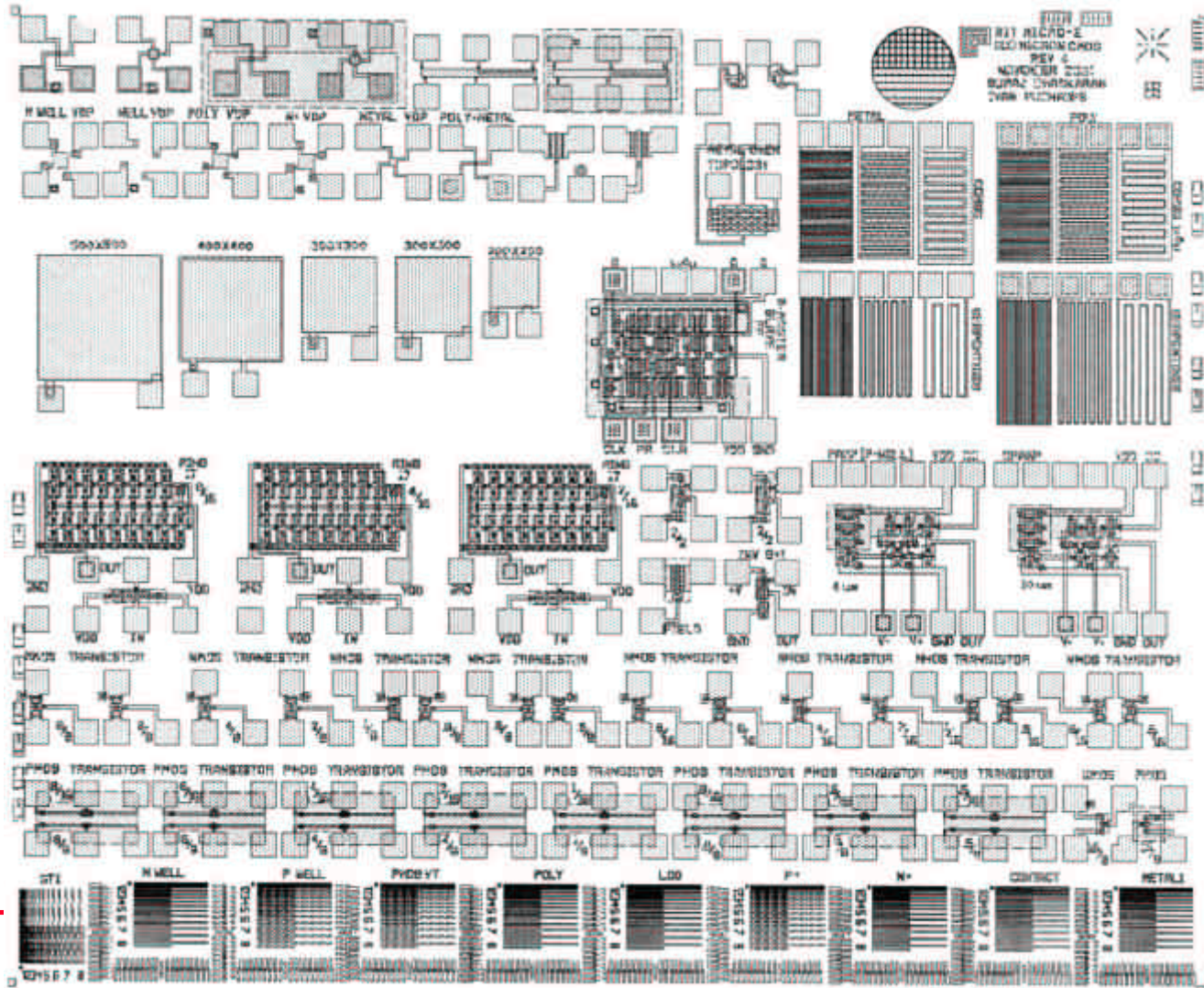
SUB-CMOS Die Photograph



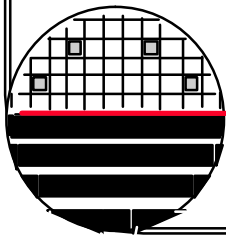
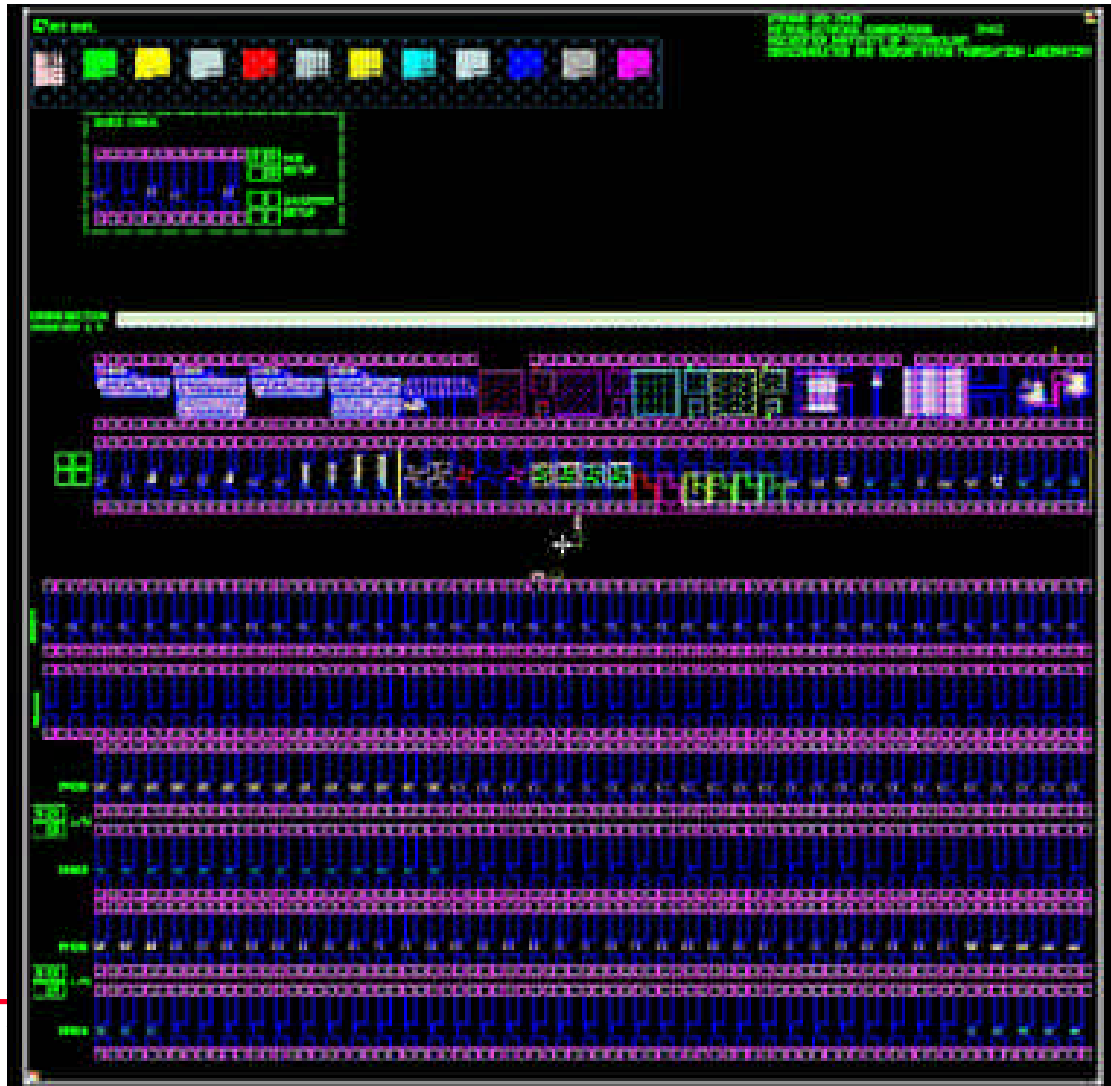
*Roches
Microe*



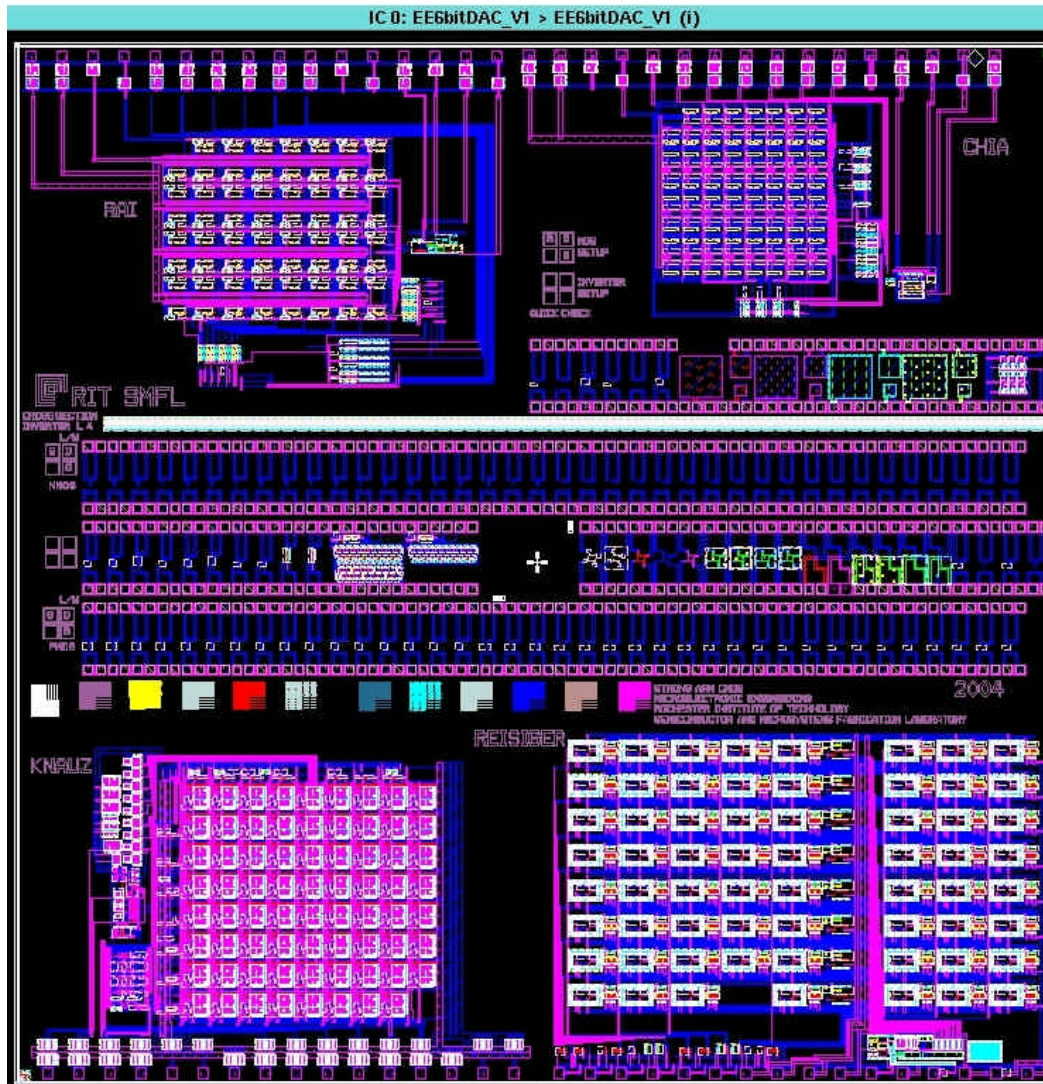
ADVANCED CMOS TEST CHIP



SPICE PARAMETRIC CMOS TEST CHIP



DAC 2003 PROJECT CHIP



GENERAL TEST INSTRUCTIONS

Test die in the center of the wafer, then upper left, upper right, lower right, and lower left (about $\frac{1}{2}$ way between center and edge).
Extract parameter values from the test results.

Create a PowerPoint document from **test_results.ppt** master (see example data powerpoint a few pages below) on Dr. Fullers webpage at <http://www.rit.edu/~lffeee/labnotes.htm> (save as) record Lot#, Wafer#, Die location (center, top left, etc), pictures of die, test results graphs, extracted parameters and comments. Email to Dr. Fuller at lffeee@rit.edu

- Test 01 – Van Der Pauw and CBKR. Record Average of five tests
- Test 02 – Transistors, test small transistors ($L=2\mu\text{m}$ for SMFL, $L=1\mu\text{m}$ for Sub-CMOS and Adv-CMOS). Record results in power point document.
- Test 03 – Inverters, Ring Oscillator. Record Average of five tests.
- Test 04 – NMOS VT wafer map

GENERAL TEST INSTRUCTIONS

Substrate or Well Connections: Most of the test structures incorporate diffusions. In Resistors, Van der Pauw's and Transistors the junctions between the diffusions and the substrate/wells are normally never forward biased. As a result the test engineer needs to evaluate the applied test voltages and connections to the substrate/wells and connections to the diffusions to ensure proper bias conditions.

For example: a P+ Van der Pauw in an N-type Well requires that the Well connection always have the highest positive voltage that is applied. If a separate (5th pad) connection is available (not often because there are only 4 SMU's) that can be set to a high voltage. Otherwise the substrate is normally connected to one of the four pads of the Van der Pauw. This pad can be swept with positive voltage thus keeping the substrate/well junction reverse biased.

GENERAL TEST INSTRUCTIONS

Each test requires you to:

1. Find the structure you want to test
2. Place the probes
3. Open the test by restoring the “testname”-1 (example PFAM-1) in ICS, view the test setup to see what SMU’s do what.
4. Set the switch matrix for the HP4145 SMU’s to the probes you are using, consistent with the test setup.
5. Edit the graph by making changes in the title, moving the cursors to the correct location
6. Copy the plot using ctrl print screen, (paste into word, copy from word to power point, crop and paste in correct location)
7. Extract the data, such as threshold voltage or LAMBDA and enter the value in the data table in the powerpoint
8. Save the powerpoint, minimize the data plot on ICS
9. When done email the powerpoint to Lynn.Fuller@rit.edu

TE01 Van Der Pauw and CBKR

5/04/06

8:31:04

MESA

Instruction Group Inquiry

IGMSINQ

S36801

QPADEV000W

RIT

Type information. Then Enter.

1=Display document, 5=Display detail

Plant : RIT
 Instruction group . . : SUB-CMOS-TE01 TEST COMPLETED WAFERS
 Revision : 150

Opt	Subgroup	Text
		1.0 Test Resistive Devices
—		2.0 Test Van Der Paw for Poly, Metal, n+/p+ Diffusion, Well
—		3.0 Cross Bridge Kelvin Structures for contact resistance
—		4.0 Via chain yes/no test (enter yes if via chain is good)
—		5.0 See SPC chart for PolySi Resistance(PolySRes.pps)
—		6.0 See SPC chart for NRRHOS (NTRHOS.pps)
—		7.0 See SPC chart for WellRes (WellRes.pps)
—		8.0 See SPC chart for PTRHOS (PTRHOS.pps)
—		9.0 Record Rhos(poly, metal, p+, n+, well)
—		Gc(metal-to-poly)mhos-sq um, Gc(metal-to-p+)mhos-sq um

Bottom

F3=Exit

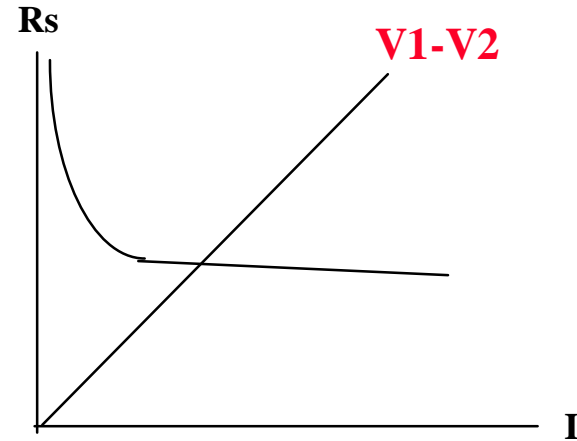
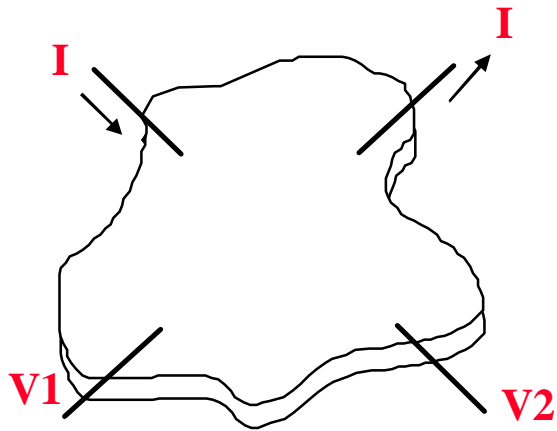
F4=Prompt

F5=Refresh

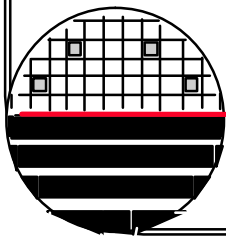
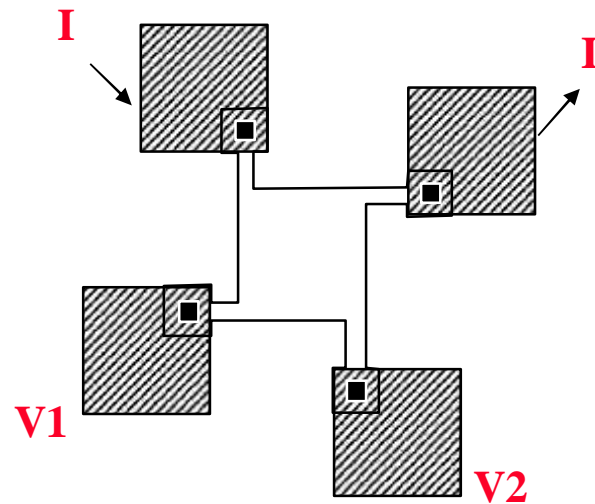
F10=View 2

F12=Cancel

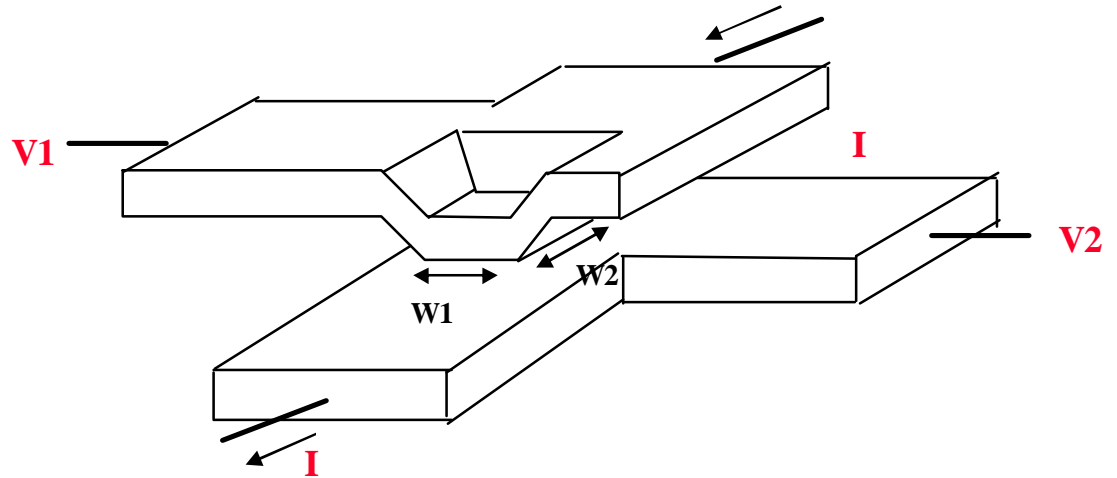
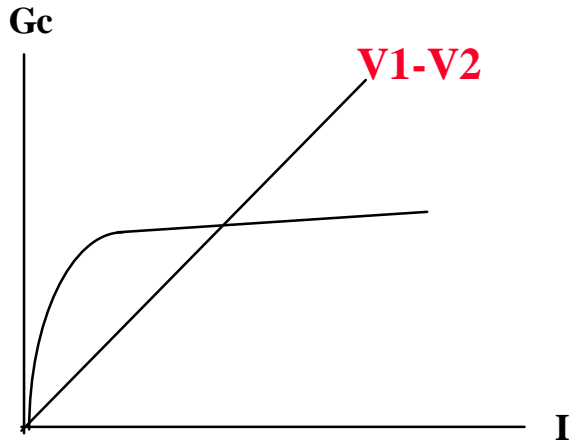
VAN DER PAUW TEST STRUCTURES FOR SHEET RESISTANCE



$$R_s = \frac{(V1-V2) P}{I \ln 2}$$

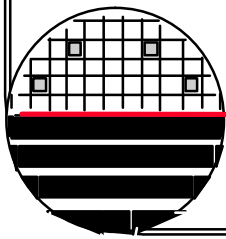


**CROSS BRIDGE KELVIN RESISTANCE TEST
STRUCTURES FOR CONTACT RESISTANCES**

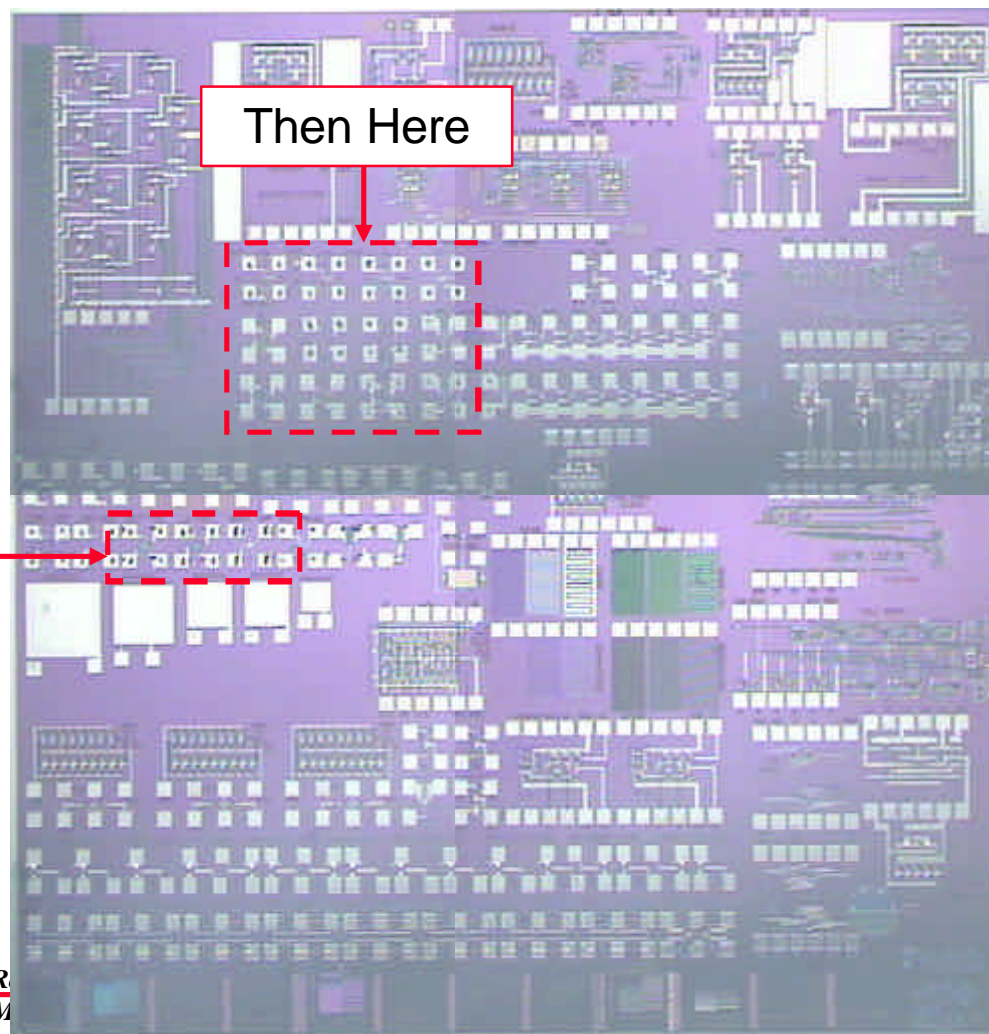


$$R_c = \frac{(V1-V2)}{I} \quad \text{ohms}$$

$$G_c = \frac{I}{(V1-V2)} = \frac{1}{W1 \times W2} \quad \text{mhos}/\mu\text{m}^2$$

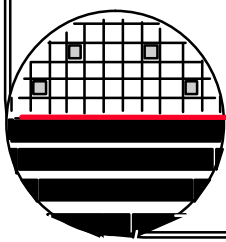


TE01 Test Structures for SUB-CMOS Process MIXED Product



Then Here

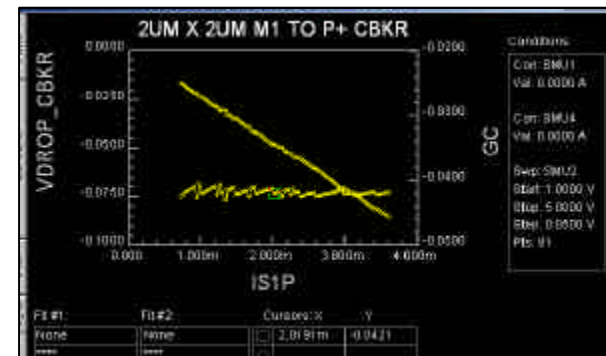
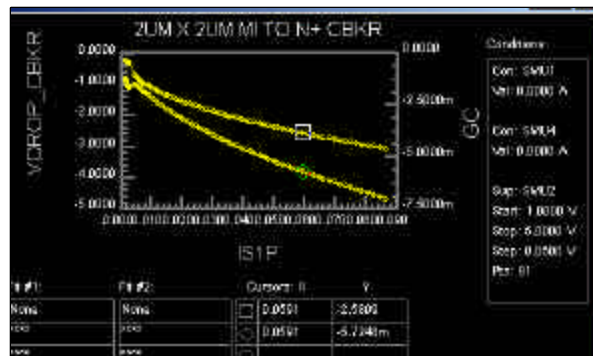
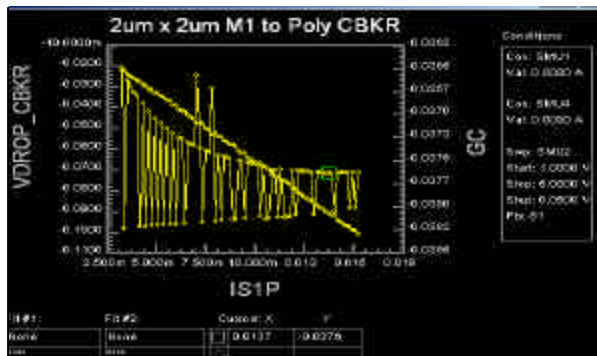
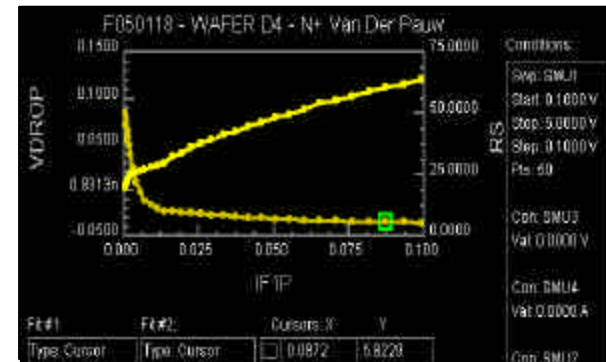
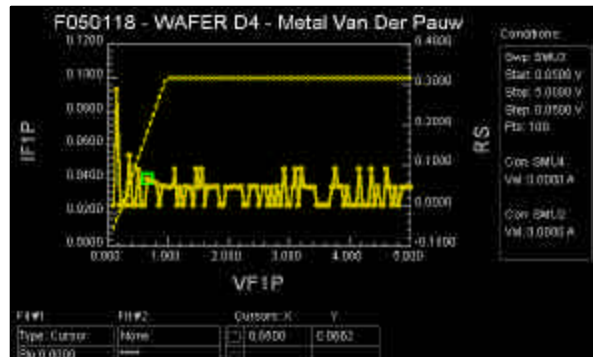
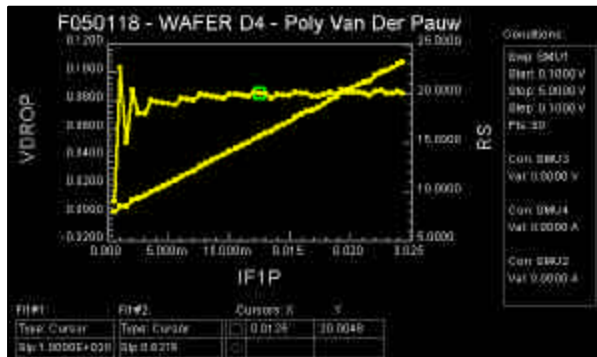
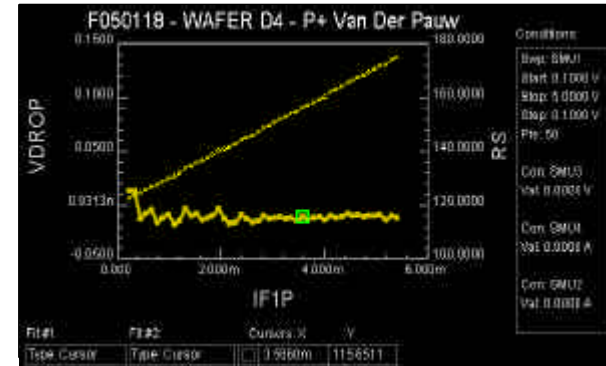
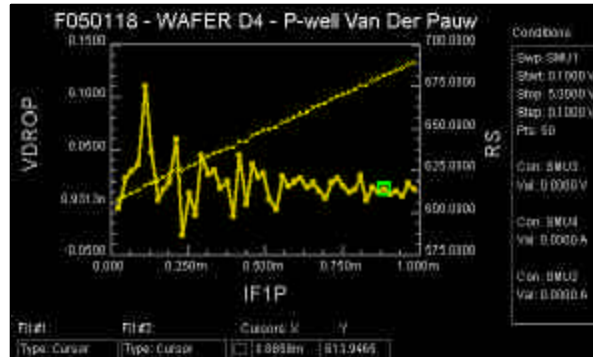
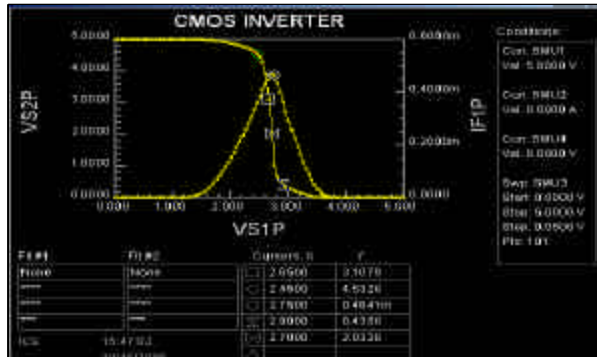
Start Here



R
M

INVERTERS, VAN DER PAUW AND CBKR

Lot Number = F050118 – Wafer Number = D4 , Die Location R= , C=



EXTRACTED PARAMETERS FROM INVERTERS, VAN DER PAUW AND CBKR

Lot Number = F050118 – Wafer Number = D4 , Die Location R= , C=

Contact Gs	CBKR	
P+	42	mmho/ μm^2
N+	8	mmho/ μm^2
poly	37	mmho/ μm^2

	Ring Oscillator	Vdd=5V
# Stages	73	
Period	104	nsec
td	0.712	nsec

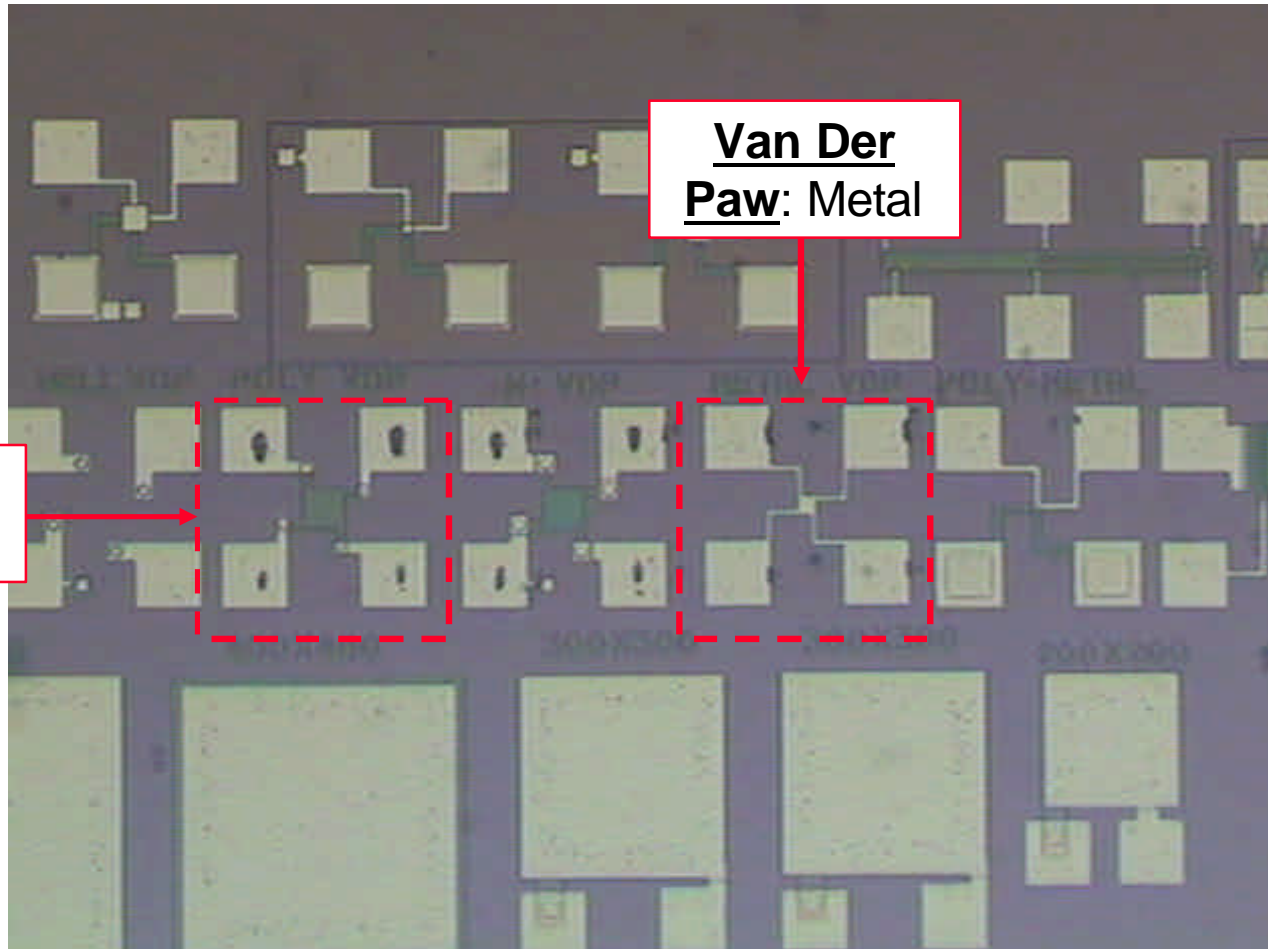
Rhos	Van der Pauw	
P+	115	Ohms
N+	5.8	Ohms
well	614	Ohms
Poly	20.0	Ohms
Al	0.0662	Ohms

	Inverter	
VinL	2.4	V
VinH	3	V
VoL	0.4	V
VoH	4.5	V
Vinv	2.6	V
Imax	4.5	mA
Gain	-21.5	
D0=ViL-VoL	2.0	V
D1=VoH-ViH	1.5	V

	OpAmp	
Gain	None	
Offset	None	mVolts
GBW	None	Hz

	VIA CHAIN	
M1-P+	None	ohms
M1-M2	None	ohms

TE01 Test Structures for SUB-CMOS Process MIXED Product



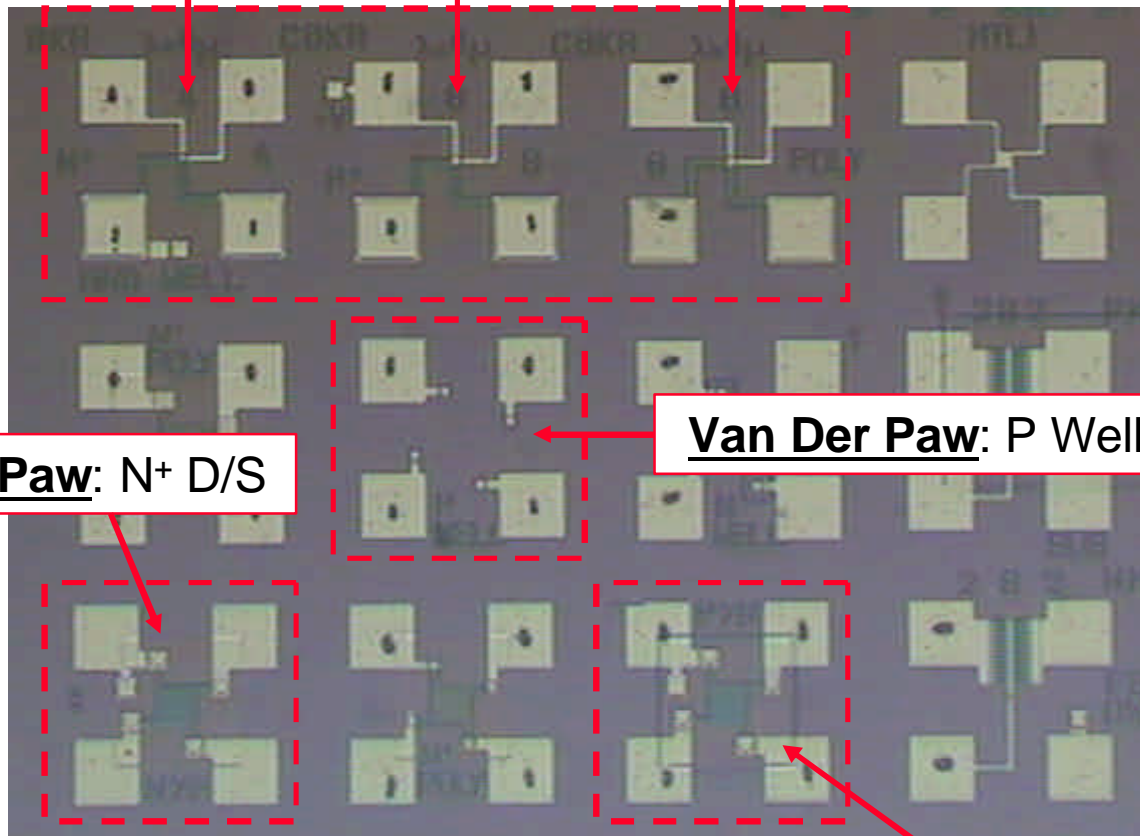
Van Der Paw: Metal

Van Der Paw: Poly

Rochester Institute of Technology
Microelectronic Engineering

TE01 Test Structures for SUB-CMOS Process MIXED Product

Cross Bridge Kelvin : N⁺ P⁺ POLY



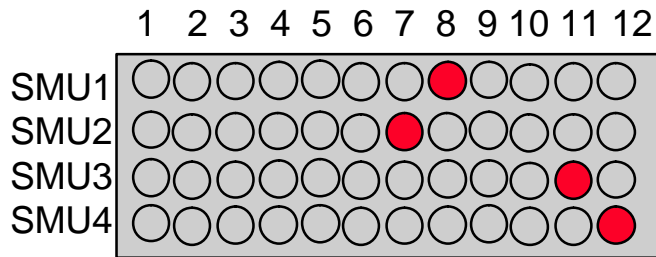
Van Der Paw: N⁺ D/S

Van Der Paw: P Well

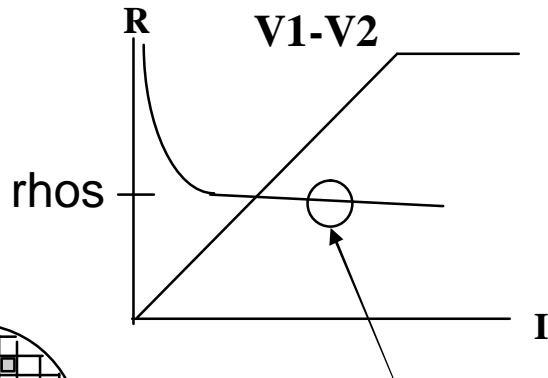
Van Der Paw: P⁺ D/S

TEST SET UP FOR POLY VAN DER PAUW (SUB-CMOS, MIXED) CHIPS

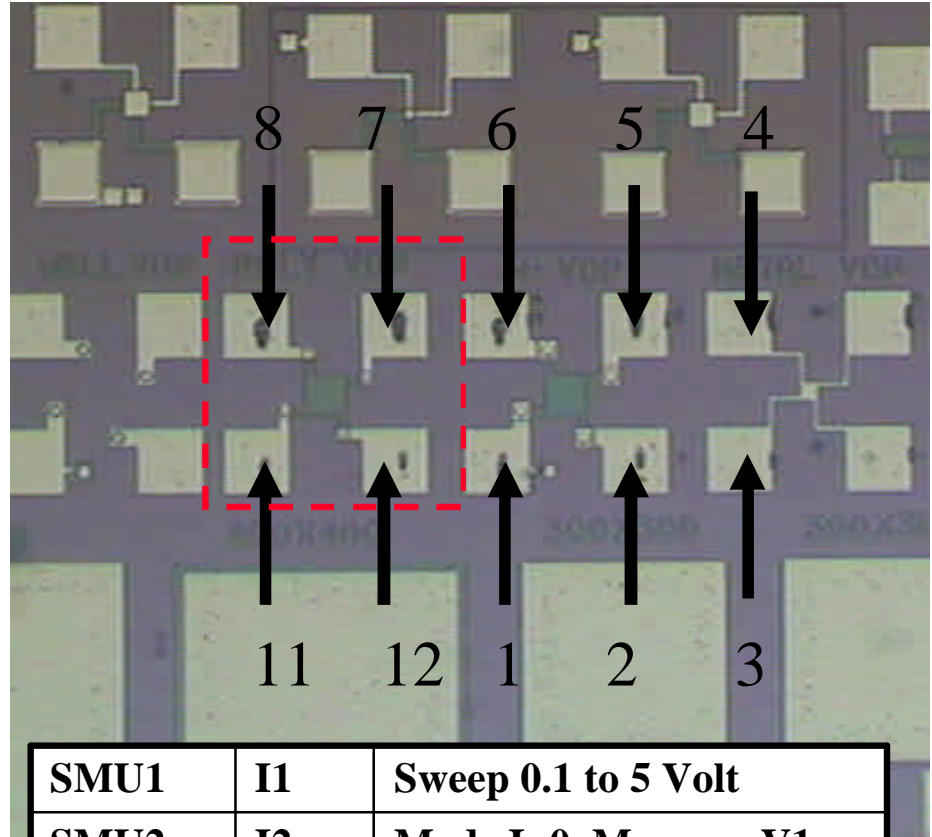
Test Name: VDP-POLY



Switch matrix



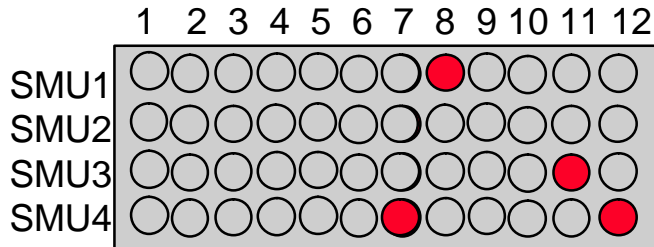
Place a cursor on the graph here to extract rhos value



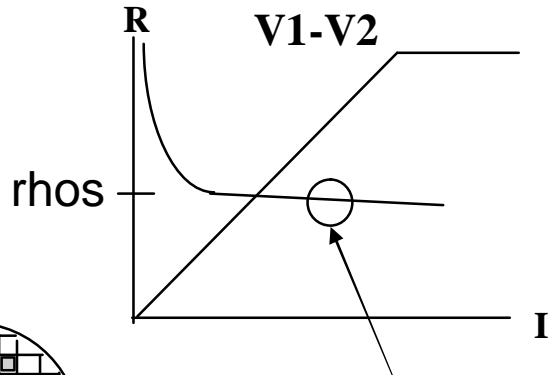
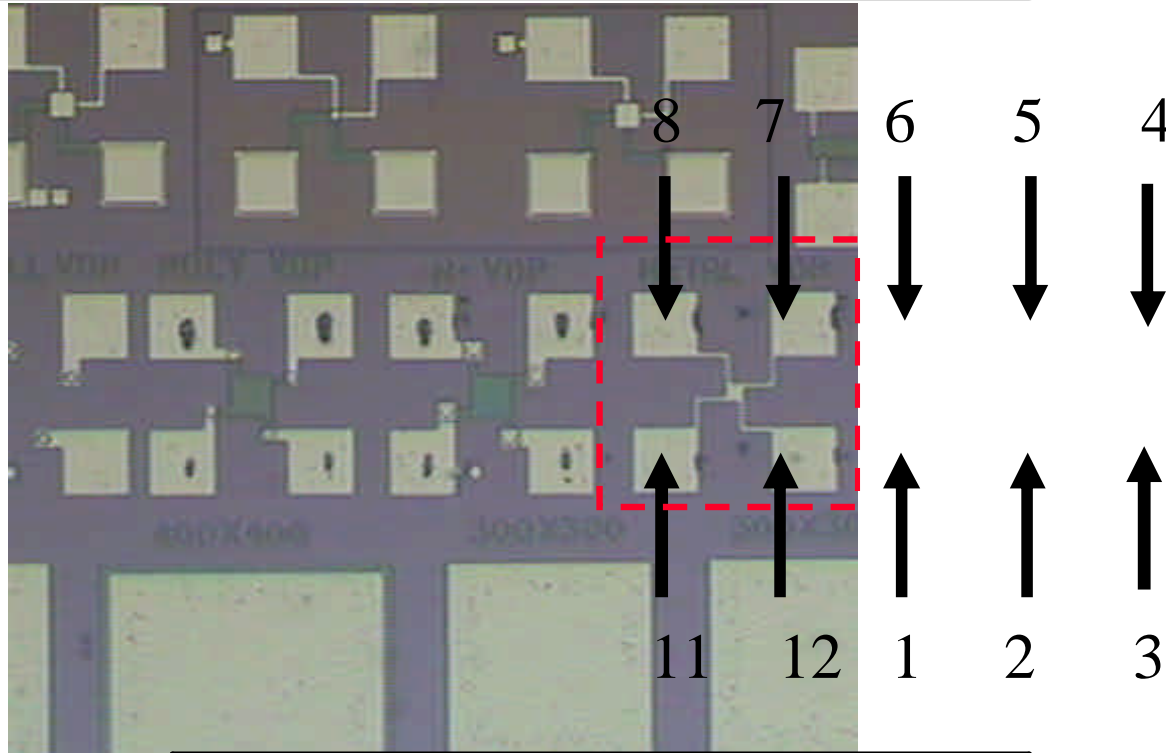
SMU1	I1	Sweep 0.1 to 5 Volt
SMU2	I2	Mode I=0, Measure V1
SMU3	V1	Com
SMU4	V2	Mode I=0, Measure V2
USER F	Rhos	= 4.532 (V1-V2)/I1

TEST SET UP FOR METAL VAN DER PAUW

Test Name: VDP-MET



Switch matrix

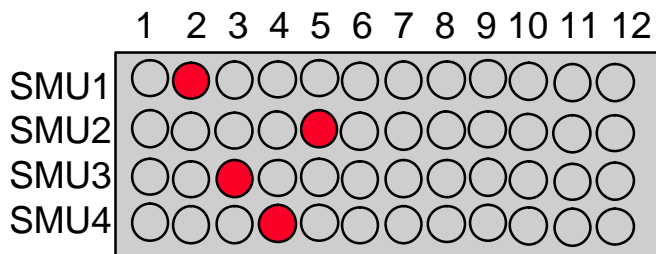


Place a cursor on the graph here to extract rhos value

SMU1	I1	Sweep 0.05 to 5 Volt
SMU2	I2	Mode I=0, Measure V1
SMU3	V1	Com
SMU4	V2	Mode I=0, Measure V2
USER F	Rhos	= 4.532 (V1-V2)/I1

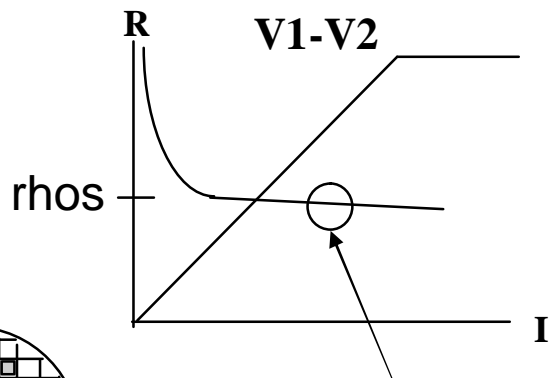
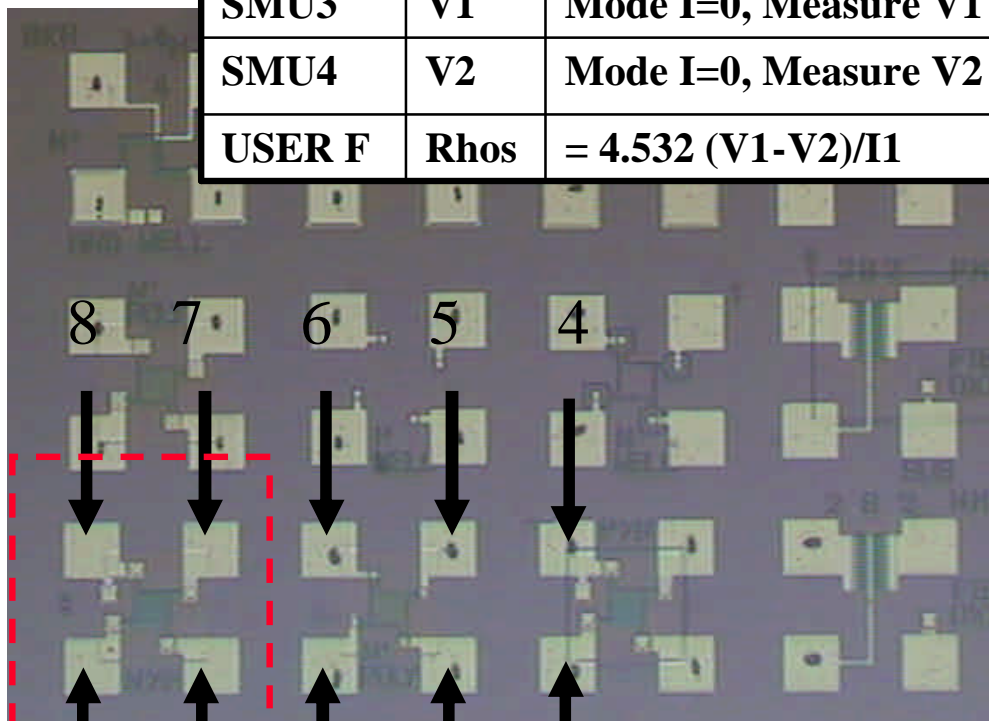
TEST SET UP FOR N+DS VAN DER PAUW

Test Name: VDP-N+

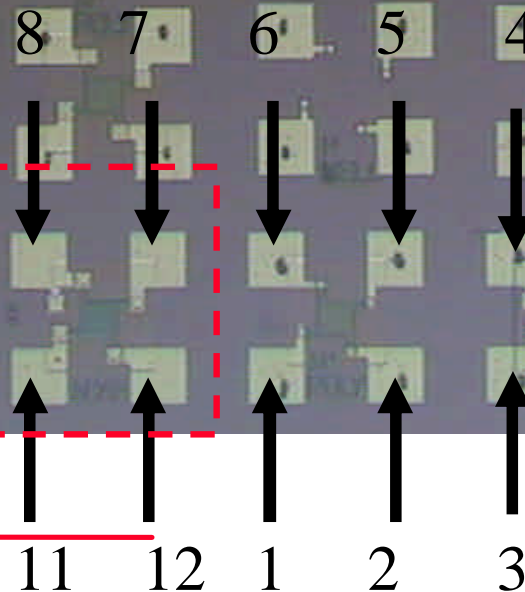


Switch matrix

SMU1	I1	Sweep 0-10mA
SMU2	I2	Com
SMU3	V1	Mode I=0, Measure V1
SMU4	V2	Mode I=0, Measure V2
USER F	Rhos	= 4.532 (V1-V2)/I1

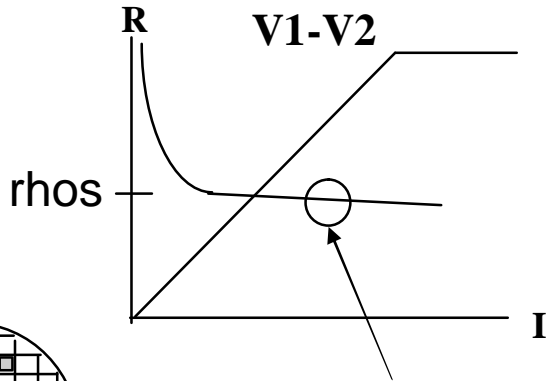
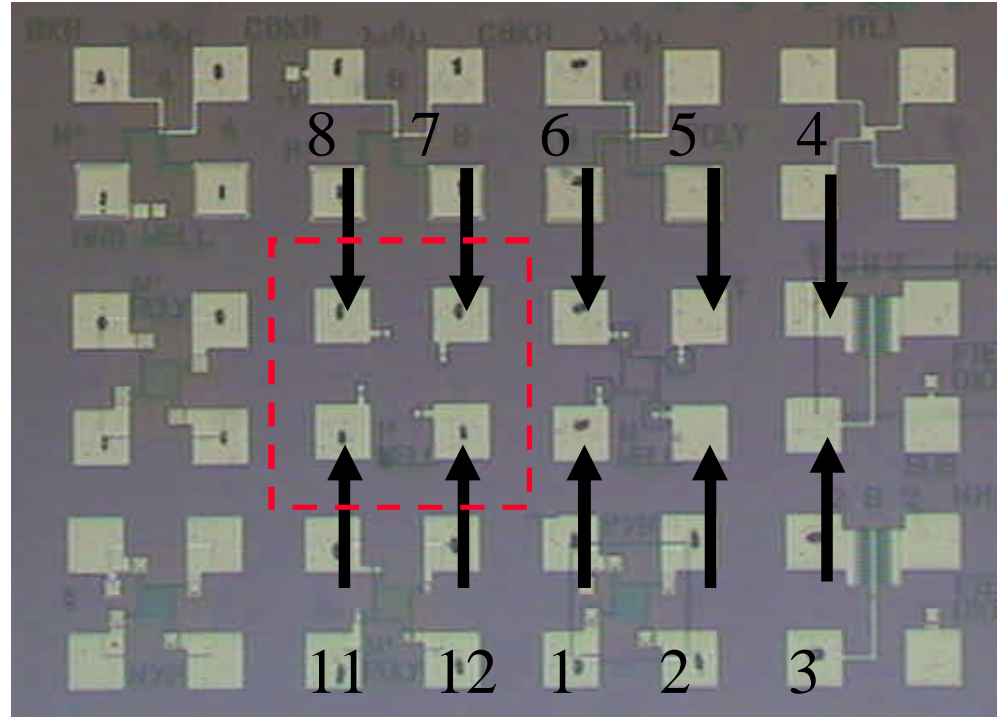
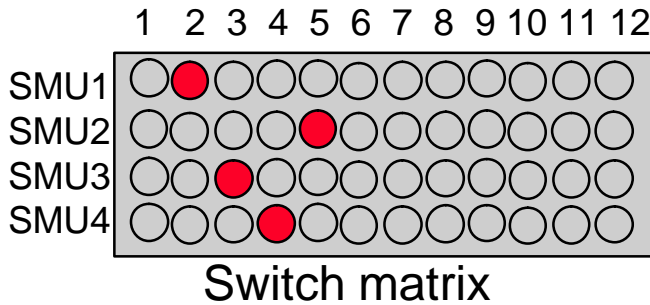


Place a cursor on the graph here to extract rhos value



TEST SET UP FOR PWell VAN DER PAUW

Test Name: VDP-PWell

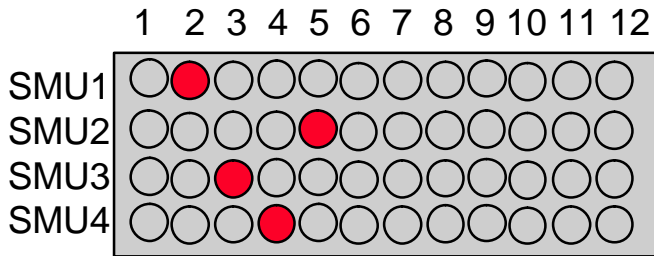


Place a cursor on the graph here to extract rhos value

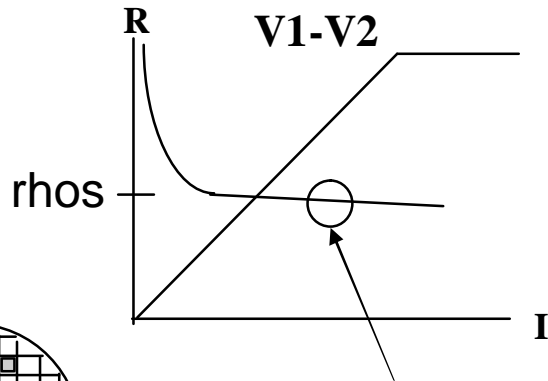
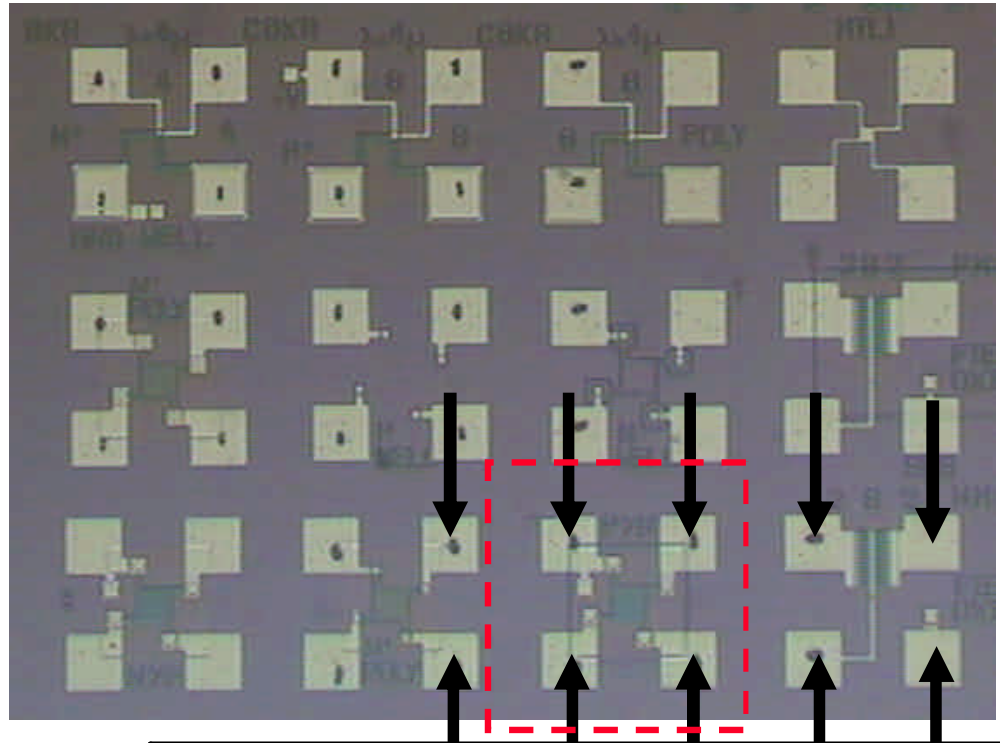
SMU1	I1	Sweep 0-10mA
SMU2	I2	Com
SMU3	V1	Mode I=0, Measure V1
SMU4	V2	Mode I=0, Measure V2
USER F	Rhos	= 4.532 (V1-V2)/I1

TEST SET UP FOR P+DS VAN DER PAUW

Test Name: VDP-P+



Switch matrix

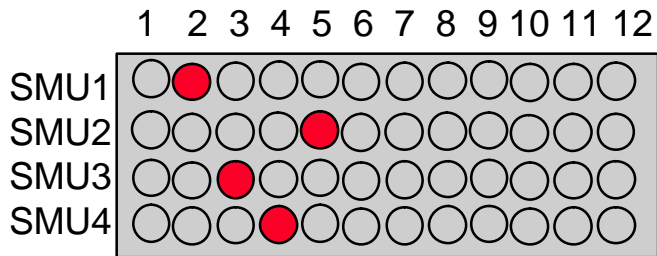


Place a cursor on the graph here to extract rhos value

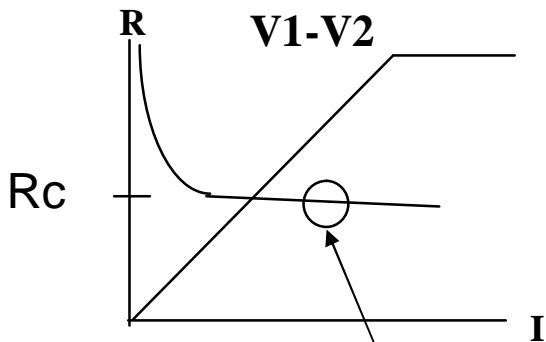
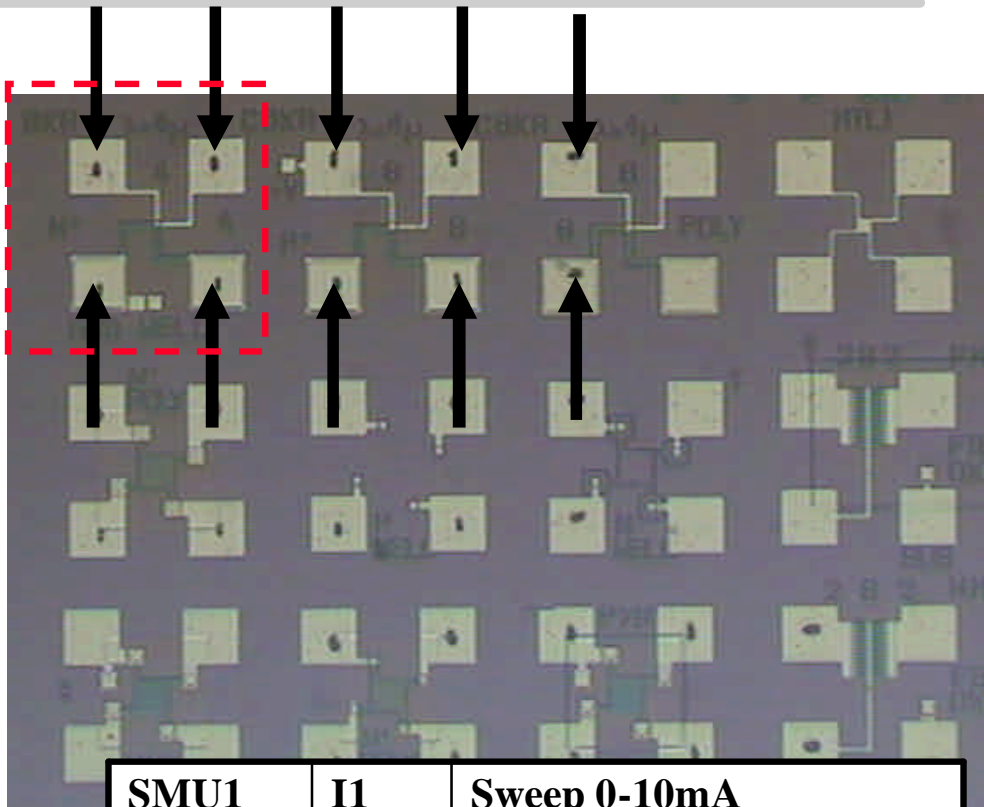
SMU1	I1	Sweep 0-10mA
SMU2	I2	Com
SMU3	V1	Mode I=0, Measure V1
SMU4	V2	Mode I=0, Measure V2
USER F	Rc	= 4.532 (V1-V2)/I1

TEST SET UP FOR N+ CBKR

Test Name: CBKR-N



Switch matrix

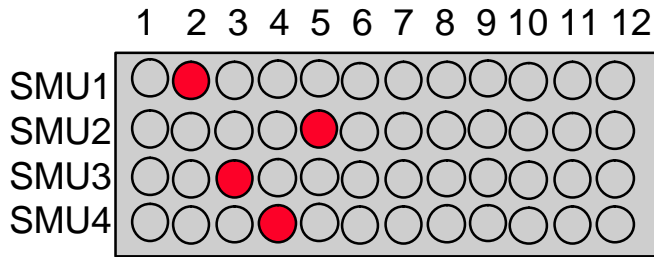


Place a cursor on the graph here to extract Specific Contact Conductance value

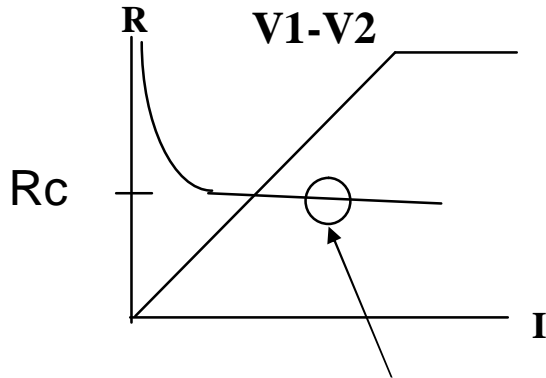
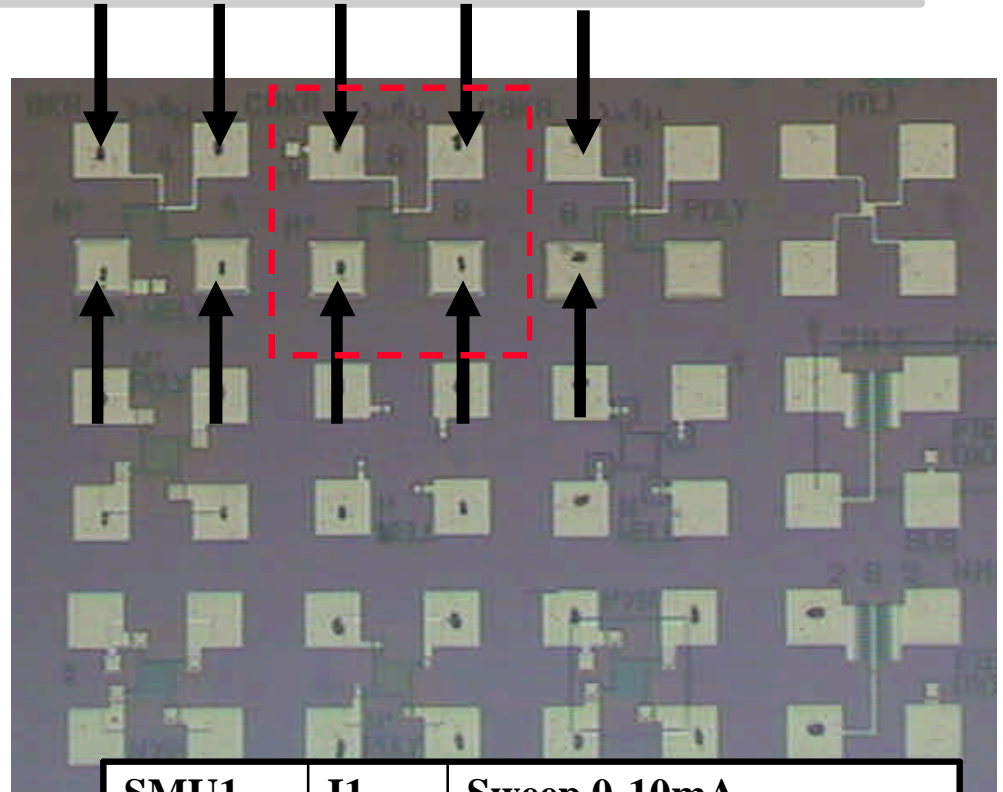
SMU1	I1	Sweep 0-10mA
SMU2	I2	Com
SMU3	V1	Mode I=0, Measure V1
SMU4	V2	Mode I=0, Measure V2
USER F	Rc	= (V1-V2)/I1

TEST SET UP FOR P+ CBKR

Test Name: CBKR-P



Switch matrix

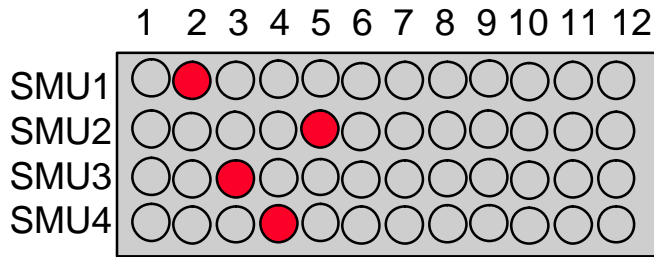


Place a cursor on the graph here to extract Specific Contact Conductance value

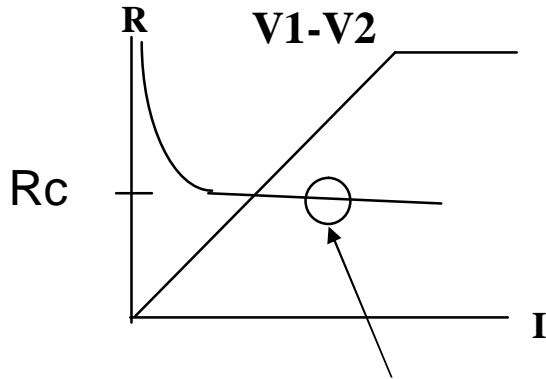
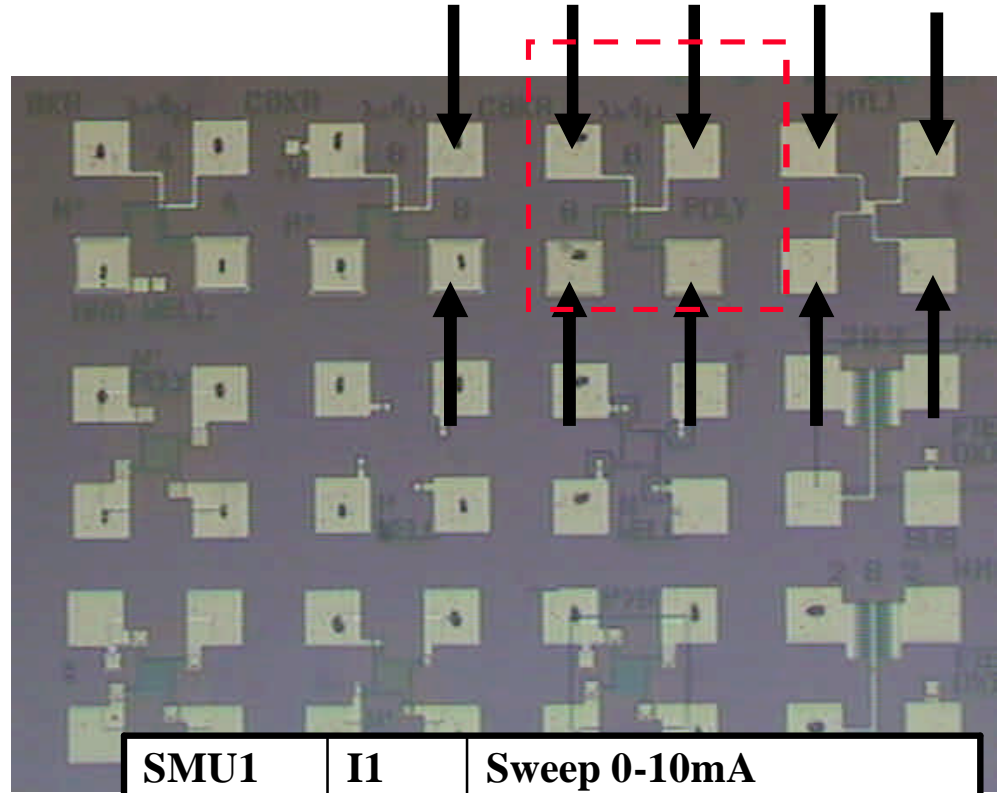
SMU1	I1	Sweep 0-10mA
SMU2	I2	Com
SMU3	V1	Mode I=0, Measure V1
SMU4	V2	Mode I=0, Measure V2
USER F	Rc	= (V1-V2)/I1

TEST SET UP FOR POLY CBKR

Test Name: CBKRPOLY



Switch matrix



Place a cursor on the graph here to extract Specific Contact Conductance value

SMU1	I1	Sweep 0-10mA
SMU2	I2	Com
SMU3	V1	Mode I=0, Measure V1
SMU4	V2	Mode I=0, Measure V2
USER F	Rhos	= (V1-V2)/I1

TE02 TRANSISTORS

5/04/06

8:35:54

MESA

Instruction Group Inquiry

IGMSINQ

S36801

QPADEV000W

RIT

Type information. Then Enter.

1=Display document, 5=Display detail

Plant : RIT

Instruction group . . : SUB-CMOS-TE02 TEST COMPLETED WAFERS

Revision : 150

Opt Subgroup Text

█
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—
—
—
—

- 1.0 Test PMOS and NMOS Transistors
for threshold voltage, tranconductance, lambda,
subthreshold slope, min and max current value on the
subthreshold test
- 2.0 Record VTn, VTp, gmn, gmp, sub-Vt-slope, Isub-min, Isub-max,
Lambda, transistor width&length for nmos & pmos, Vt field

Bottom

F3=Exit

F4=Prompt

F5=Refresh

F10=View 2

F12=Cancel

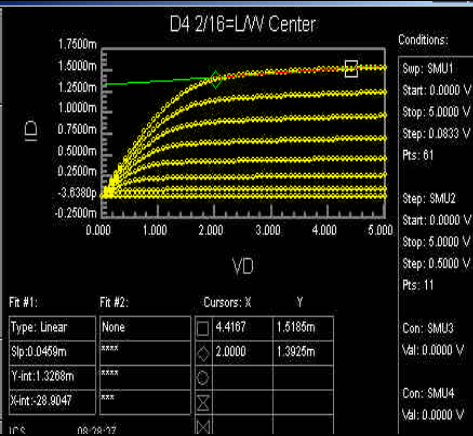
MOSFET IV CHARACTERISTICS

Lot Number = F050118
Process = SMFL CMOS

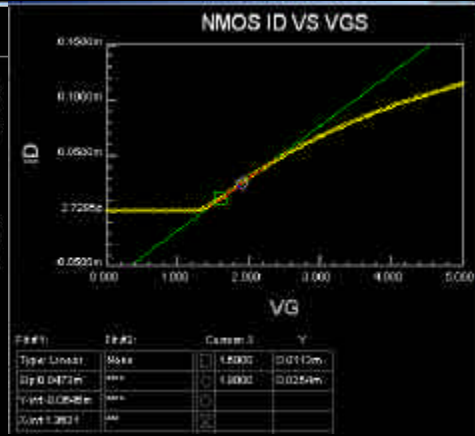
Wafer Number = D4
Product = DAC03

Date = 11-17-2006

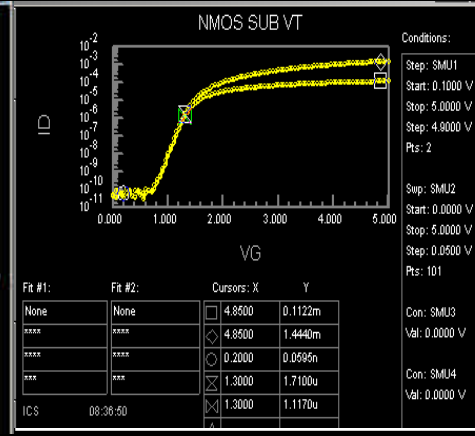
NMOS L/W = 2/16



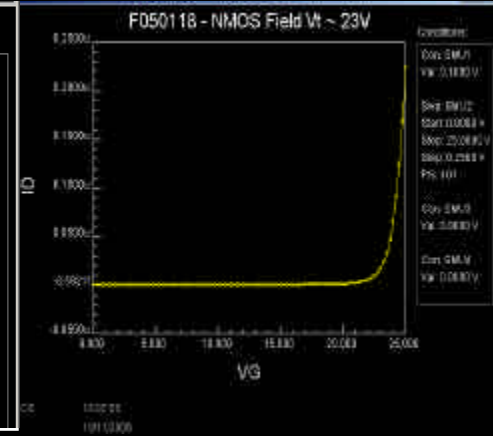
NFAM



NVT

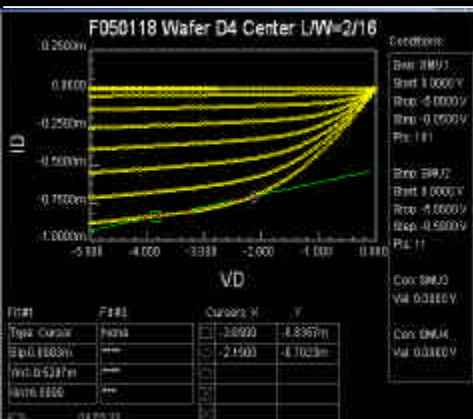


NSUB

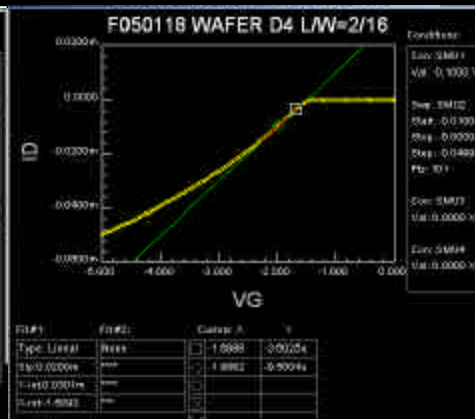


NFIELD

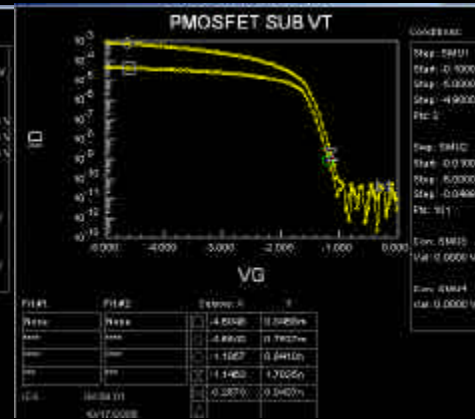
PMOS L/W = 2/16



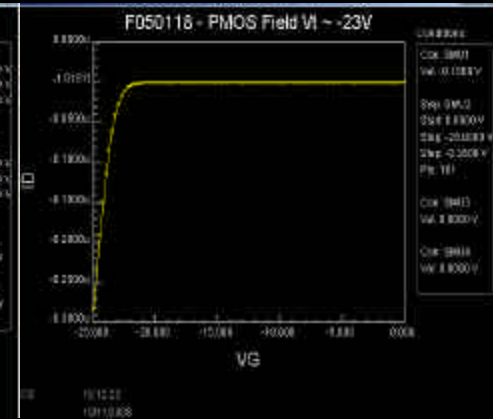
PFAM



PVT



PSUB



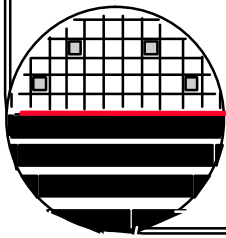
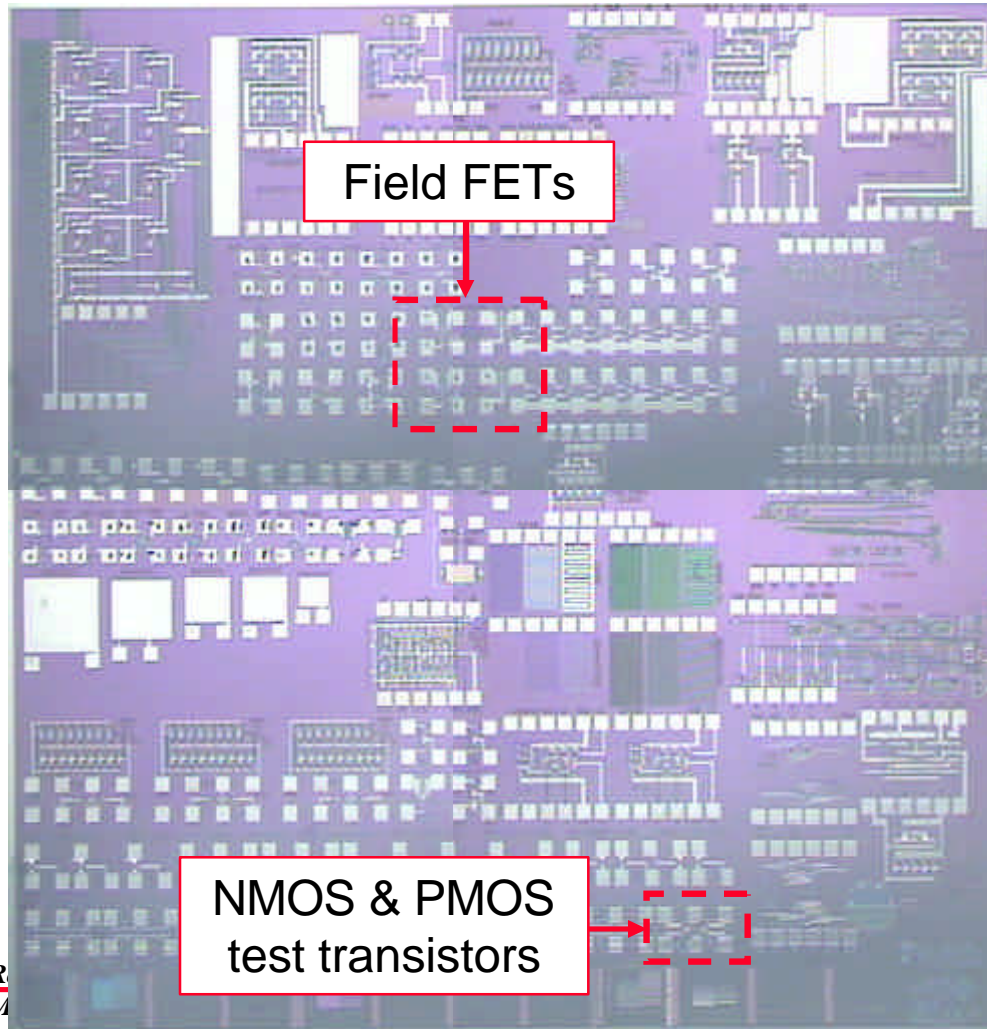
PFIELD

MOSFET EXTRACTED PARAMETERS

Lot Number = F050118 – Wafer Number = D4, Die Location R= , C=

	PMOS	NMOS	Units
Mask Length / Width	2/16	2/16	μm
VT	-1.51	1.36	V
Lambda (for Vgs = Vdd)	0.115	0.0417	V ⁻¹
Max gm / mm of channel width	21.3	31.3	S/mm
Idrive	54.4	93.8	μA/μm
Ion/Ioff @ Vd = 0.1V	6	5	Decades
Ion/Ioff @ Vd = 5V	7	6	Decades
Ioff @ Vd = 0.1V	5.9e-11	5.0e-10	A/μm
Ioff @ Vd = 5V	5.9e-11	5.0e-10	A/μm
Sub-Vt Slope @ Vd = 0.1V	90	190	mV/Dec
Sub-Vt Slope @ Vd = 5 V	90	190	mV/Dec
DIBL@1nA/μm = $\Delta V_g / \Delta V_d$	0	0	mV/V
Field VT	-23	23	V

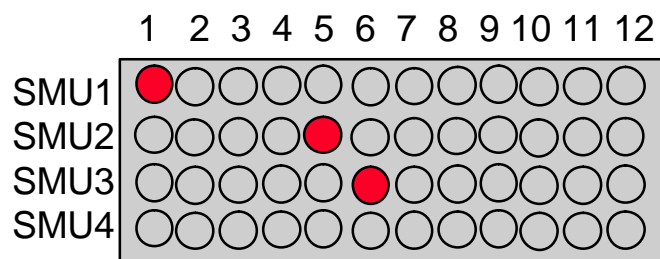
TE02 TEST STRUCTURES



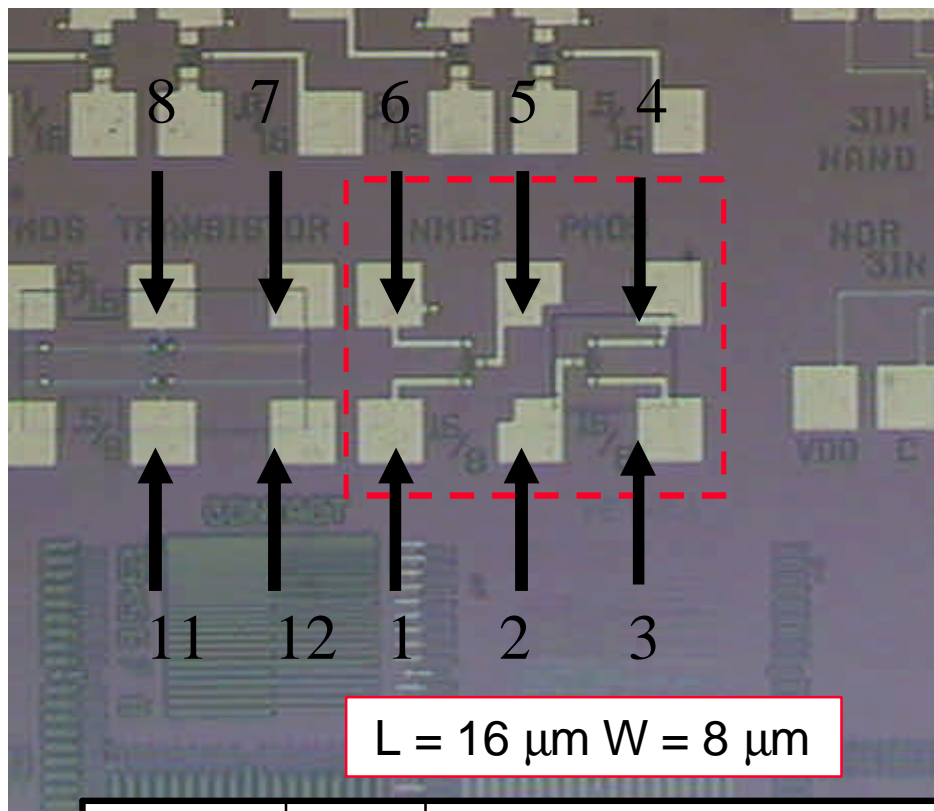
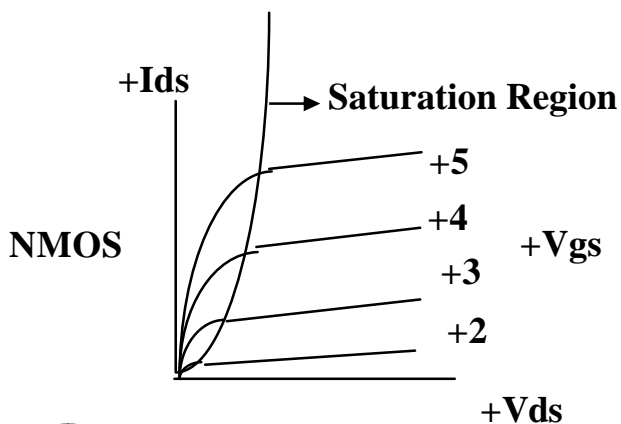
R
M

LARGE NMOS FAMILY OF CURVES

Test Name: NFAM



Switch matrix

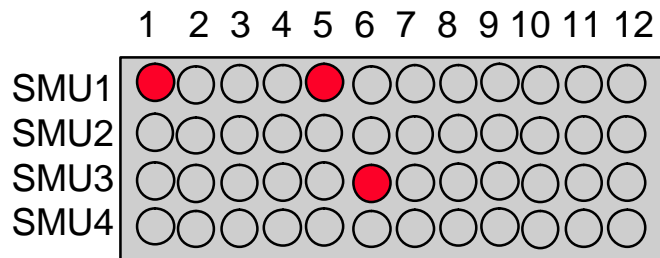


SMU1	Vds	Sweep 0 - 5 V, 101 steps
SMU2	Vgs	11 Steps 0 - 5V
SMU3	Com	Vs = 0
SMU4		

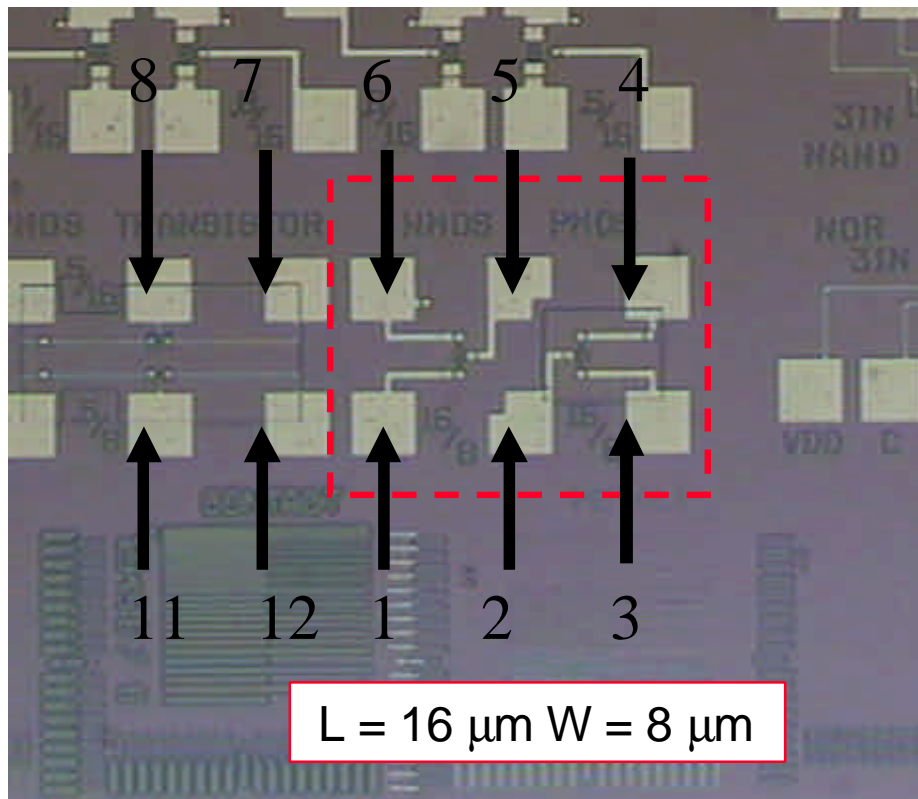
Extract: Lambda

LARGE NMOS ID-VGS

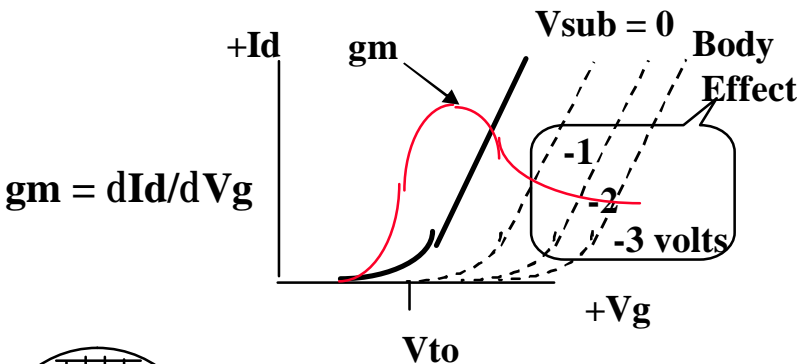
Test Name: NVT



Switch matrix



$L = 16 \mu\text{m}$ $W = 8 \mu\text{m}$

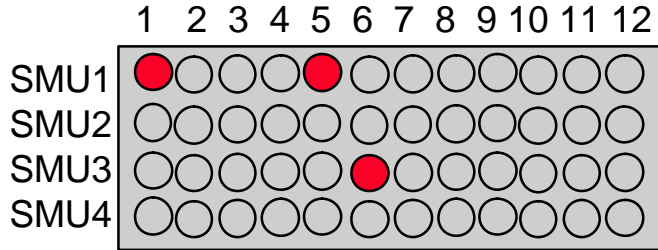


Extract: Max gm, Vto

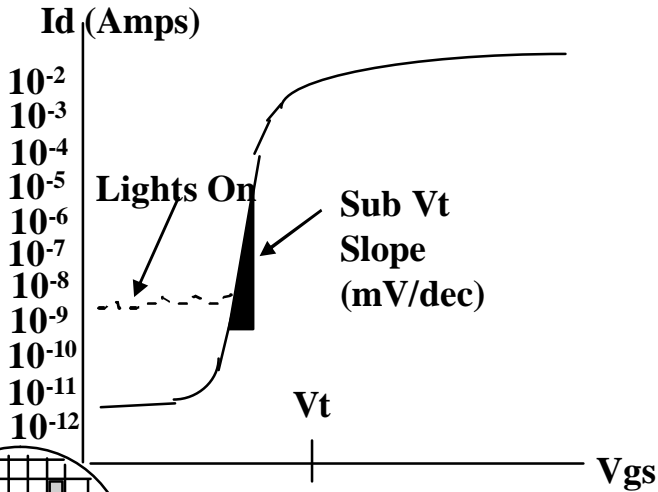
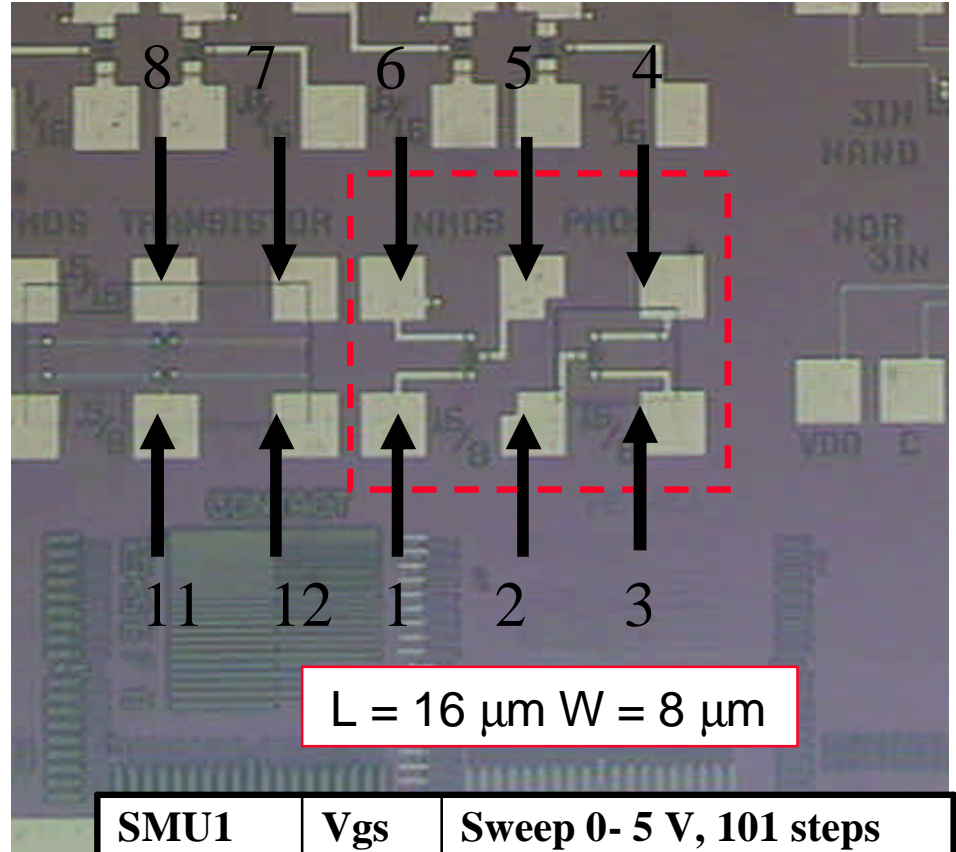
SMU1	Vgs	Sweep 0- 5 V, 101 steps
SMU2		
SMU3	Com	Vs = 0
SMU4		

LARGE NMOS SUBTHRESHOLD

Test Name: NSUB



Switch matrix

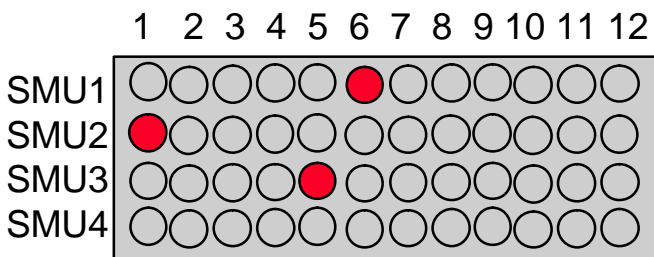


Extract: I_{max}, I_{min}, Sub Slope

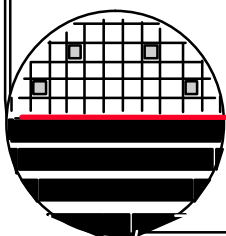
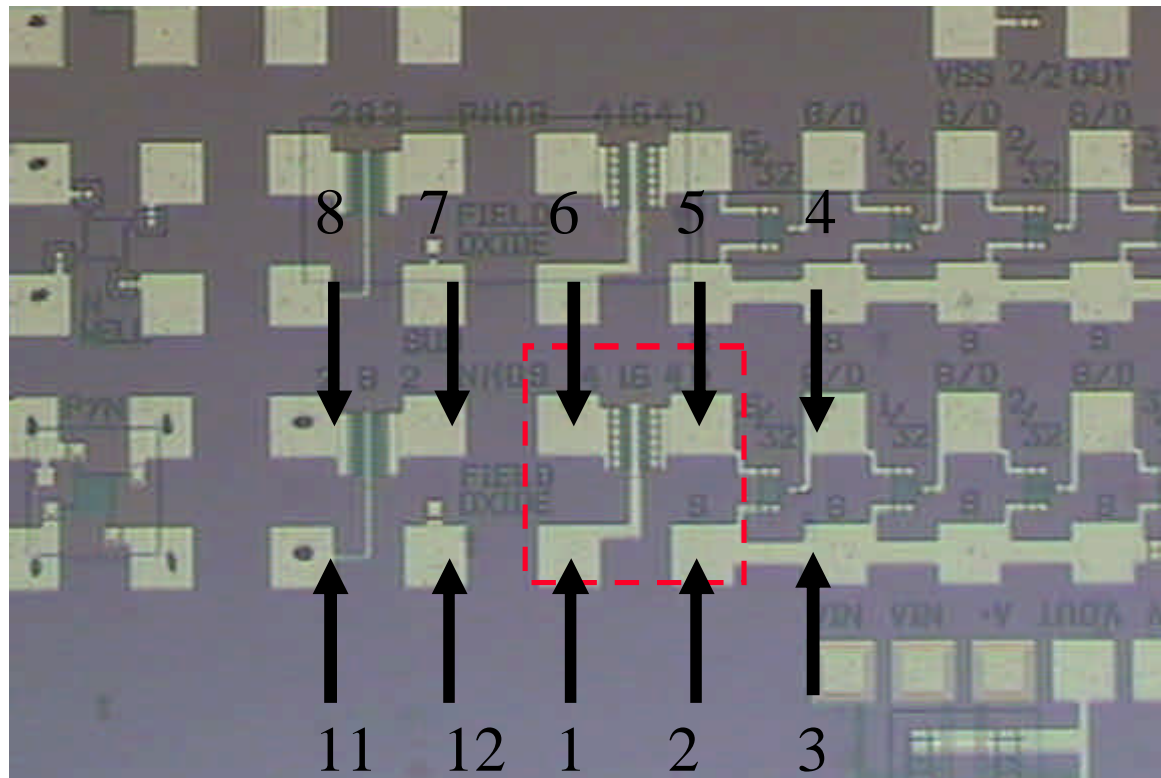
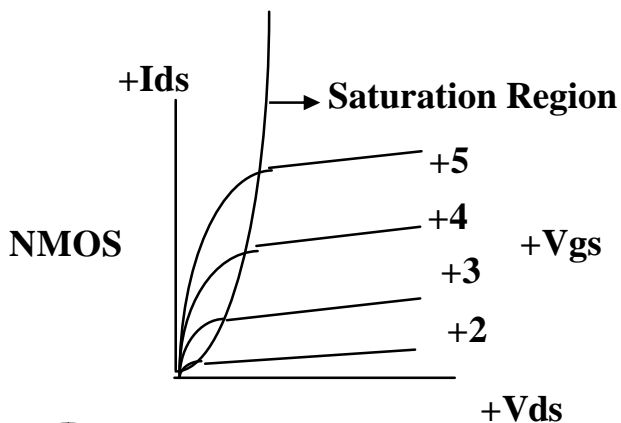
SMU1	Vgs	Sweep 0- 5 V, 101 steps
SMU2		
SMU3	Com	Vs = 0
SMU4		

NMOS FIELD VT

Test Name: NFIELD



Switch matrix

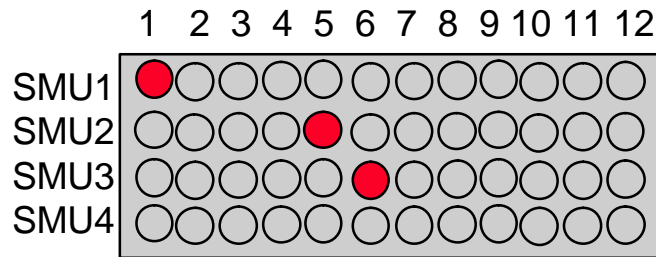


Extract: $\sim V_t$

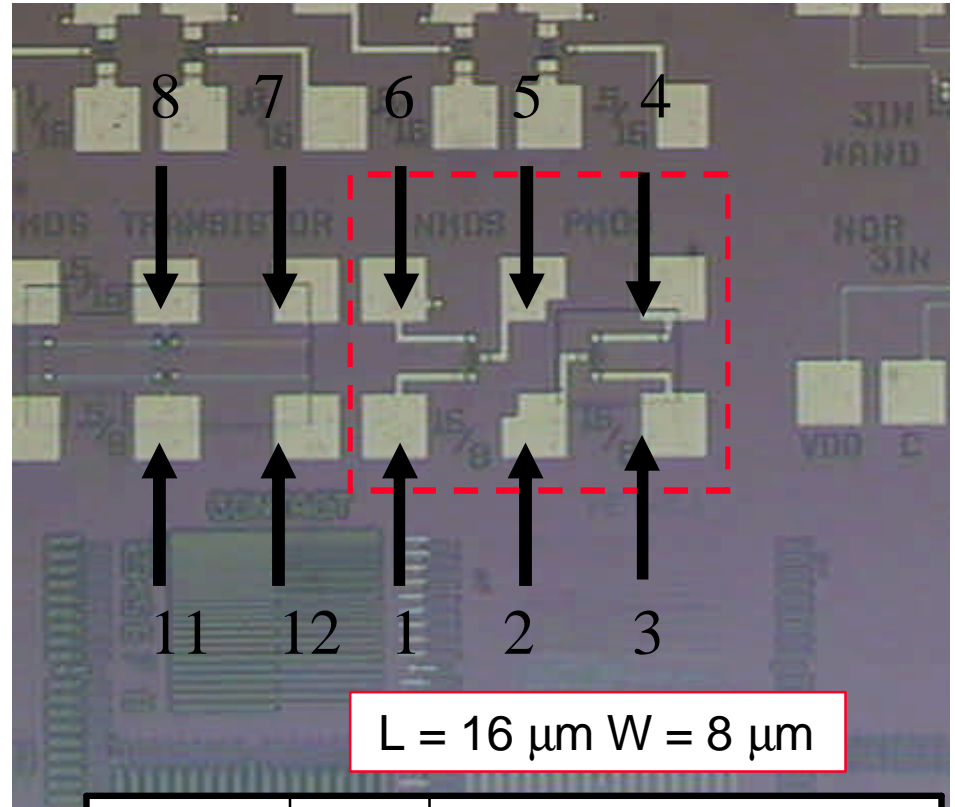
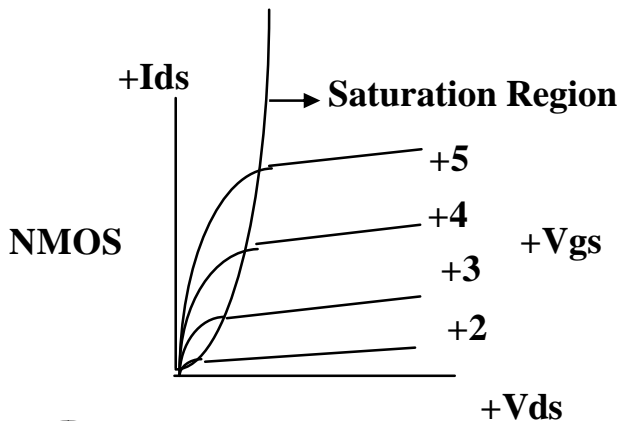
SMU1	Vds	Sweep 0 to 20 V, 101 steps
SMU2	Vgs	11 Steps 0 to 20V
SMU3	Com	Vs = 0
SMU4		

LARGE PMOS FAMILY OF CURVES

Test Name: PFAM



Switch matrix

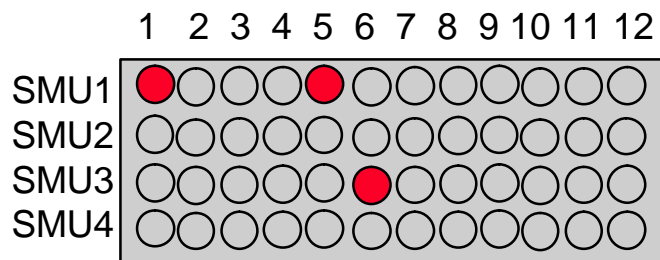


SMU1	Vds	Sweep 0 - 5 V, 101 steps
SMU2	Vgs	11 Steps 0 - 5V
SMU3	Com	Vs = 0
SMU4		

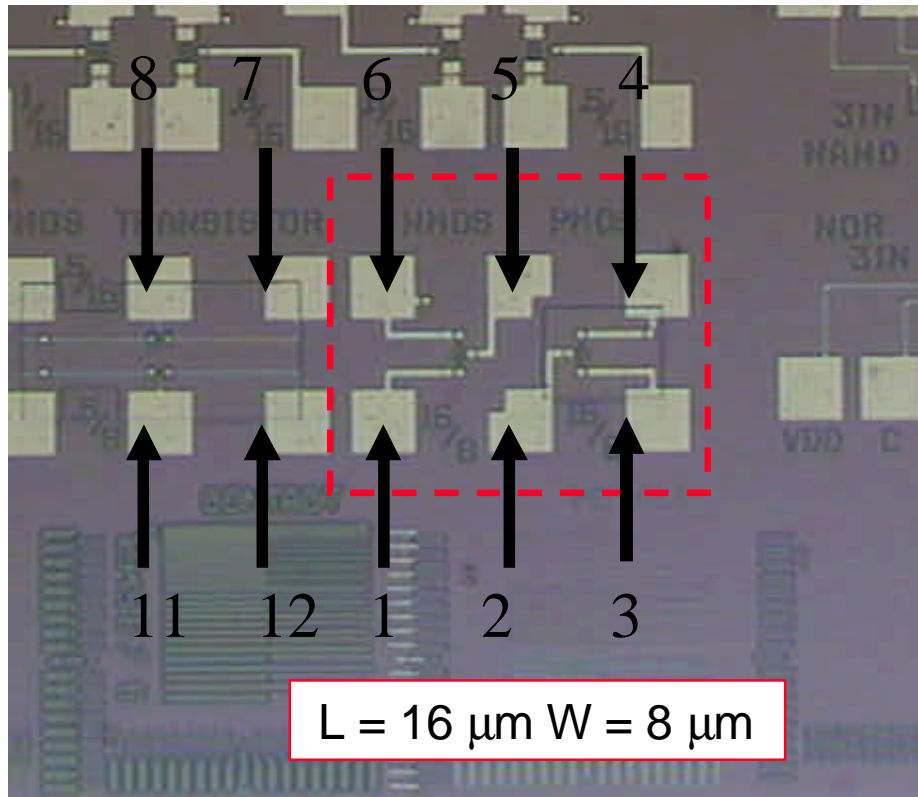
Extract: Lambda

LARGE PMOS ID-VGS

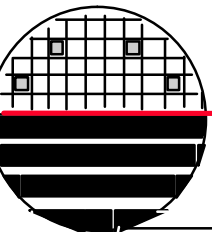
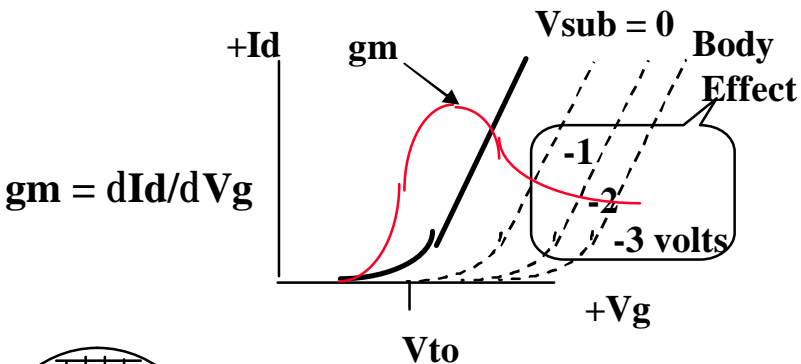
Test Name: PVT



Switch matrix



L = 16 μm W = 8 μm

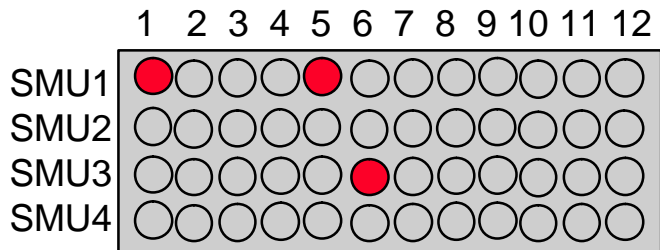


Extract: Max gm, Vto

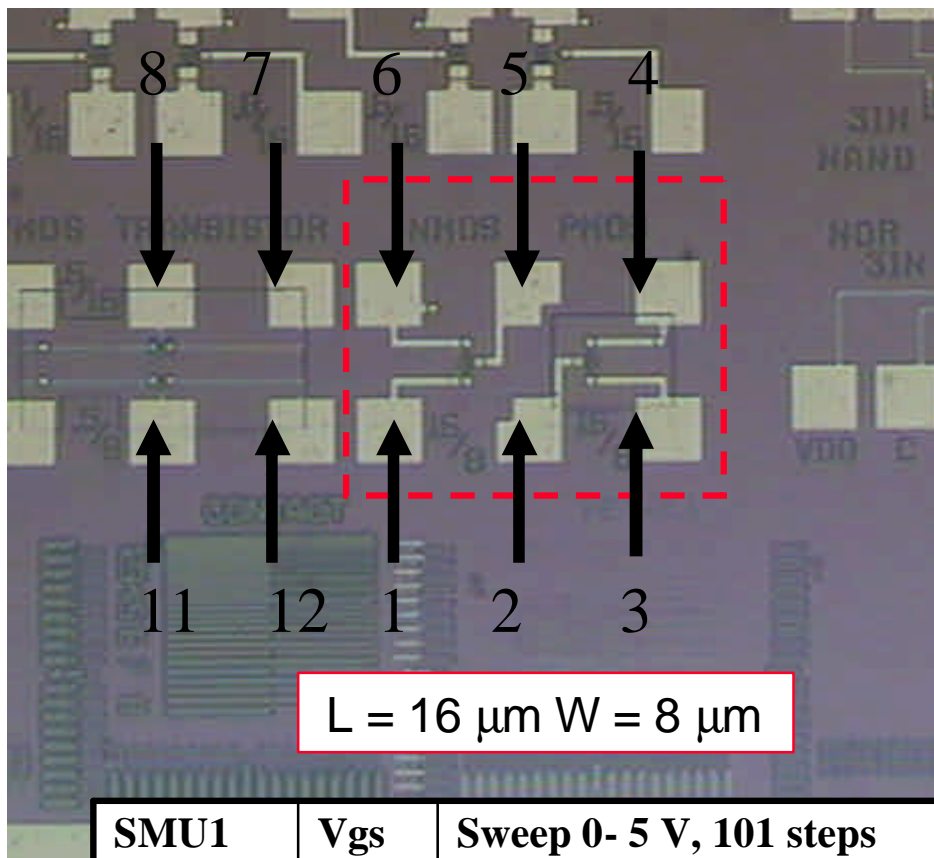
SMU1	Vgs	Sweep 0- 5 V, 101 steps
SMU2		
SMU3	Com	Vs = 0
SMU4		

LARGE PMOS SUBTHRESHOLD

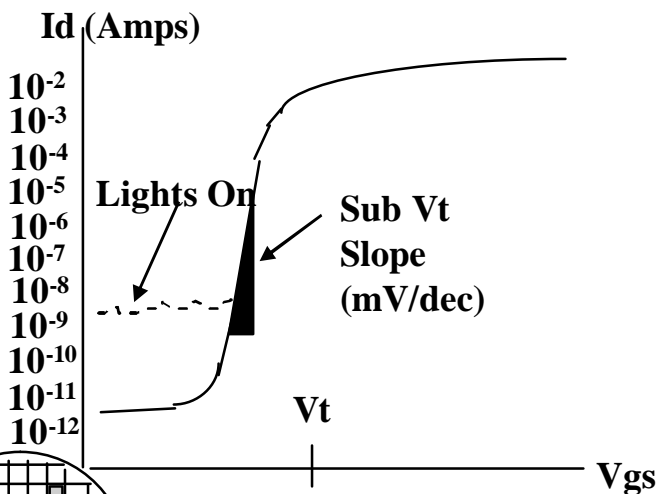
Test Name: PSUB



Switch matrix



$L = 16 \mu\text{m}$ $W = 8 \mu\text{m}$

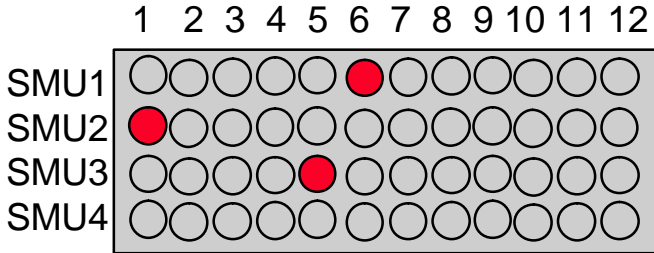


Extract: I_{max}, I_{min}, Sub Slope

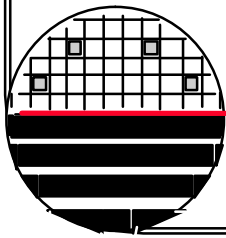
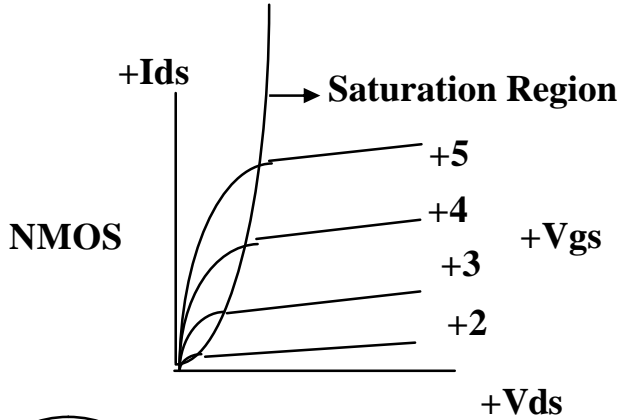
SMU1	V _{gs}	Sweep 0- 5 V, 101 steps
SMU2		
SMU3	Com	V _s = 0
SMU4		

PMOS FIELD VT

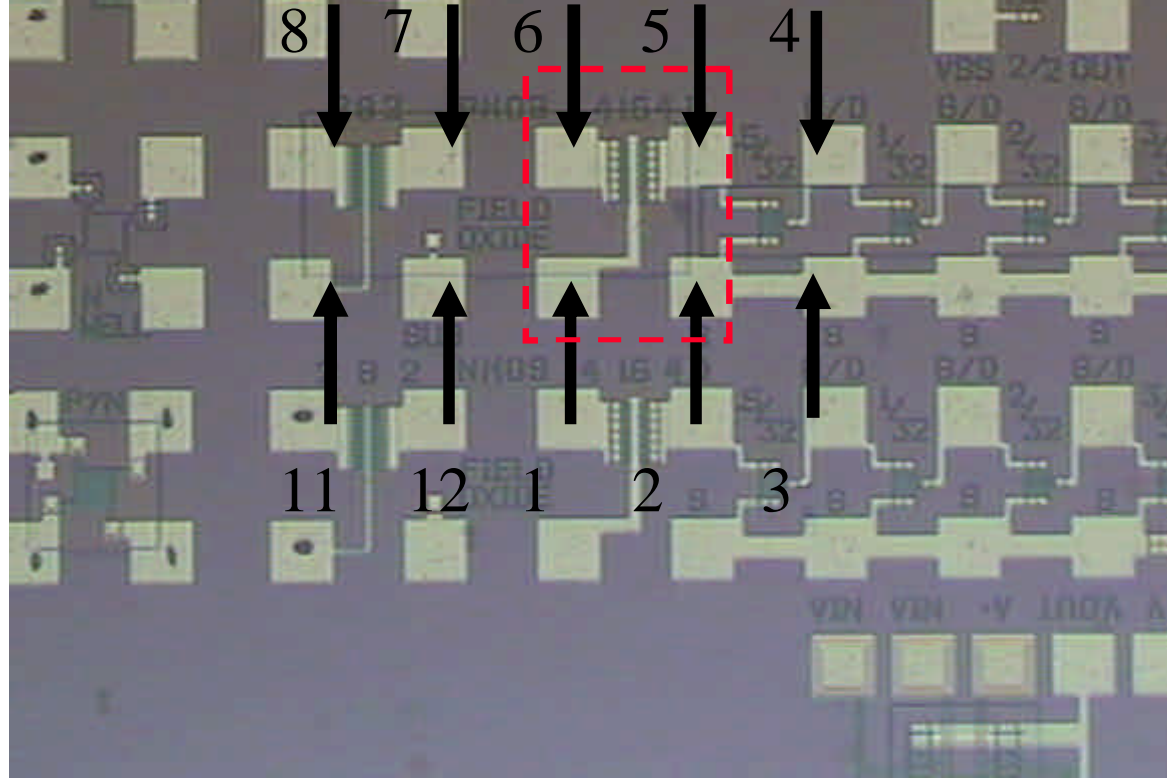
Test Name: PFIELD



Switch matrix



Extract: $\sim V_t$



SMU1	Vds	Sweep 0 to -20 V, 101 steps
SMU2	Vgs	11 Steps 0 to - 20V
SMU3	Com	Vs = 0
SMU4		

TE03 INTEGRATED CIRCUITS

5/04/06

MESA

IGMSINQ

S36801

8:37:20

Instruction Group Inquiry

QPADEV000W

RIT

Type information. Then Enter.
1=Display document, 5=Display detail

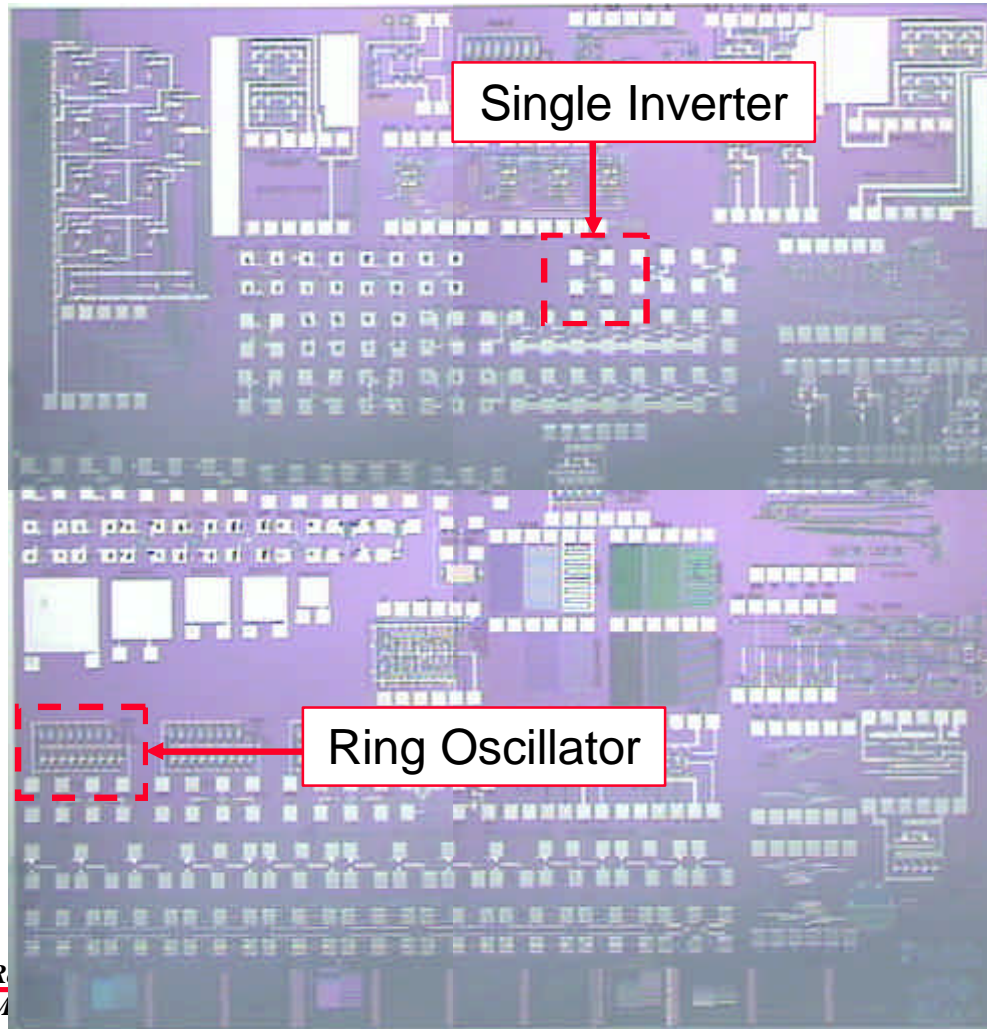
Plant : RIT
 Instruction group . . : SUB-CMOS-TE03 TEST COMPLETED WAFERS
 Revision : 150

Opt	Subgroup	Text
█		1.0 Test Inverters and Ring Oscillator
-		2.0 Record ViL, ViH, VoL, VoH, Vinv, Imax, Ring Oscillator
-		Frequency, Number of Stages

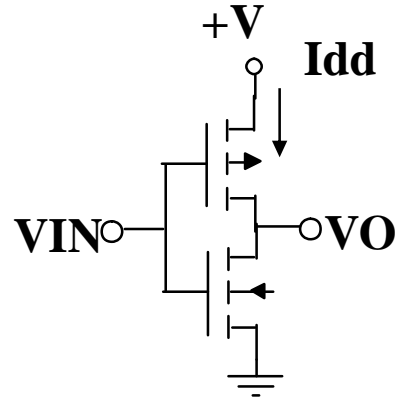
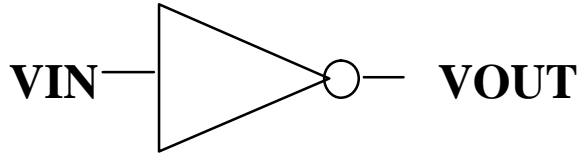
Bottom

F3=Exit F4=Prompt F5=Refresh F10=View 2 F12=Cancel

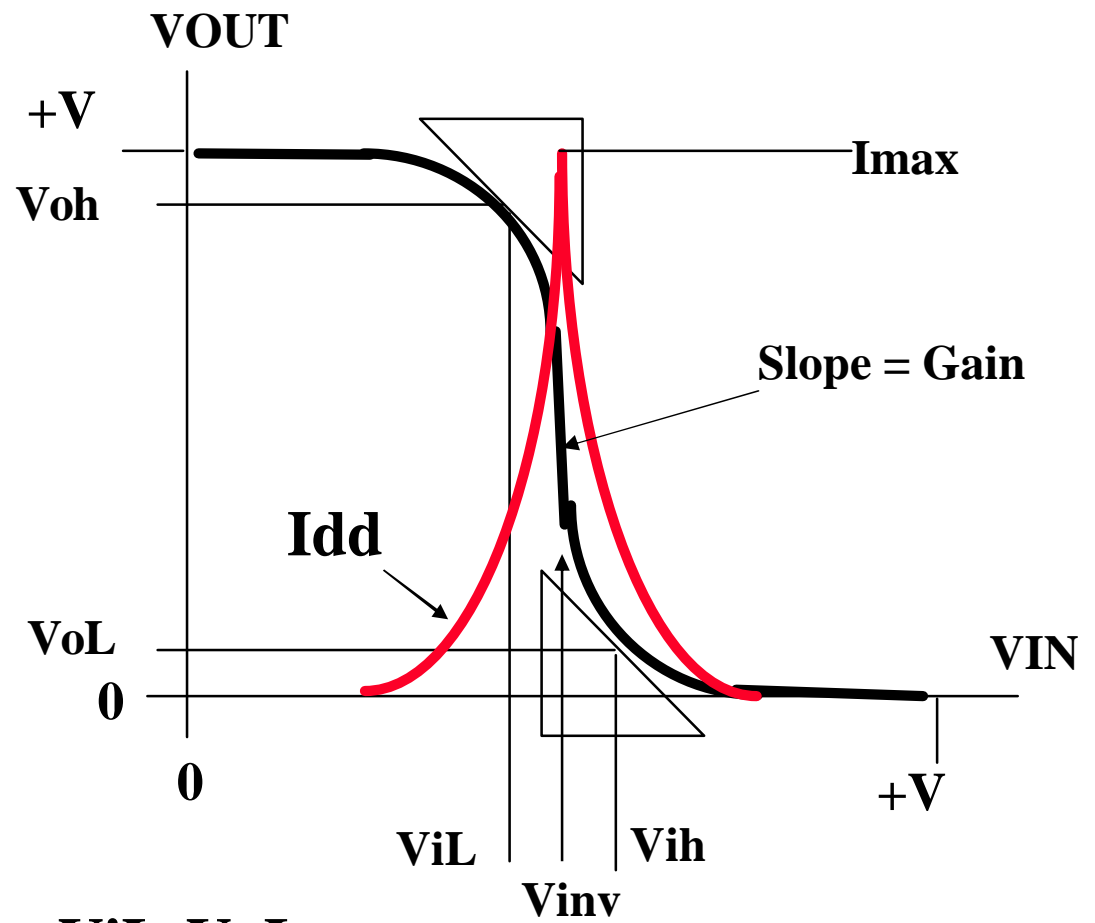
TE03 TEST STRUCTURES



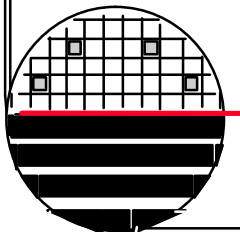
INVERTERS



CMOS



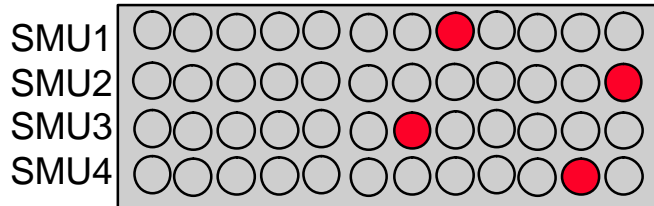
D0 noise margin = $V_{iL} - V_{oL}$
D1 noise margin = $V_{oH} - V_{iH}$



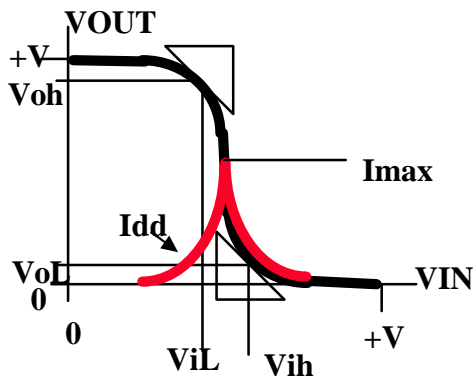
INVERTER TEST SETUP

Test Name: INV

1 2 3 4 5 6 7 8 9 10 11 12

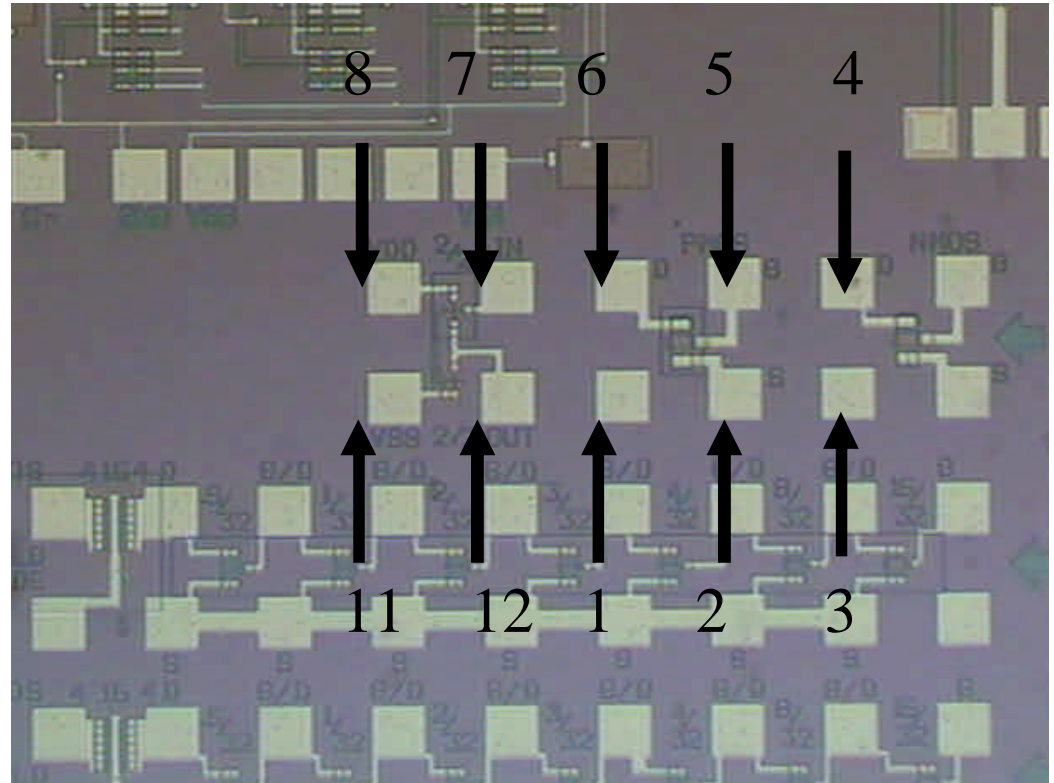


Switch matrix



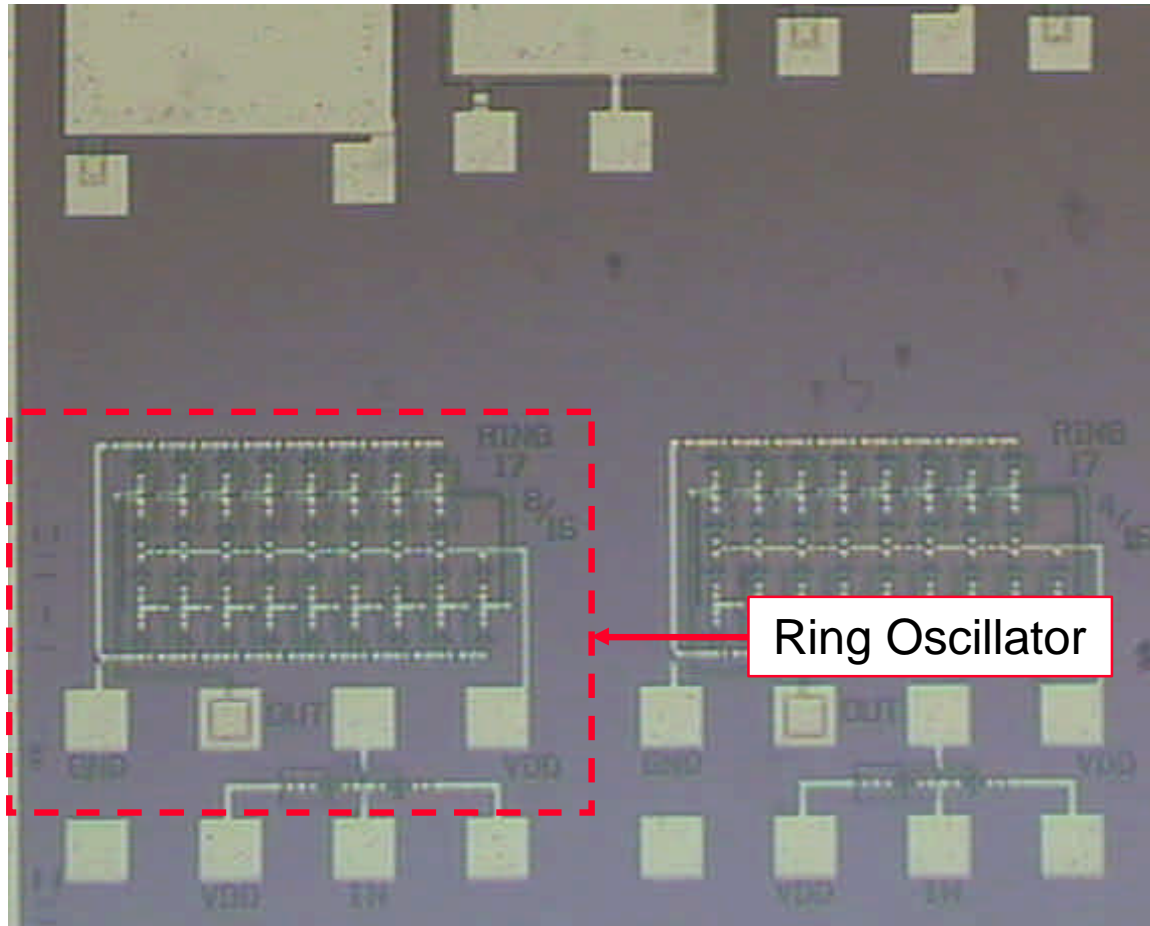
D0 noise margin = $V_{iL} - V_{oL}$
 D1 noise margin = $V_{oH} - V_{iH}$

Extract: Voh, Vol, Vih, Vil, Vinv, Imax, Gain



SMU1	Vdd	Constant +5 V
SMU2	Vin	Sweep 0 to +5V, 101 steps
SMU3	Vout	I mode, measure Vout
SMU4	Com	0 Volts

TE03 RING OSCILLATOR



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RING OSCILLATOR, t_d

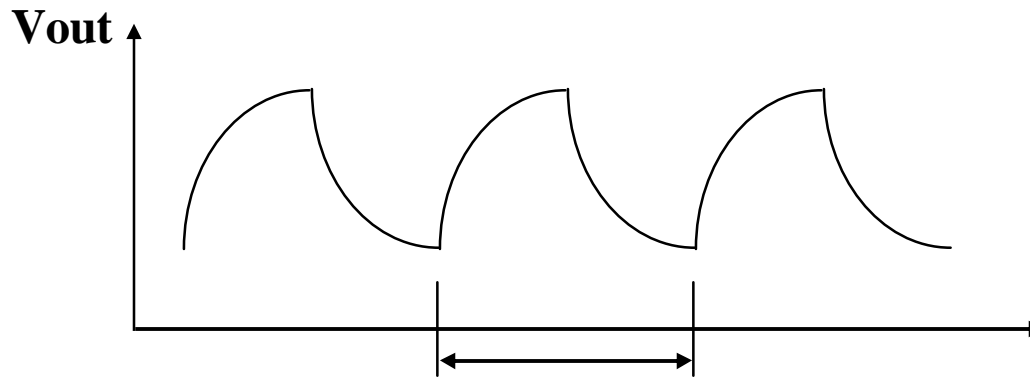
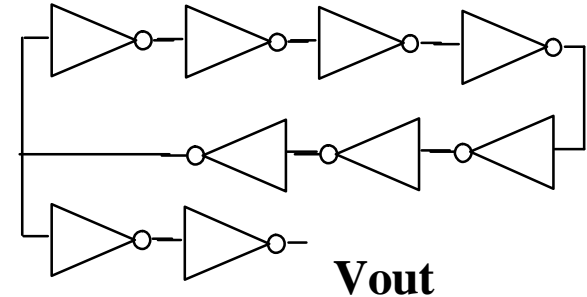
**Seven stage ring oscillator
with two output buffers**

$t_d = T / 2 N$

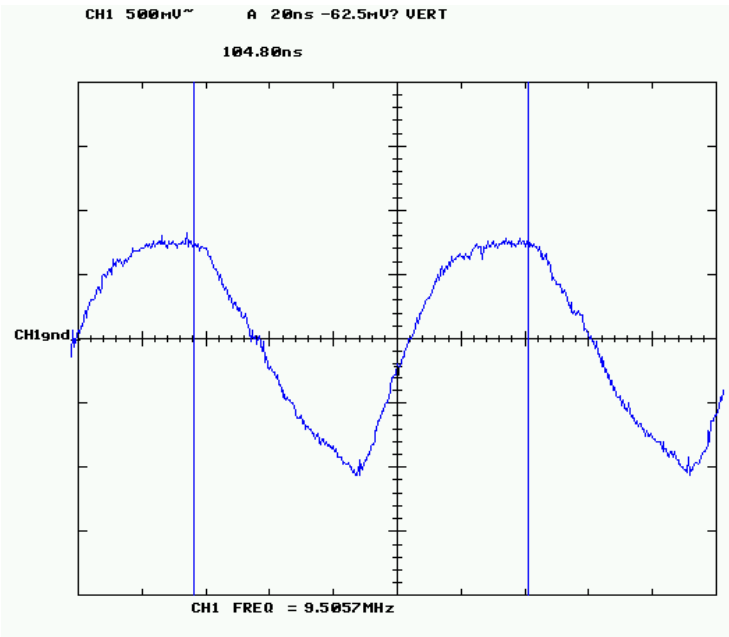
t_d = gate delay

N = number of stages

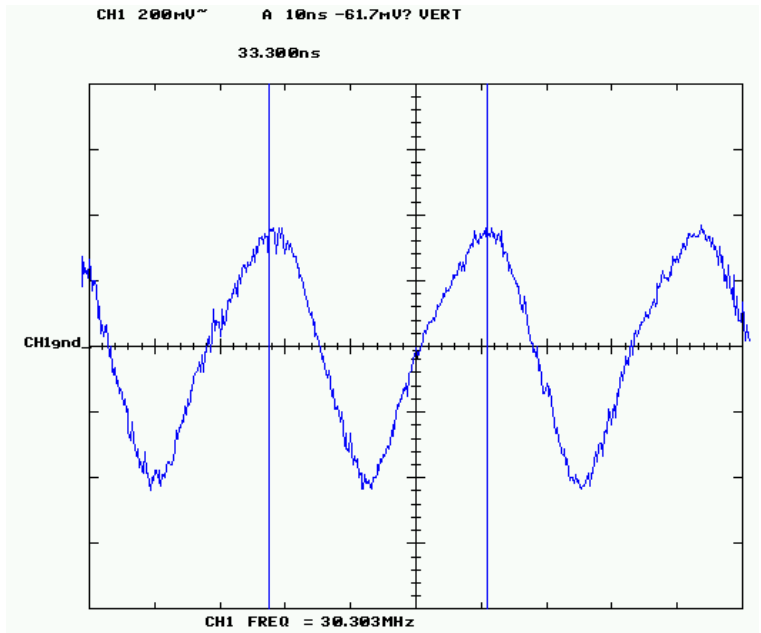
T = period of oscillation



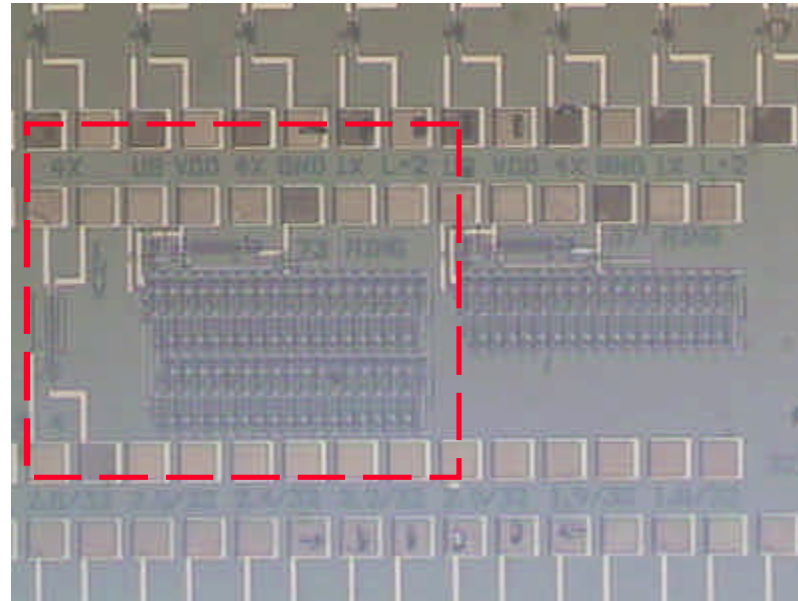
T = period of oscillation



73 Stage Ring at 5V, $t_d = 0.712\text{ns}$



73 Stage Ring at 6V, $t_d = 0.228\text{ns}$



TE03 INSTRUCTIONS

- Move to manual probe station.
- Place wafer on stage and apply vacuum.
- Move stage such that Ring Oscillator is in the field of view.
- Move manual probes to make contact with the “GND”, “OUT”, and “VDD” probe pads.
- Use a DC power supply to supply 5 V to VDD, and 0 V to GND.
- Use the oscilloscope to view & measure the frequency.
- 17, 37 or 73 stages.

**Output:**

Open Folder name: Textronixoutput on desktop

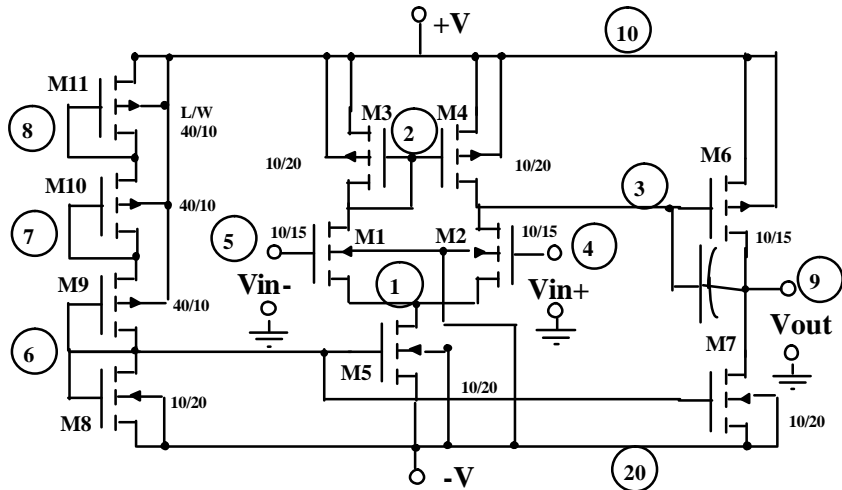
Open Program 7470 (DOS)

Click Acquire; Request address number 7

Data will download to computer and plot will update

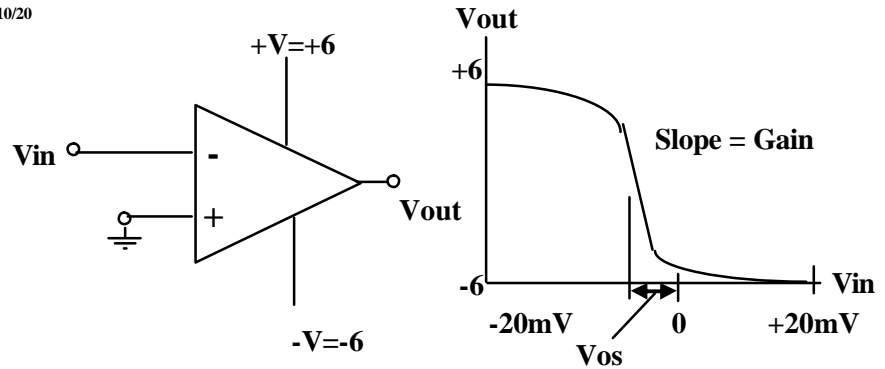
Print plot or save as: filename.gif

OPERATIONAL AMPLIFIER



p-well CMOS

dimensions
L/W
($\mu\text{m}/\mu\text{m}$)



Set up the HP 4145 to sweep the V_{in} from -20 mV to $+20\text{ mV}$ in 0.001V steps. Measure Gain and Input offset voltage.

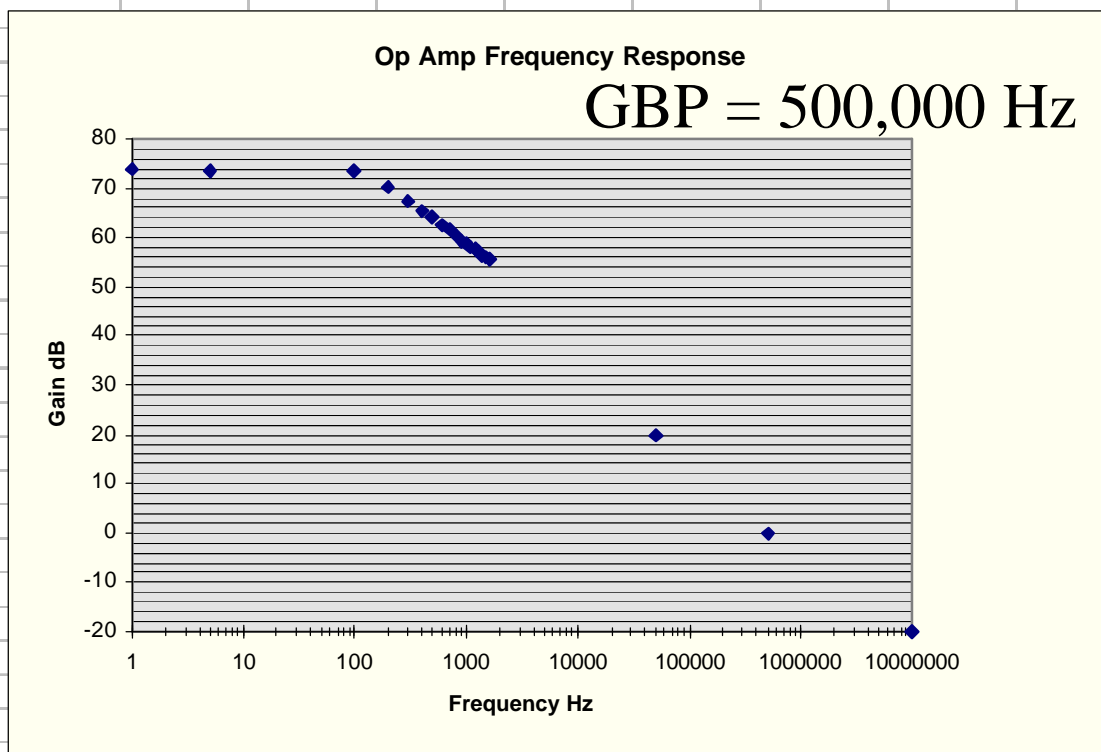
AC TEST RESULTS

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MICROELECTRONIC ENGINEERING

LFF OPAMP.XLS FILE3B

LOT F960319 OPAMP TEST RESULTS - 1-29-97

Frequency hZ	Gain dB	Vout V	Vin mV
1	73.9794	10	2
5	73.53387	9.5	2
100	73.33036	9.28	2
200	70.31748	6.56	2
300	67.53154	4.76	2
400	65.48316	3.76	2
500	63.97314	3.16	2
600	62.41148	2.64	2
700	61.51094	2.38	2
800	60.34067	2.08	2
900	59.46256	1.88	2
1000	58.68997	1.72	2
1100	58.0618	1.6	2
1200	57.50123	1.5	2
1300	57.14665	1.44	2
1400	56.5215	1.34	2
1500	56.1236	1.28	2
1600	55.56303	1.2	2
50000	20	0.02	2
500000	0	0.002	2
1000000	-20	0.0002	2



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TE04

5/04/06
8:38:46

MESA
Instruction Group Inquiry

IGMSINQ S36801
QPADEV000W RIT

Type information. Then Enter.
1=Display document, 5=Display detail

Plant : RIT
Instruction group . . : TE04 WAFER MAP OF VT
Revision : _____

Opt Subgroup Text

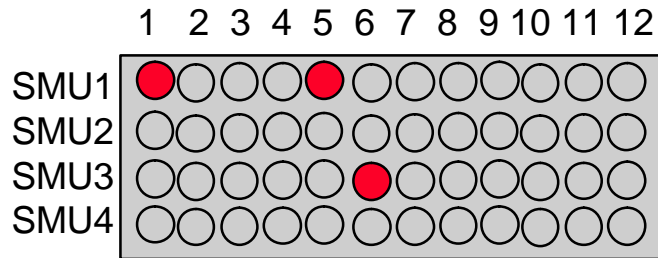
- 1.0 Take data for wafer map of Vt, test all transistors
(see wafermap.pps)
- 2.0 Compute +/- 10%, 20%, 30%, 40% of target:
 CMOS Targets are +/-1.0, PMOS Target is -2.0 volts
 Record data row by row, each character in a row
 represents a different column (die), the value will be
 5 if within 10% of target
 4 if between -20% and -10% of target
 6 if between +10% and +20% of target
 3 if between -30% and -20% of target, etc.

Bottom

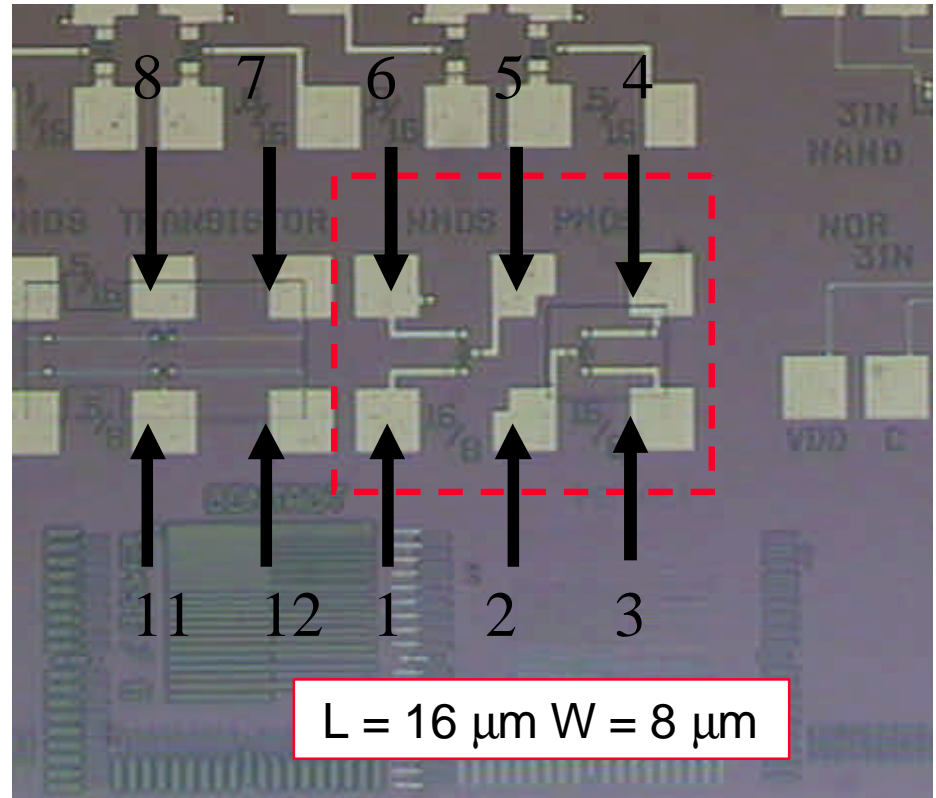
F3=Exit F4=Prompt F5=Refresh F10=View 2 F12=Cancel

NMOS ID-VGS

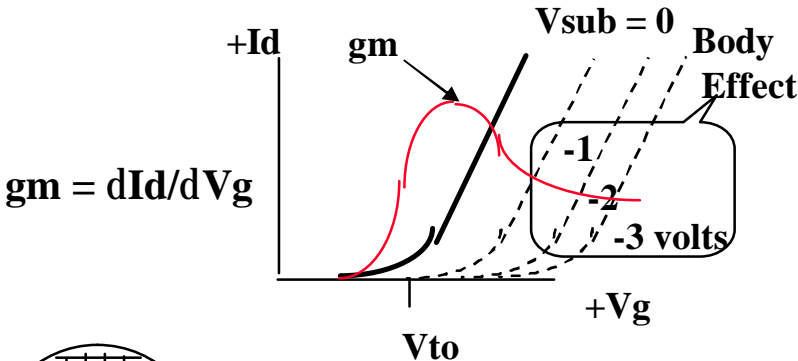
Test Name: NVT



Switch matrix



L = 16 μm W = 8 μm

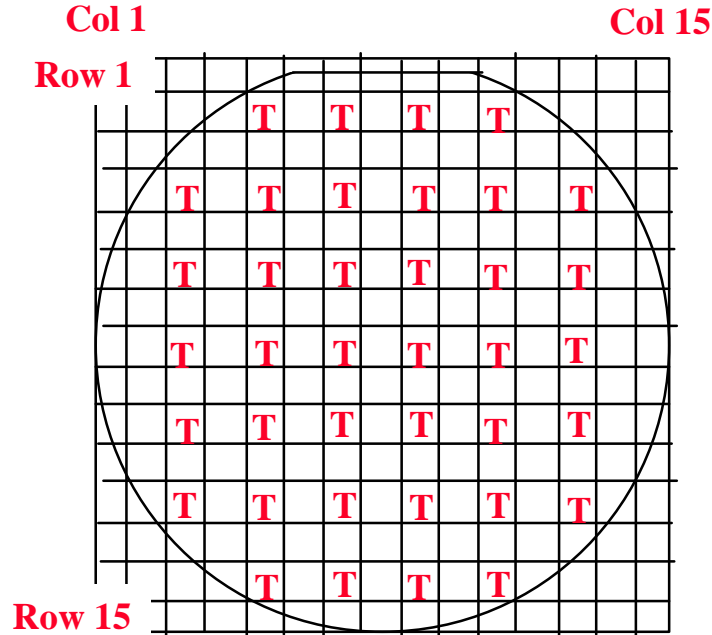


Extract: Vto

SMU1	Vgs	Sweep 0- 5 V, 101 steps
SMU2		
SMU3	Com	Vs = 0
SMU4		

TE04 INSTRUCTIONS – WAFER MAP

- Measure V_t for NFET on each die in a 15 x 15 array centered on the wafer.
- Record information in MESA and on an excel spreadsheet using the Binning described in below.



Example Data

```

nmos Vt target +1
0000000000000000
0000505050500000
0000000000000000
0050605070507000
0000000000000000
0040403040303000
0000000000000000
0040404040404000
0000000000000000
0040504050906000
0000000000000000
0050506060607000
0000000000000000
0000505050500000
0000000000000000
    
```

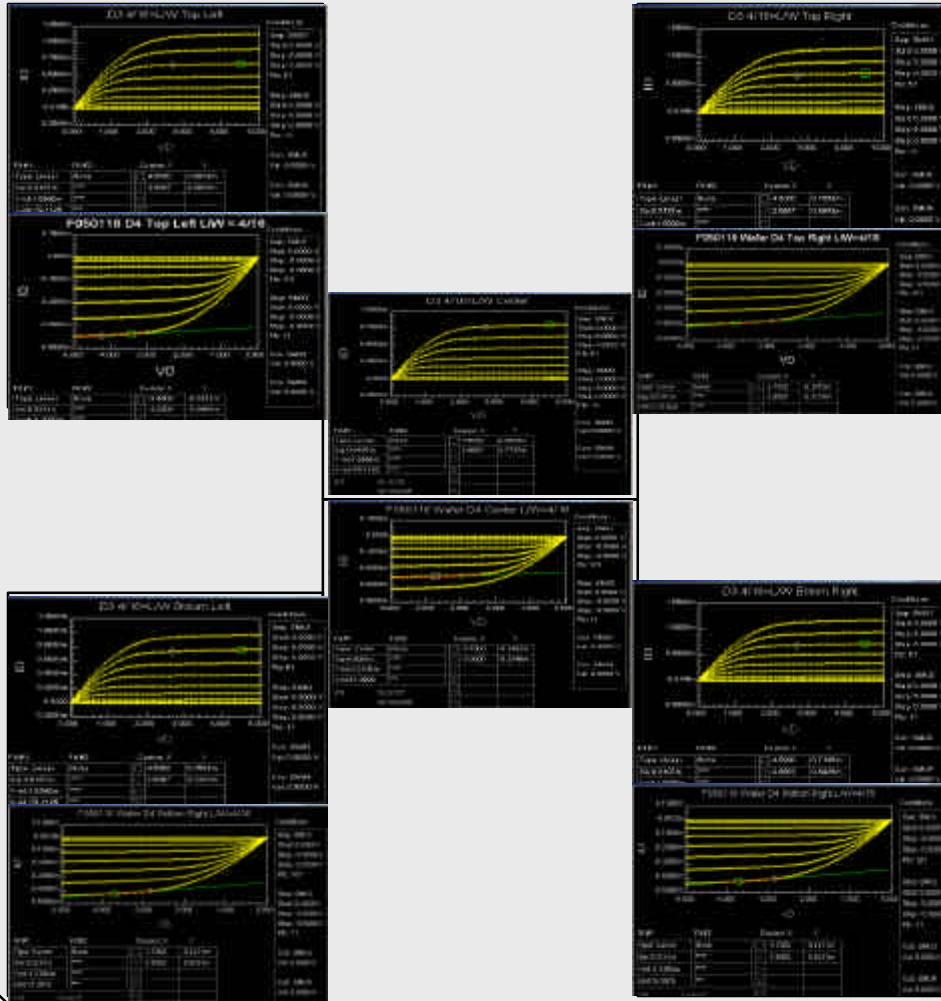
Code

- 0 no die
- 1 value<(Target-70%)
- 2 (Target-70%)<value<(Target-50%)
- 3 (Target-50%)<value<(Target-30%)
- 4 (Target-30%)<value<(Target-10%)
- 5 (Target-10%)<value<(Target+10%)
- 6 (Target+10%)<value<(Target+30%)
- 7 (Target+30%)<value<(Target+50%)
- 8 (Target+50%)<value<(Target+70%)
- 9 (Target+70%)<value

Lot Number = F050118

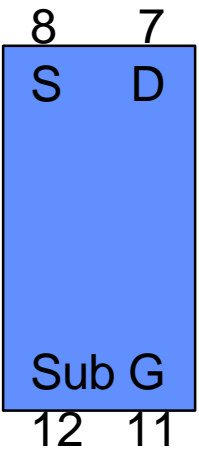
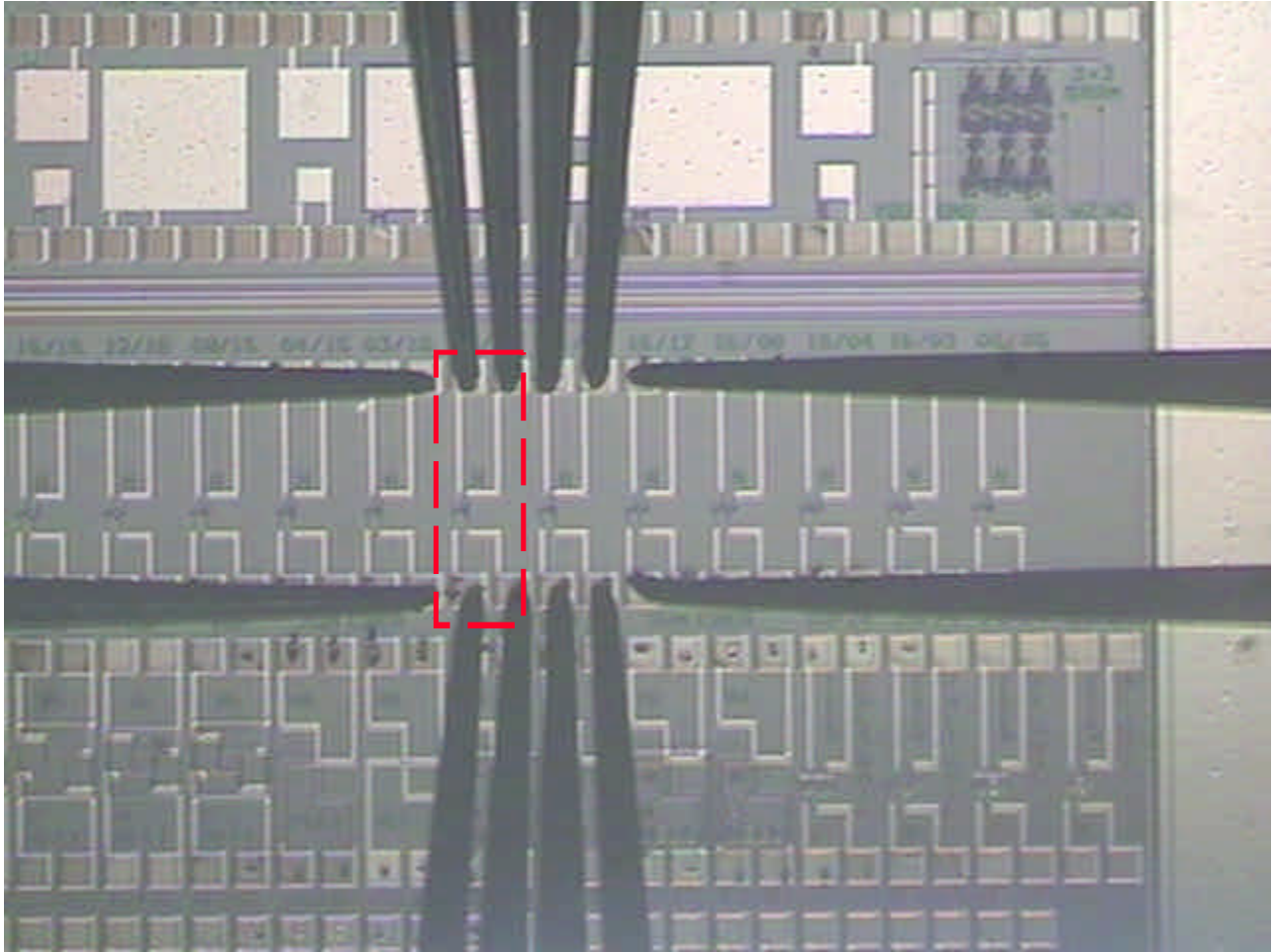
Wafer Number = D3

Family of curves for L=4 μ m MOSFETs



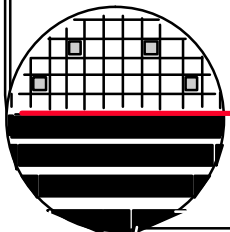
2 μ m/32 μ m L/W NMOS AND PMOS

SMFL CMOS DAC TEST STRUCTURES

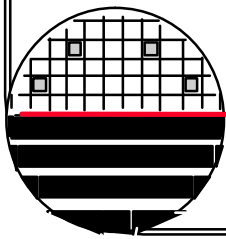
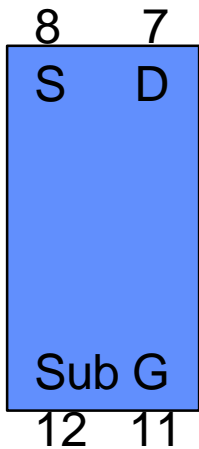
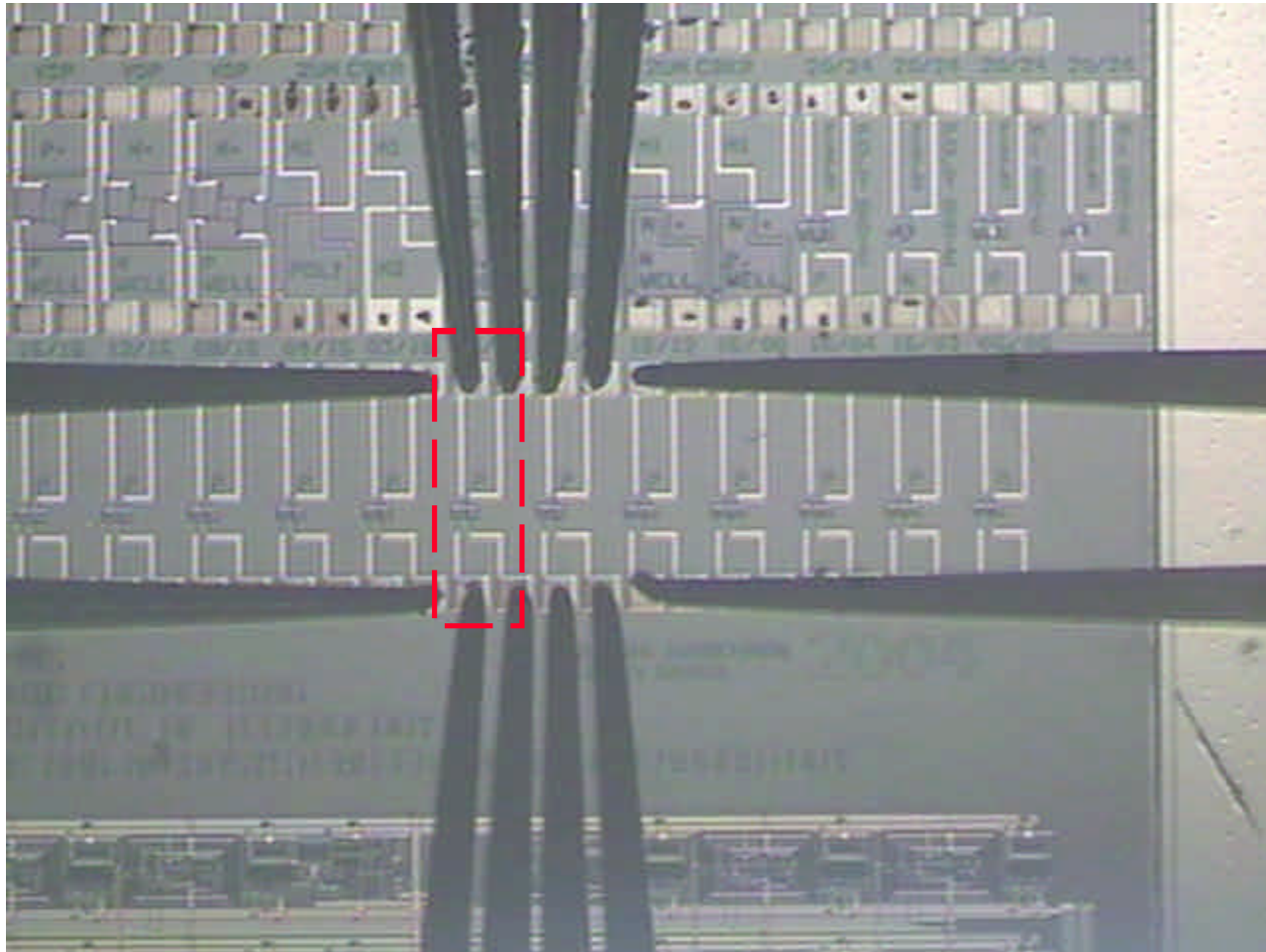


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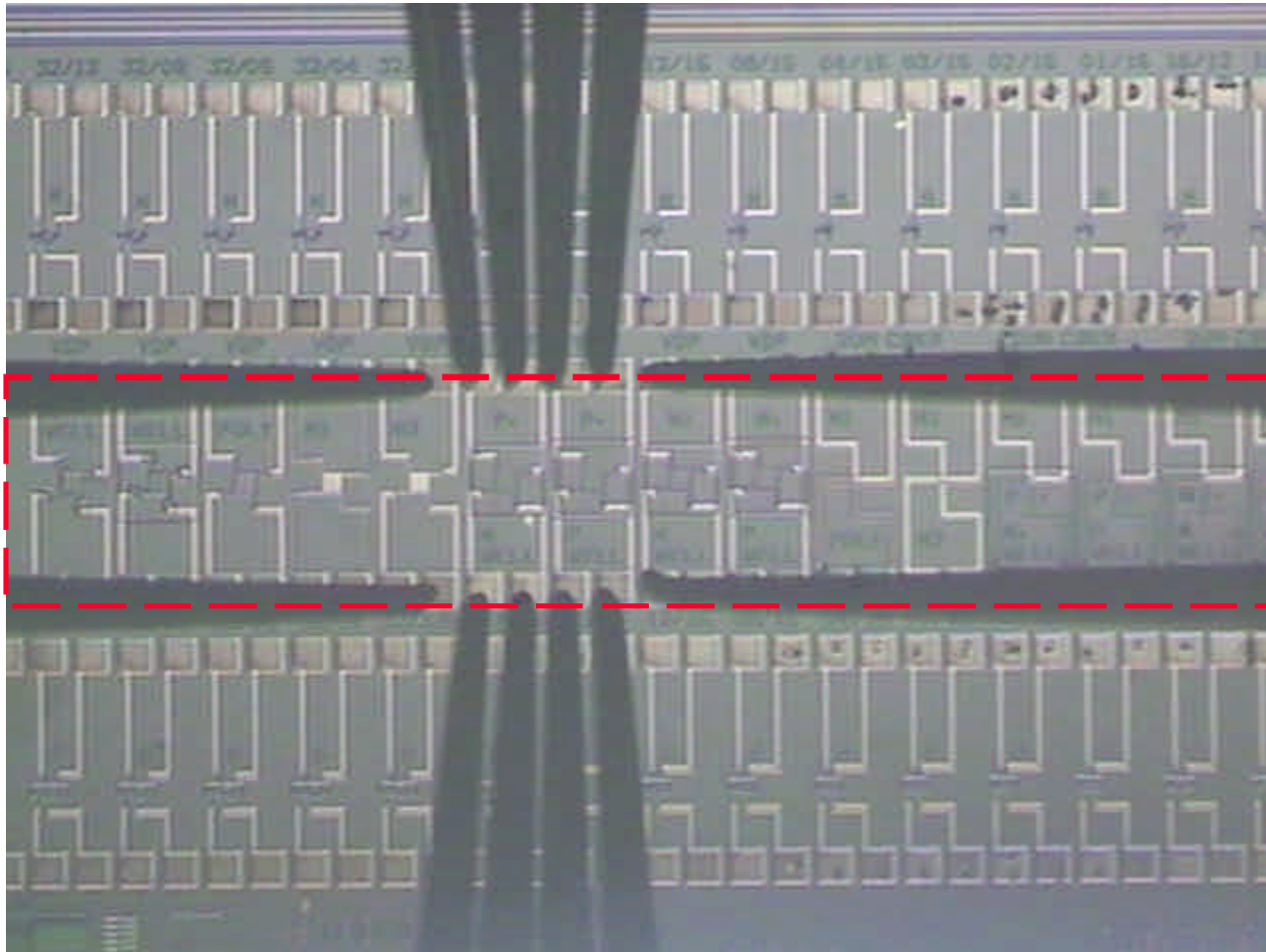
2/16 L/W NMOS FET



SMFL CMOS DAC TEST STRUCTURES

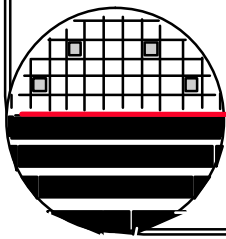


SMFL CMOS DAC TEST STRUCTURES

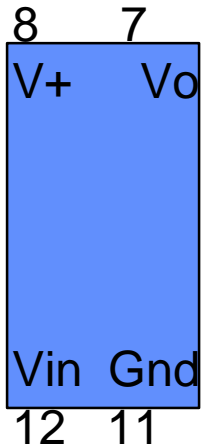


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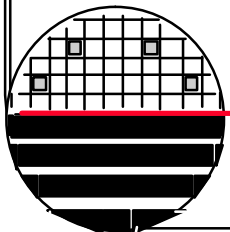
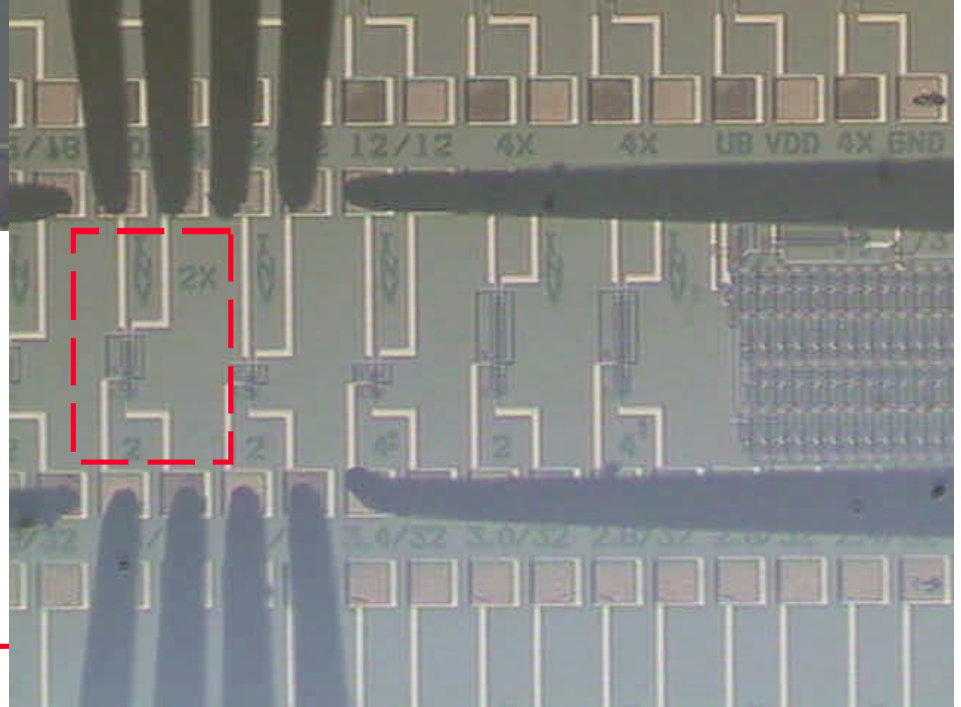
VAN DER PAUW AND CBKR



SMFL CMOS DAC TEST STRUCTURES

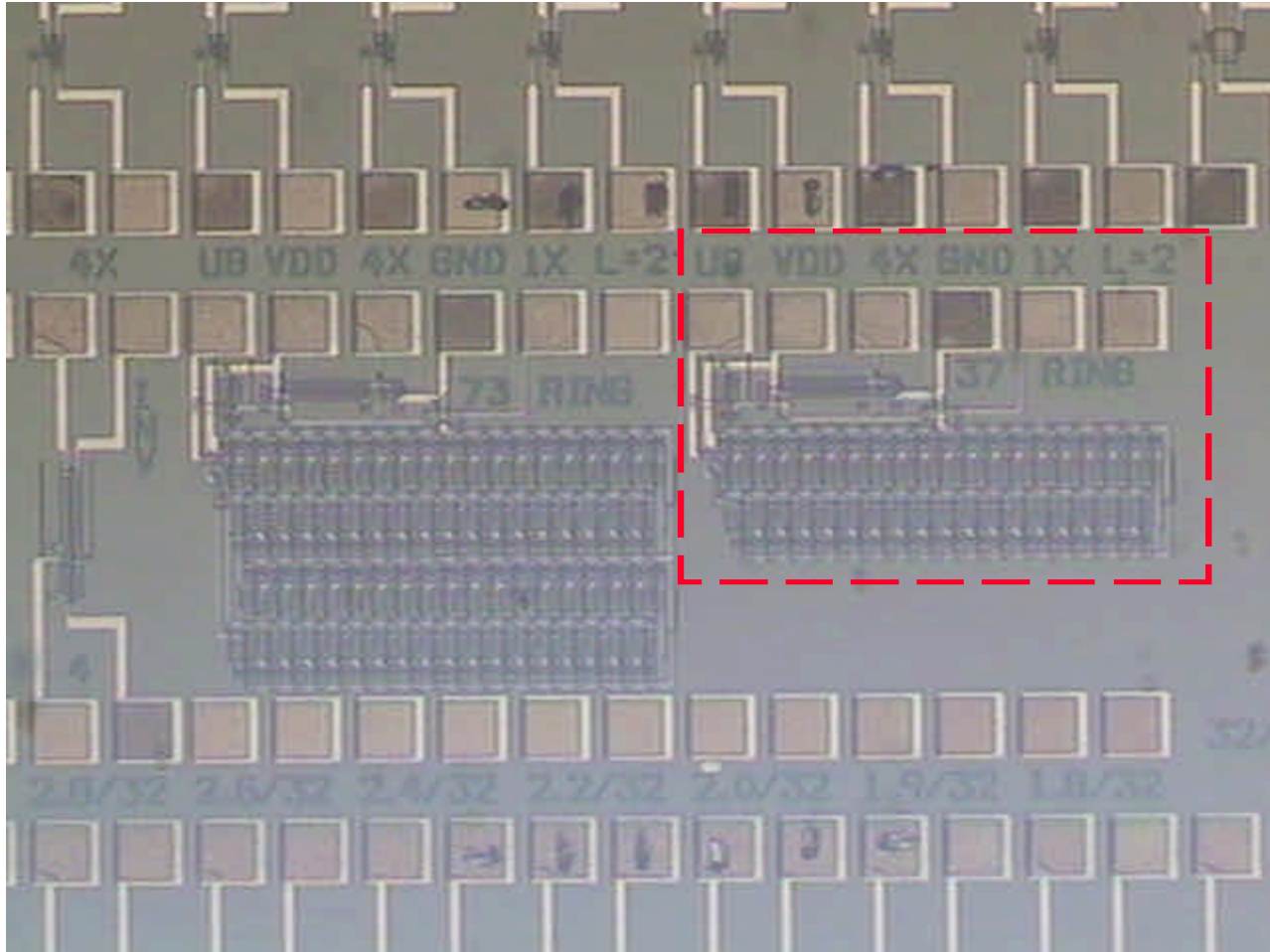


L = 2um INVERTERS



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SMFL CMOS DAC TEST STRUCTURES



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37 STAGE 2μm RING OSCILLATOR